

Rhodium Pyrazolate Complexes as Potential CVD Precursors

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Supplementary Material

CVD Studies: Experimental Details

Complexes **1-5** were assessed for use as potential MOCVD precursors. Initial investigations of their volatility and thermal stability were carried out in sealed systems under N₂ both at 1 atm. and at reduced pressure (0.1 torr). None of the complexes were found to be volatile at atmospheric pressure. Complexes **2** and **4** both decomposed in the solid state at temperatures under 100 °C under 1 atmosphere of N₂ and they also showed no evidence of sublimation before decomposing under vacuum.

Complexes **1**, **4**, and **5** are all volatile under reduced pressures near their melting points. **1** sublimates at ca. 154 °C (0.1 torr), which is in the melting point range under 1 atmosphere of N₂. The melting of **1** (1 atm. N₂) is accompanied by a darkening of the liquid however its decomposition temperature could not be determined reliably by this method. **3** sublimates at ca. 100 °C under reduced pressure and melted at 103-105 °C under 1 atm. under N₂. A transition of the melt from bright yellow to black occurs at 182-184 °C and this was taken as the decomposition temperature. **5** has a slightly higher melting point than **3** (1 atm. N₂), but sublimates at the same temperature (ca. 100 °C). Analysis of the sublimate revealed that sublimation of **5** under reduced pressure results in loss of PMe₃ and formation of **3**.

Films were deposited in a horizontal hot-wall CVD reactor comprising a tube furnace surrounding a quartz tube as the deposition chamber. All other parts of the apparatus were constructed of stainless steel and utilized ¼" VCR fittings for interconnects. The sample path was kept warm with insulated heating tape covered with glass wool. High purity argon (99.999% Matheson) and ultra-high purity hydrogen (99.9999% Praxair) were used as the carrier gases regulated with a mass flow controller (range 1-50 sccm) and a rotary-vane vacuum pump (< 0.05 torr) was used to provide reduced pressure. 400 nm SiO₂/Si(100) wafers were used as substrates. In a typical experiment a saturator was charged with 50-100 mg of a complex under a nitrogen atmosphere.

The reactor was then pumped down under vacuum and purged with argon/hydrogen several times before a final evacuation. The carrier gas was then allowed to flow through the system (5-10 sccm) while the hot zone of the reactor system was gradually heated. Once thermal equilibrium was achieved at the desired temperature, the precursor was heated to initiate evaporation. The time taken for film growth was typically 30-120 min. before the precursor flow was stopped and the reactor allowed to cool to room temperature.

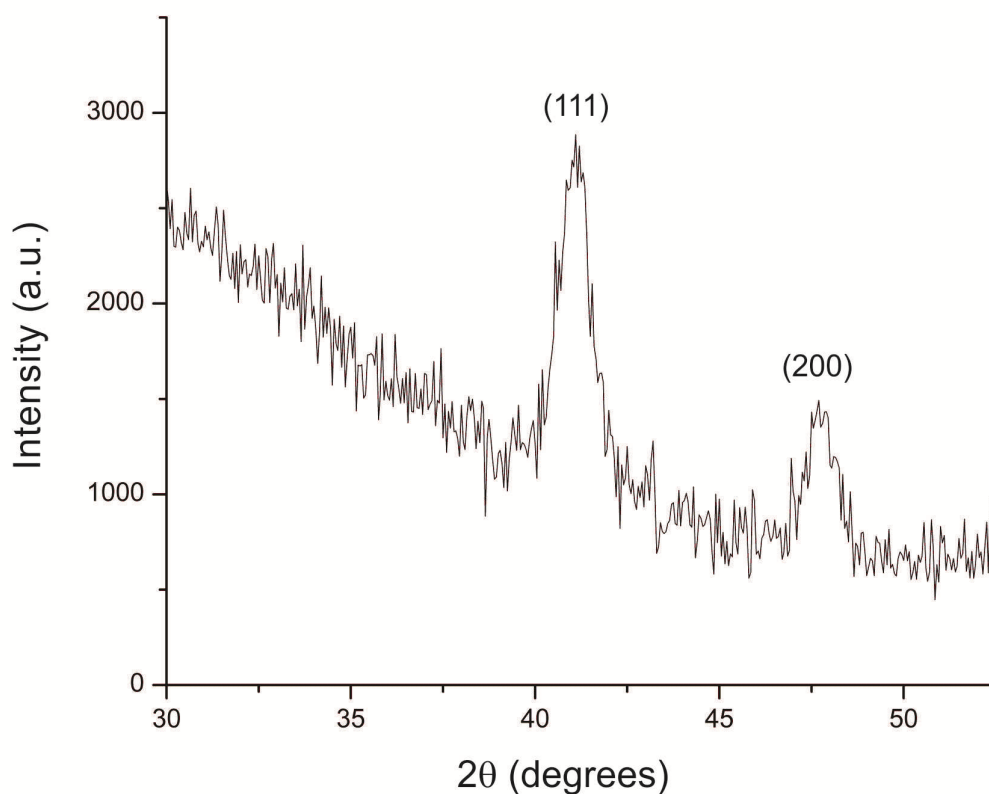
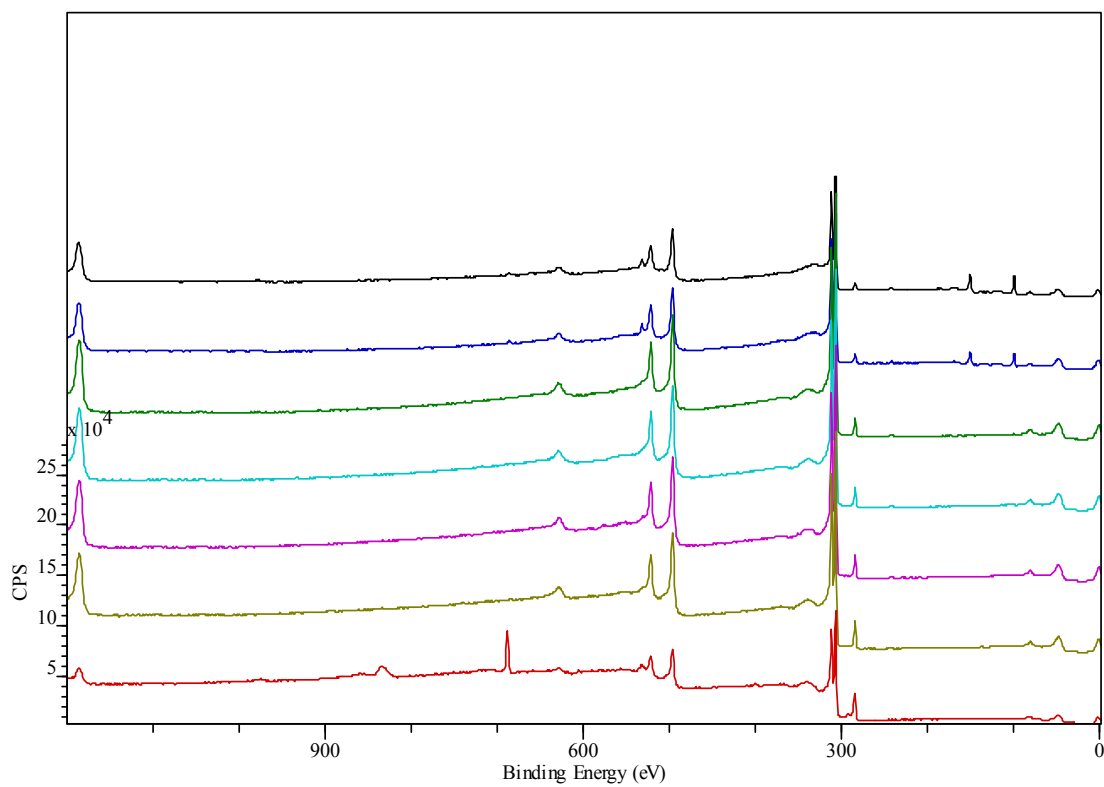


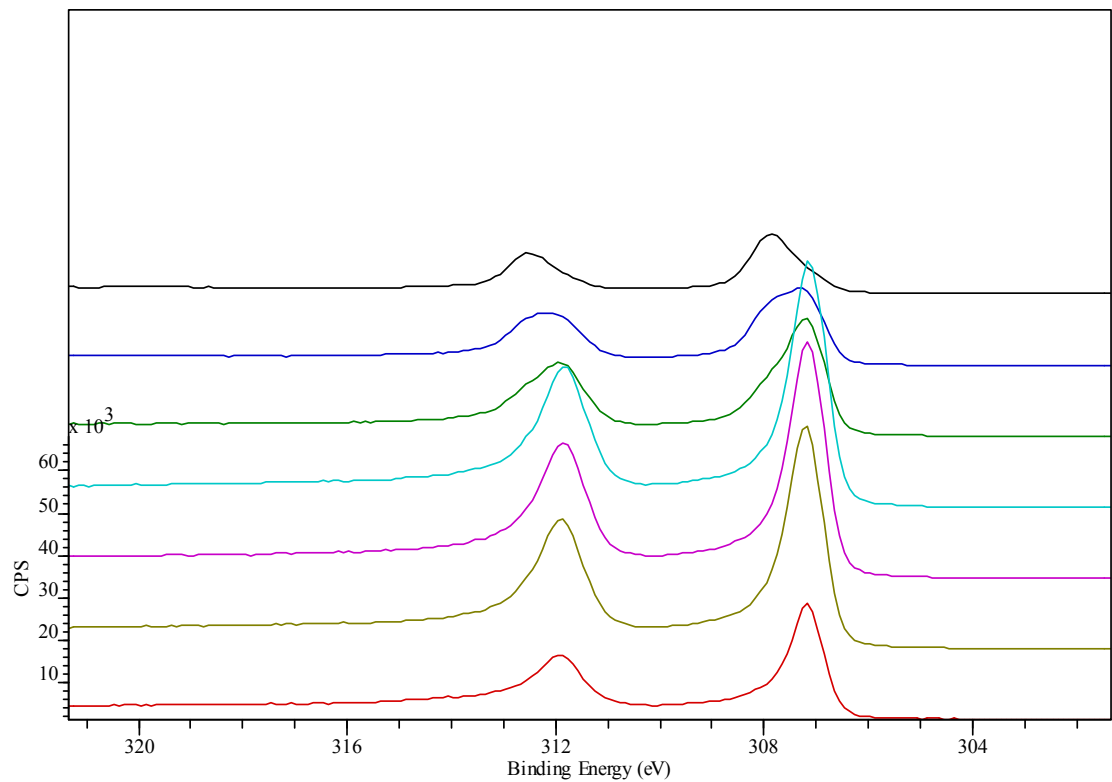
Figure S1. Low angle XRD of film grown from **1** using Ar carrier gas (flow rate 5 sccm, pressure 0.3 torr), deposition temperature of 500 °C for 60 minutes.

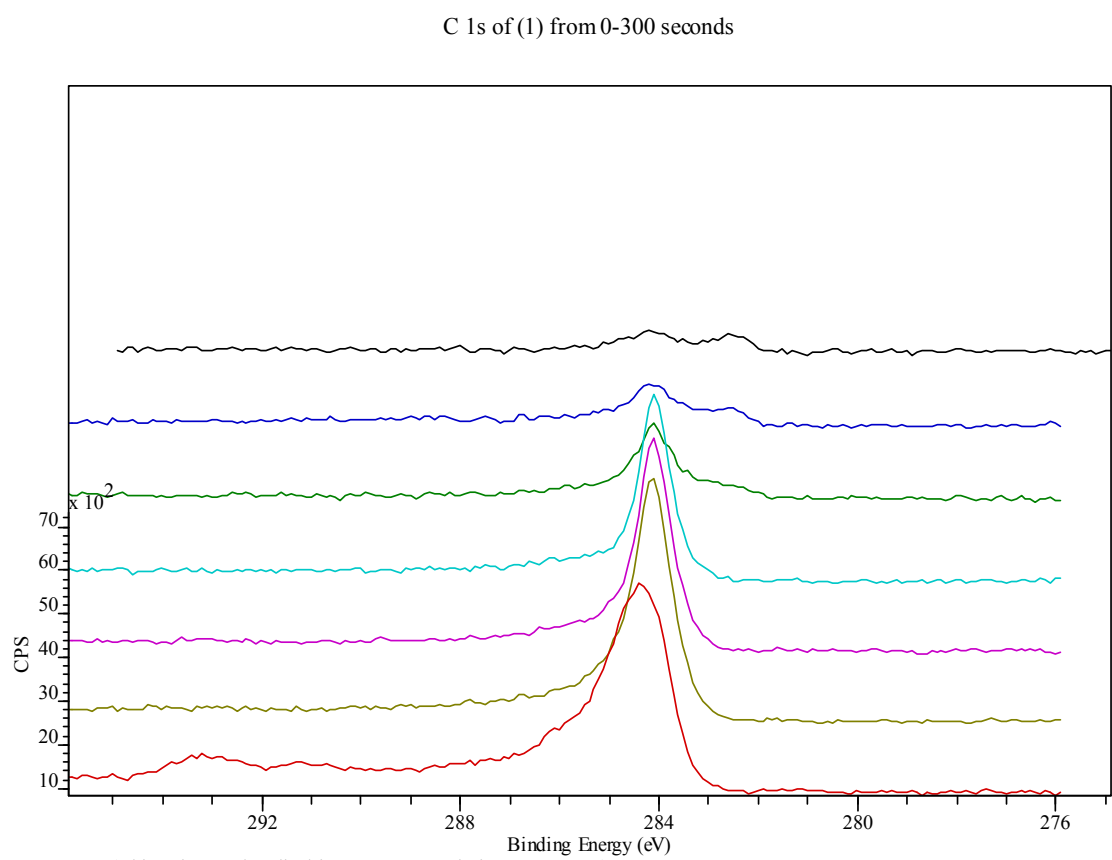
XPS spectroscopy of $[\text{Rh}(\eta^2\text{-C}_2\text{H}_4)_2(\mu\text{-3,5-(CF}_3)_2\text{-Pz})]_2$ (**1**) using hydrogen carrier gas

surveys of (**1**) from 0-300 seconds

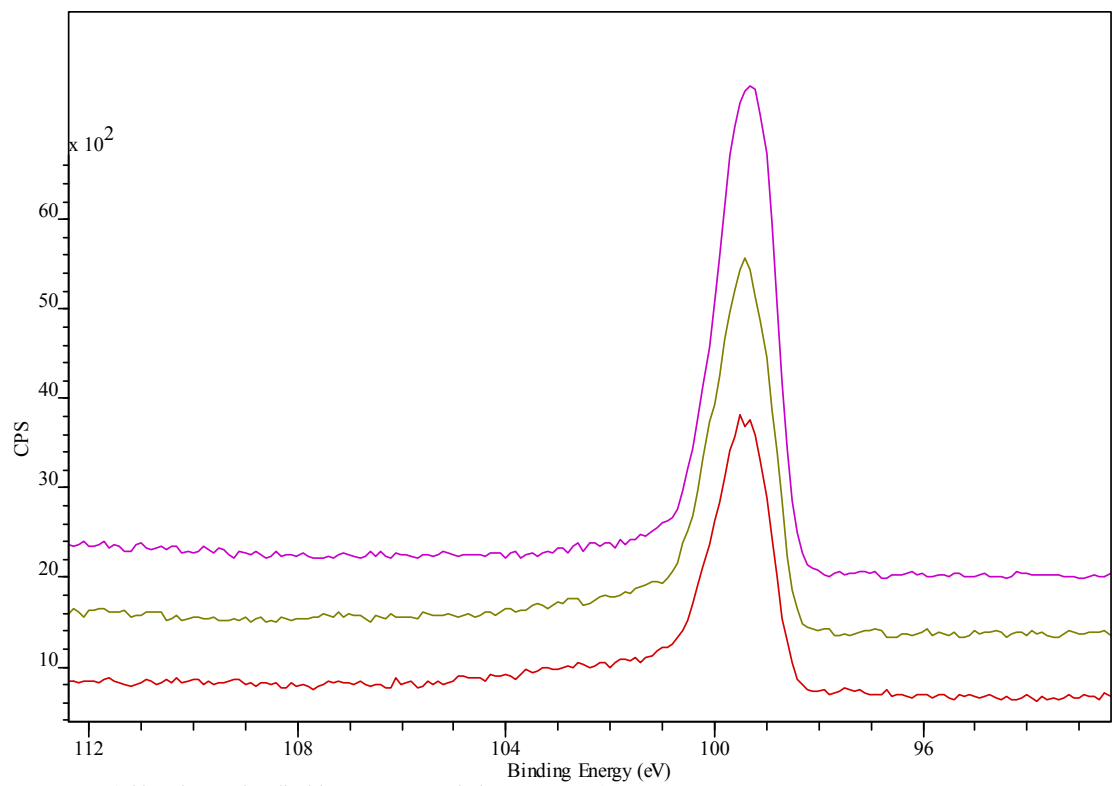


Rh 3d of (1) from 0-300 seconds

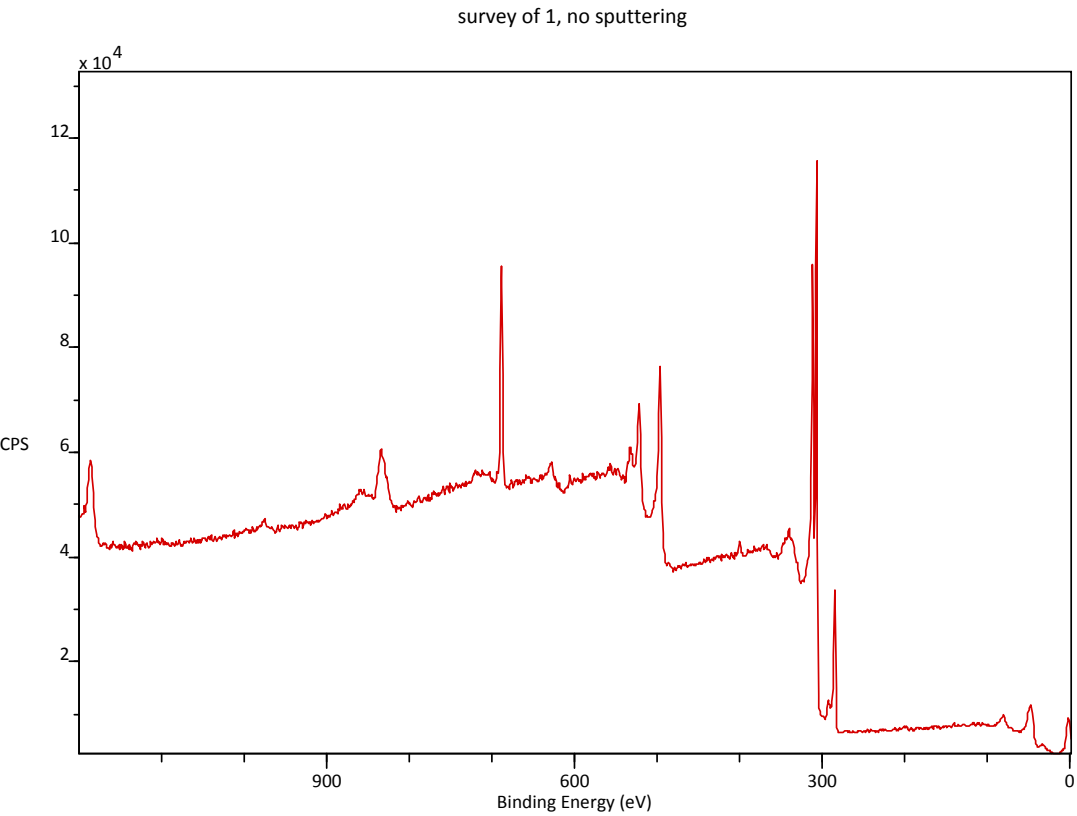


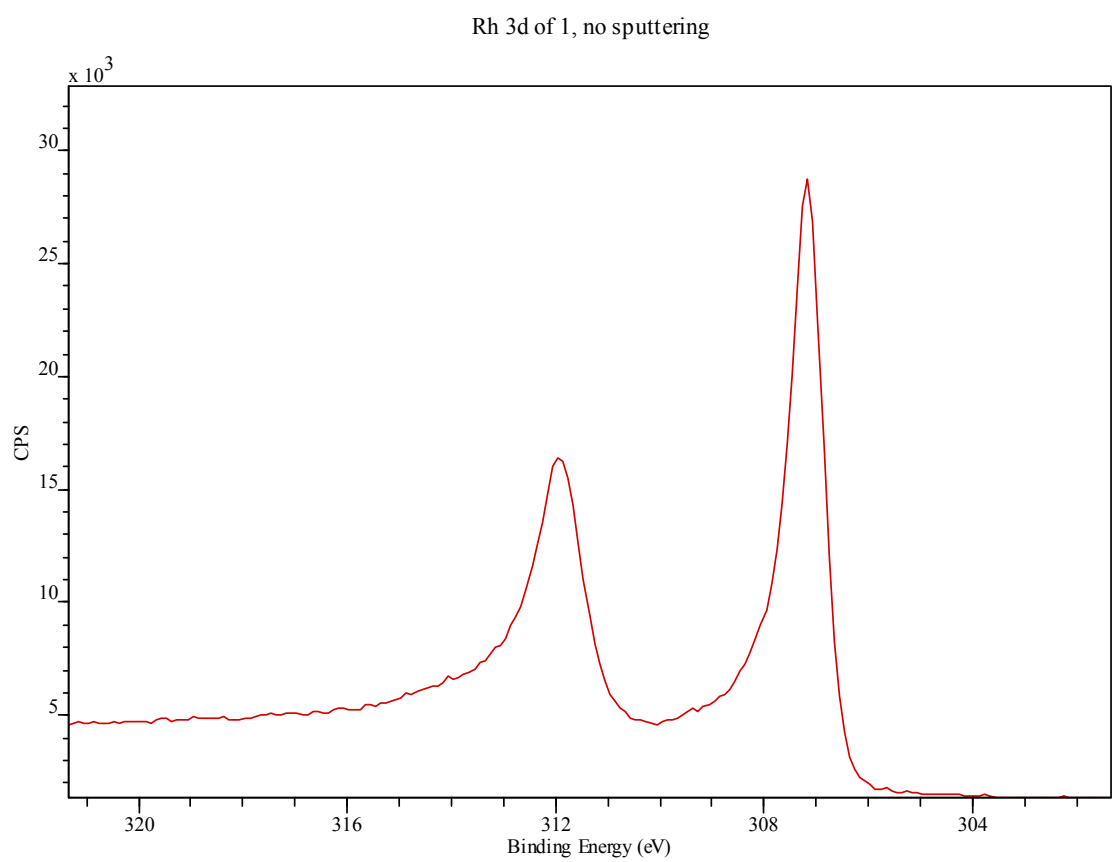


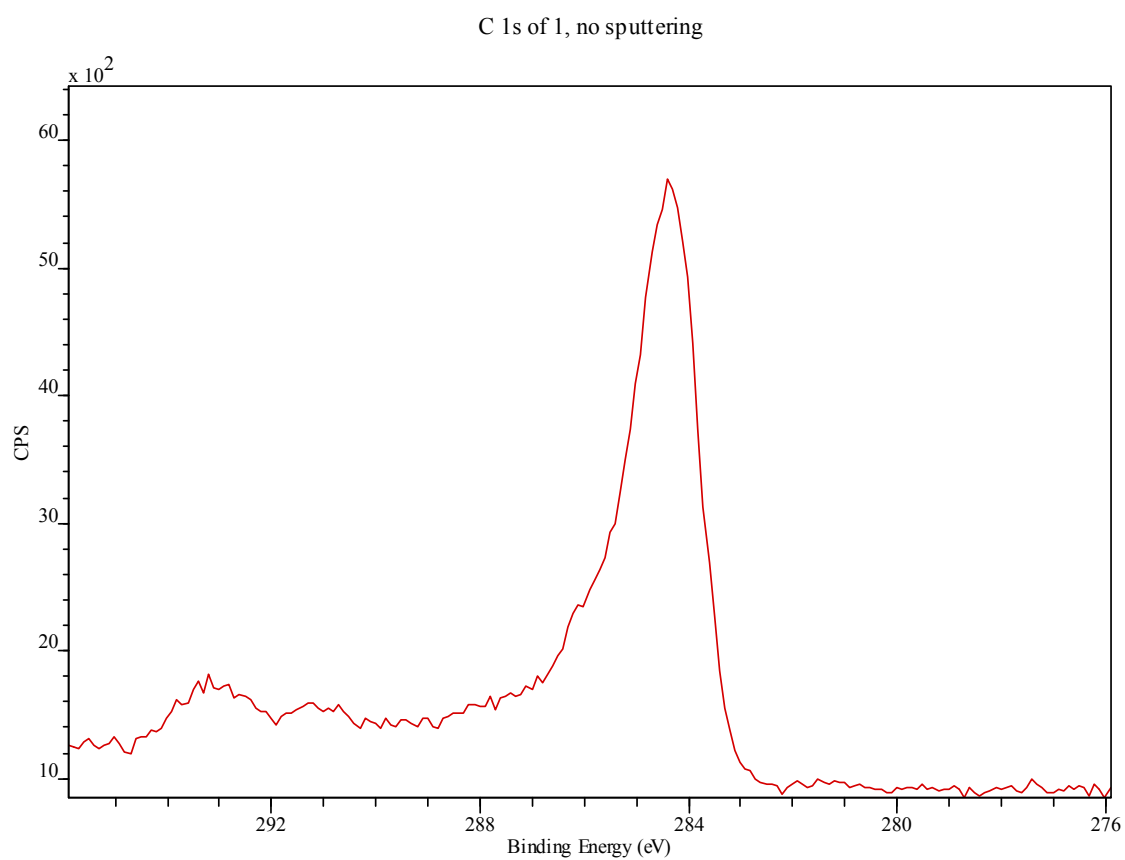
Si 2p of (1) from 210-300 seconds

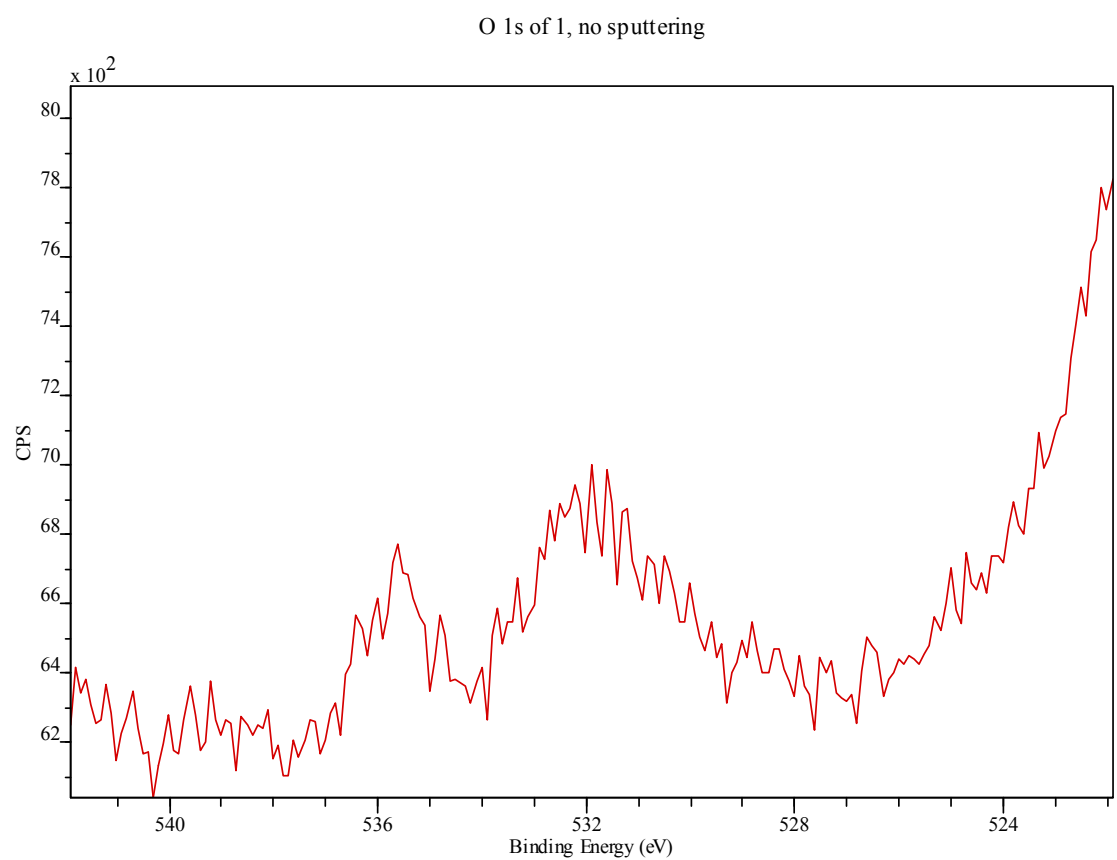


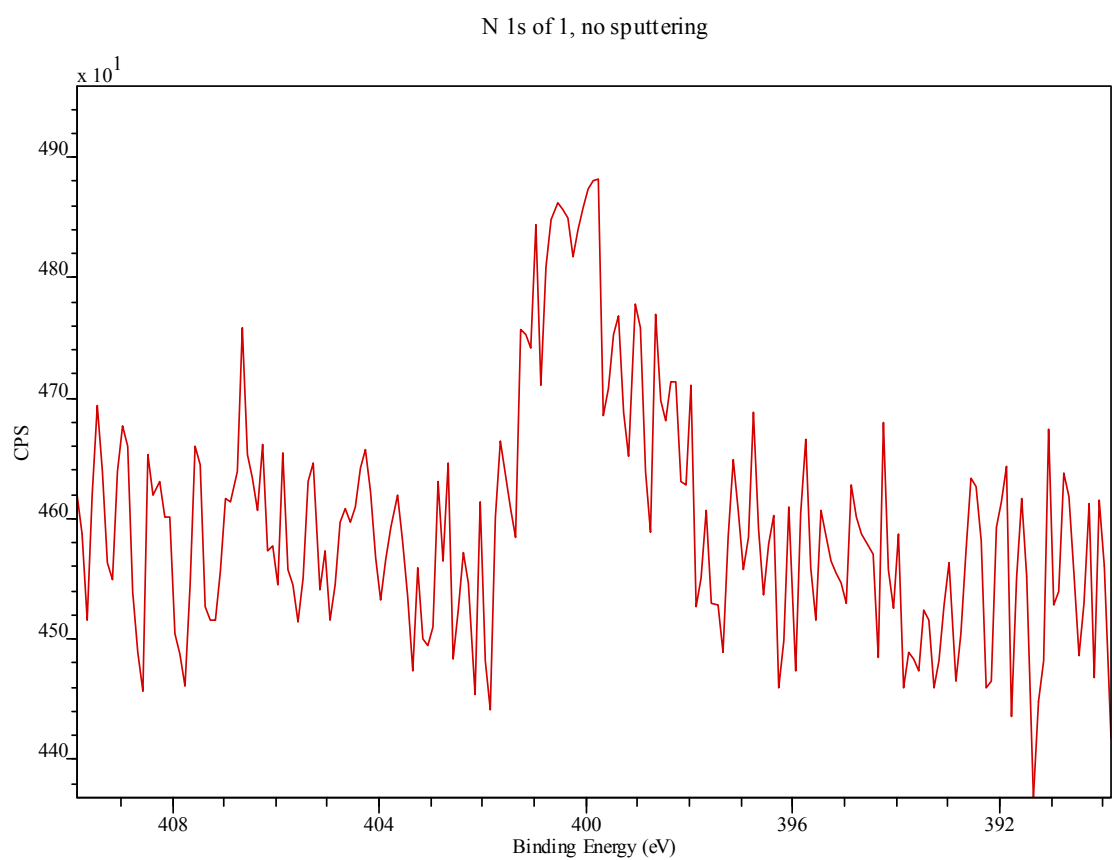
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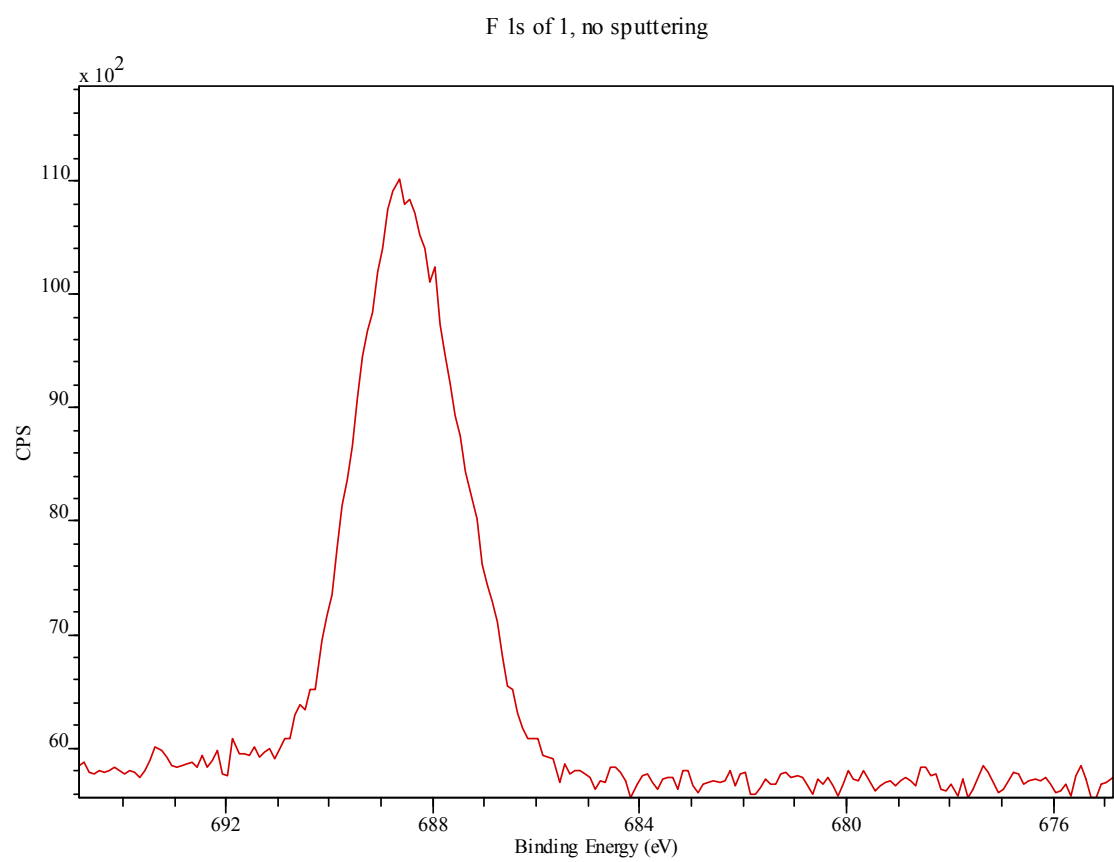




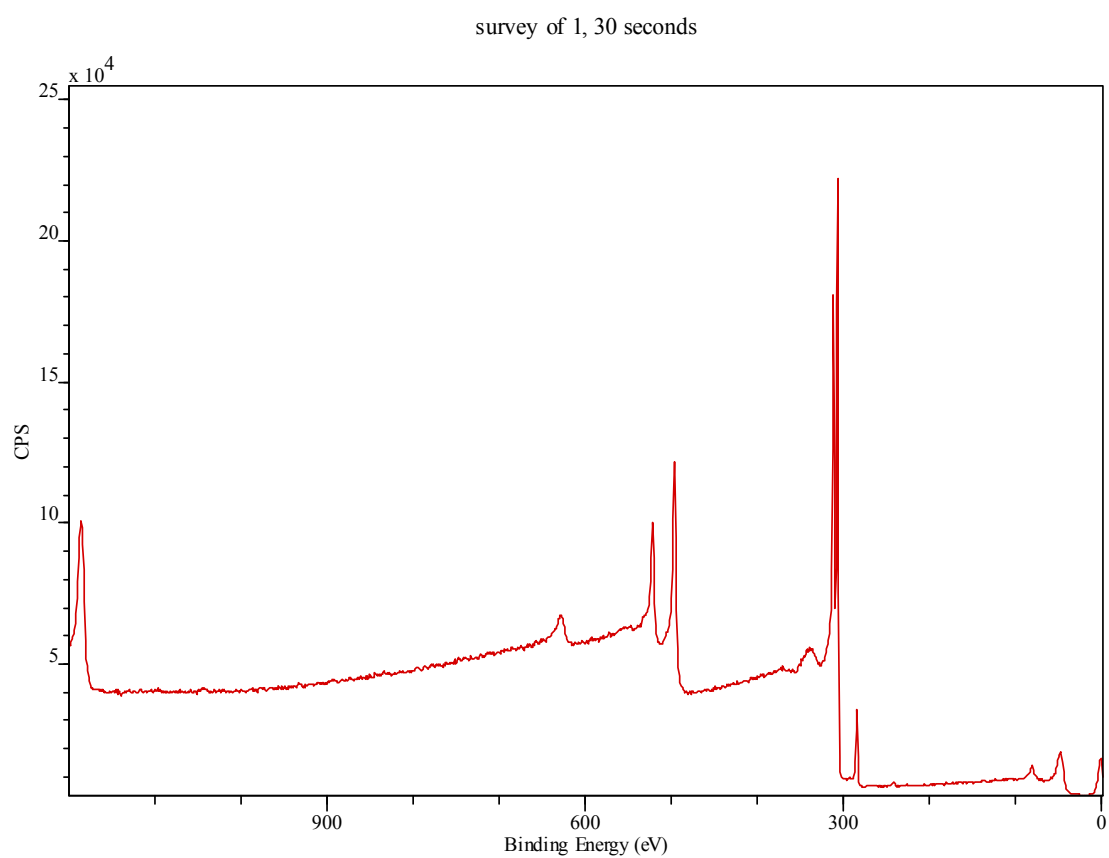


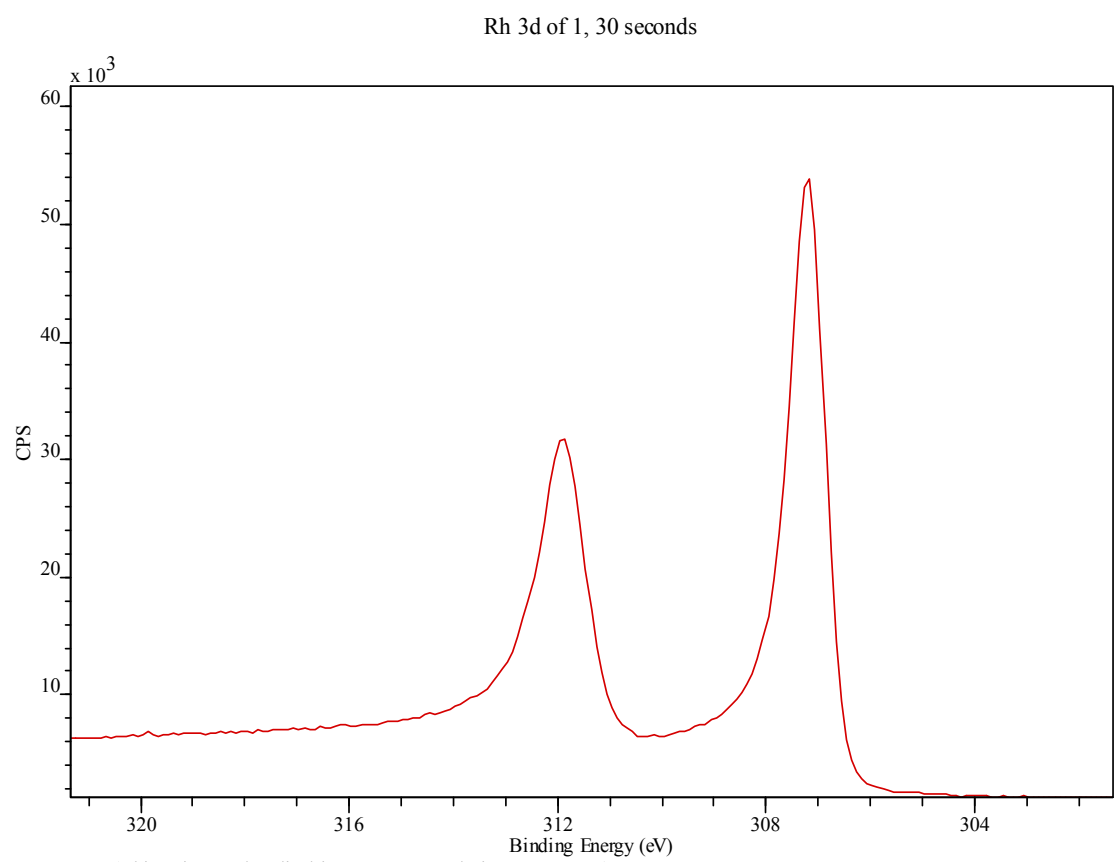


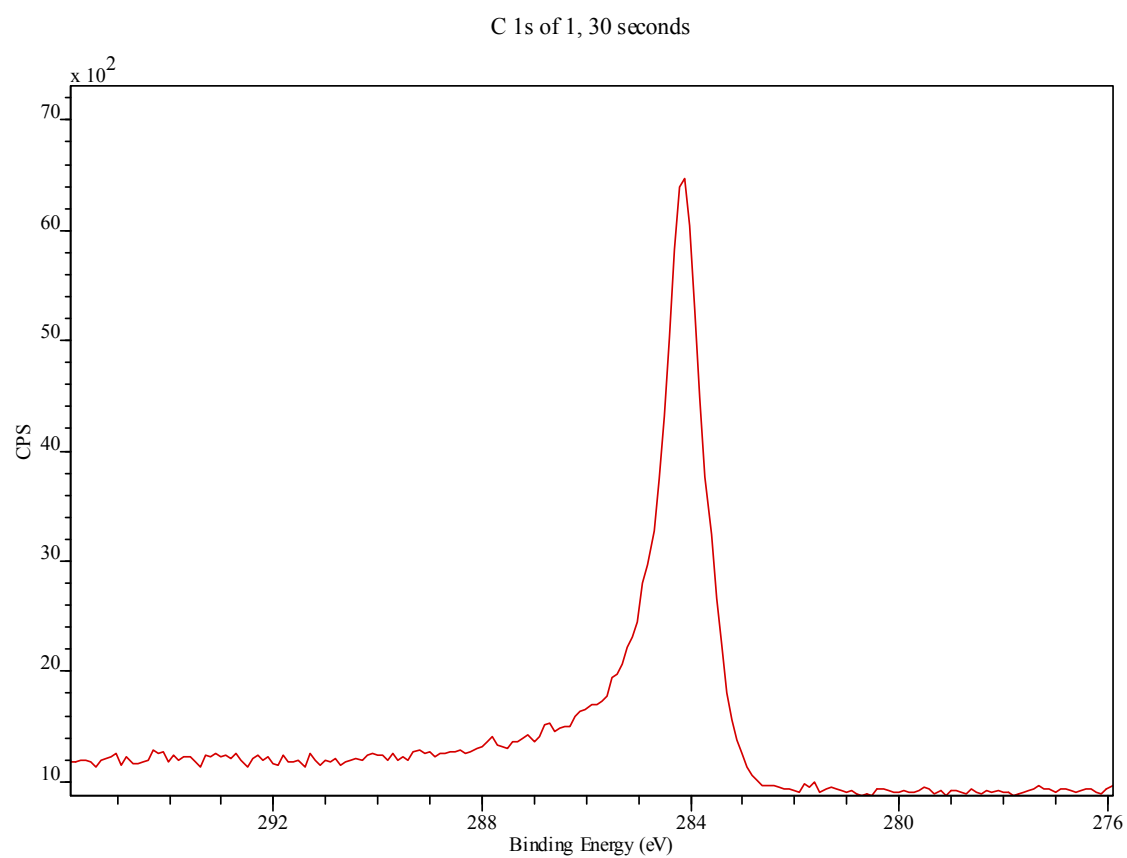




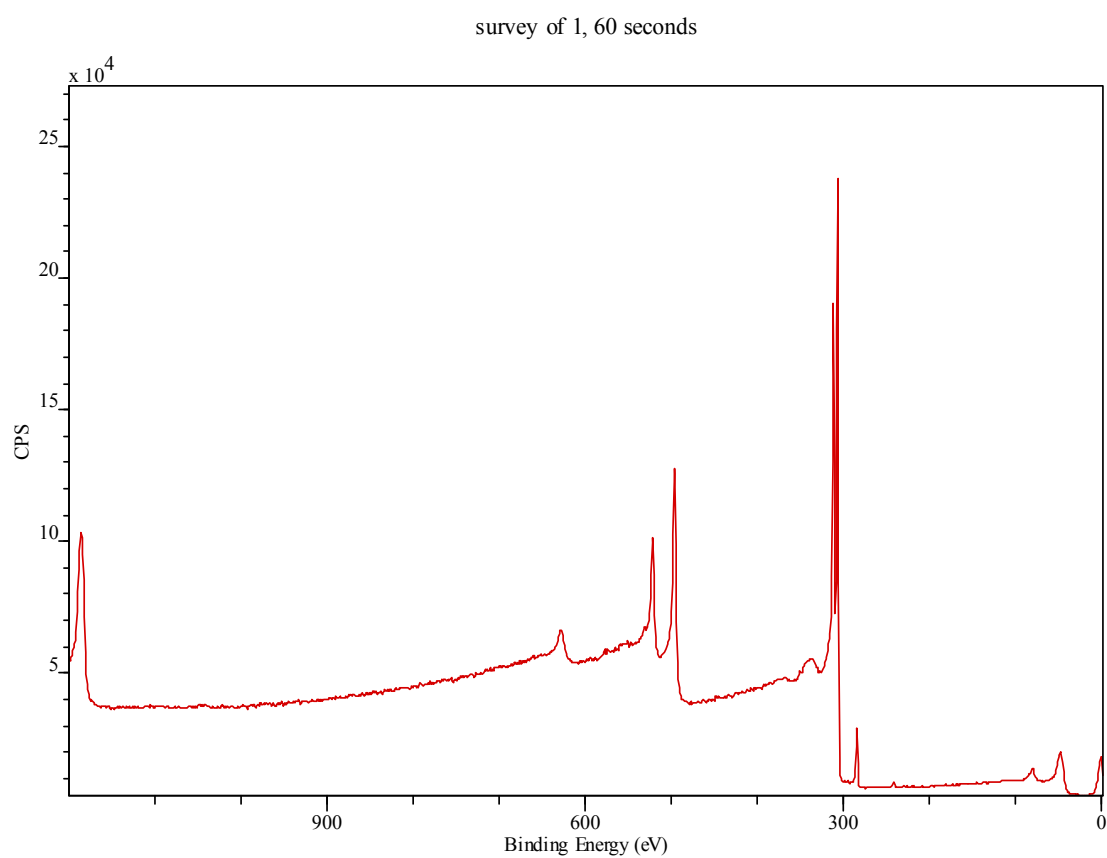
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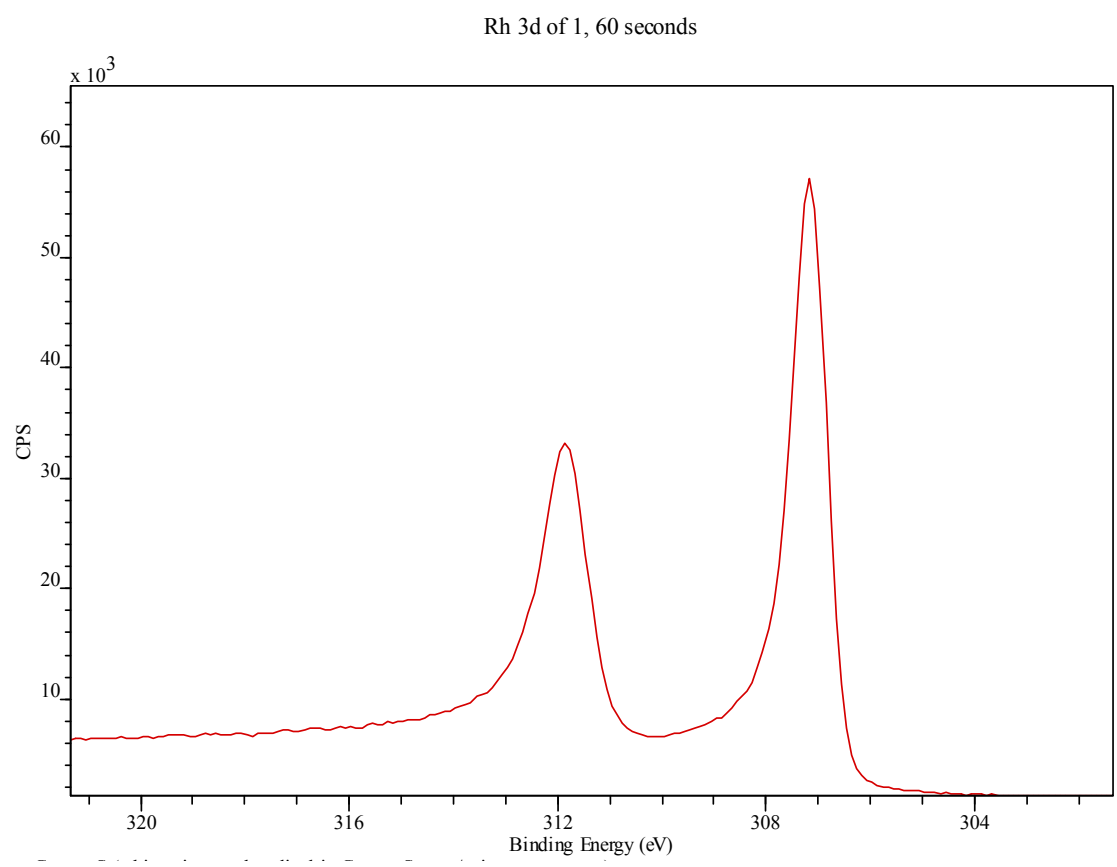


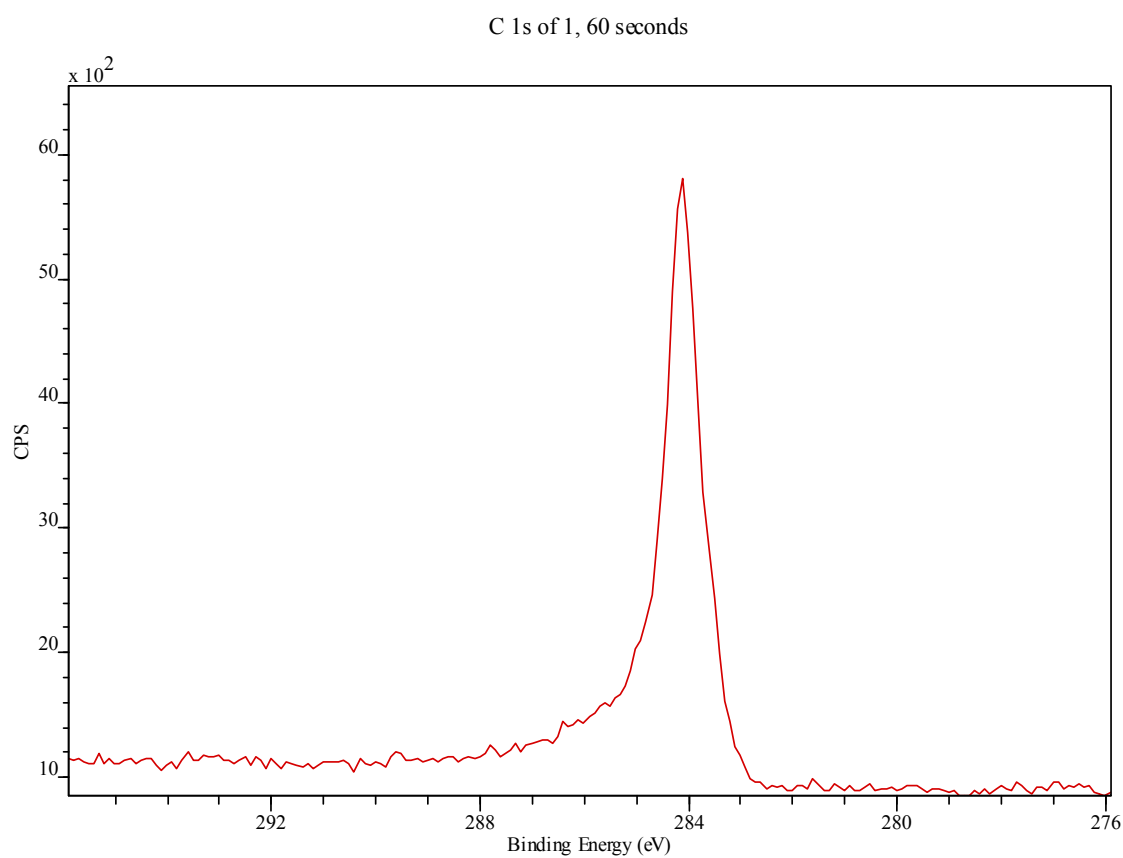




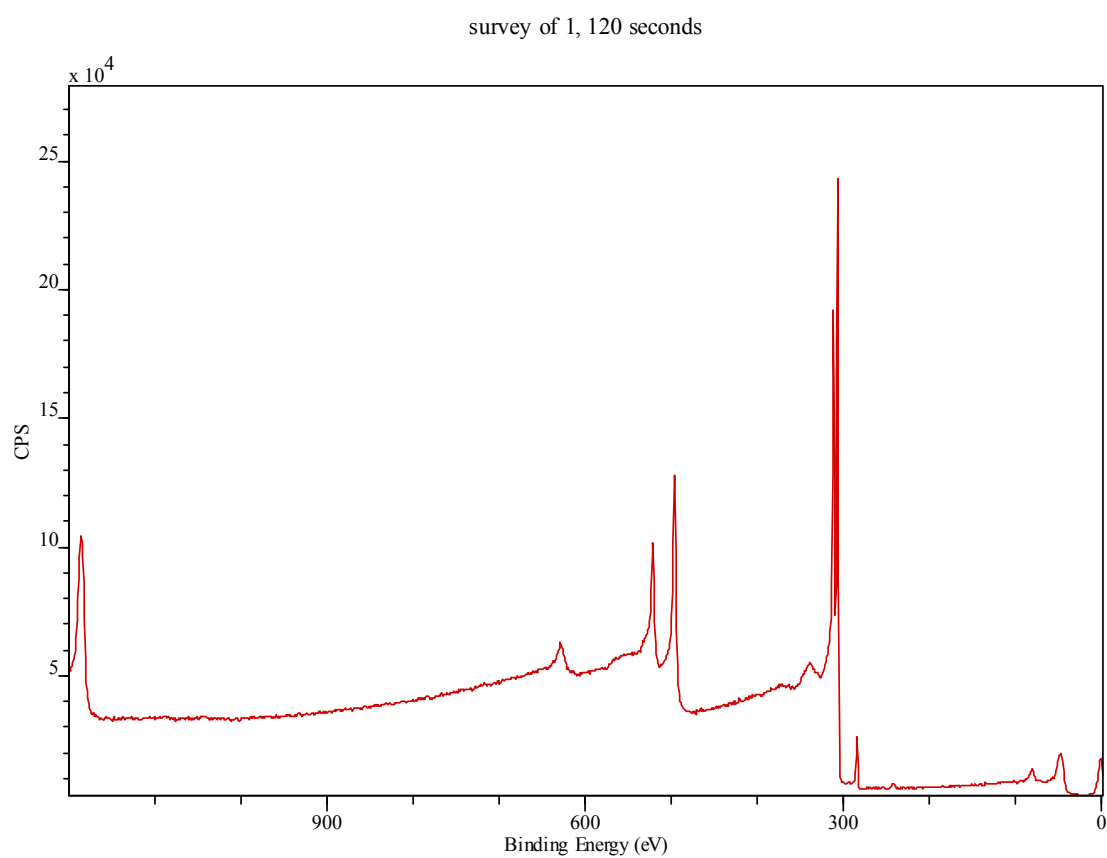
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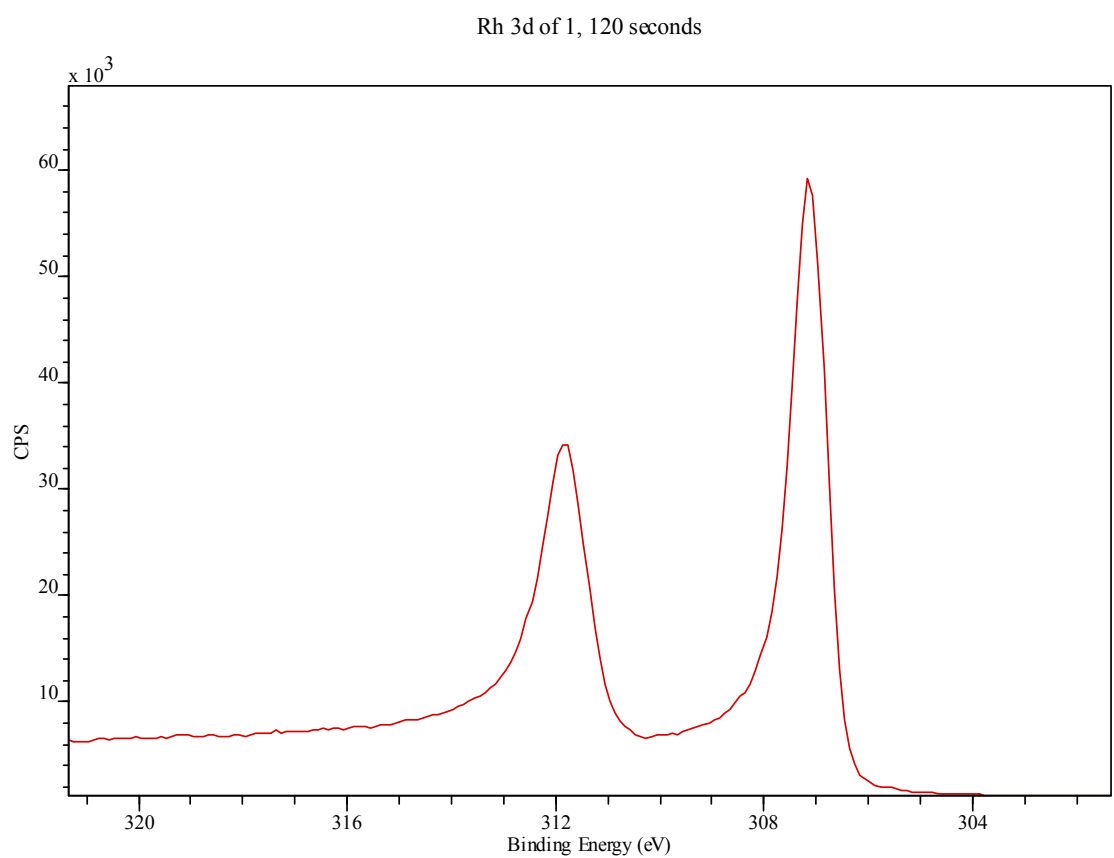


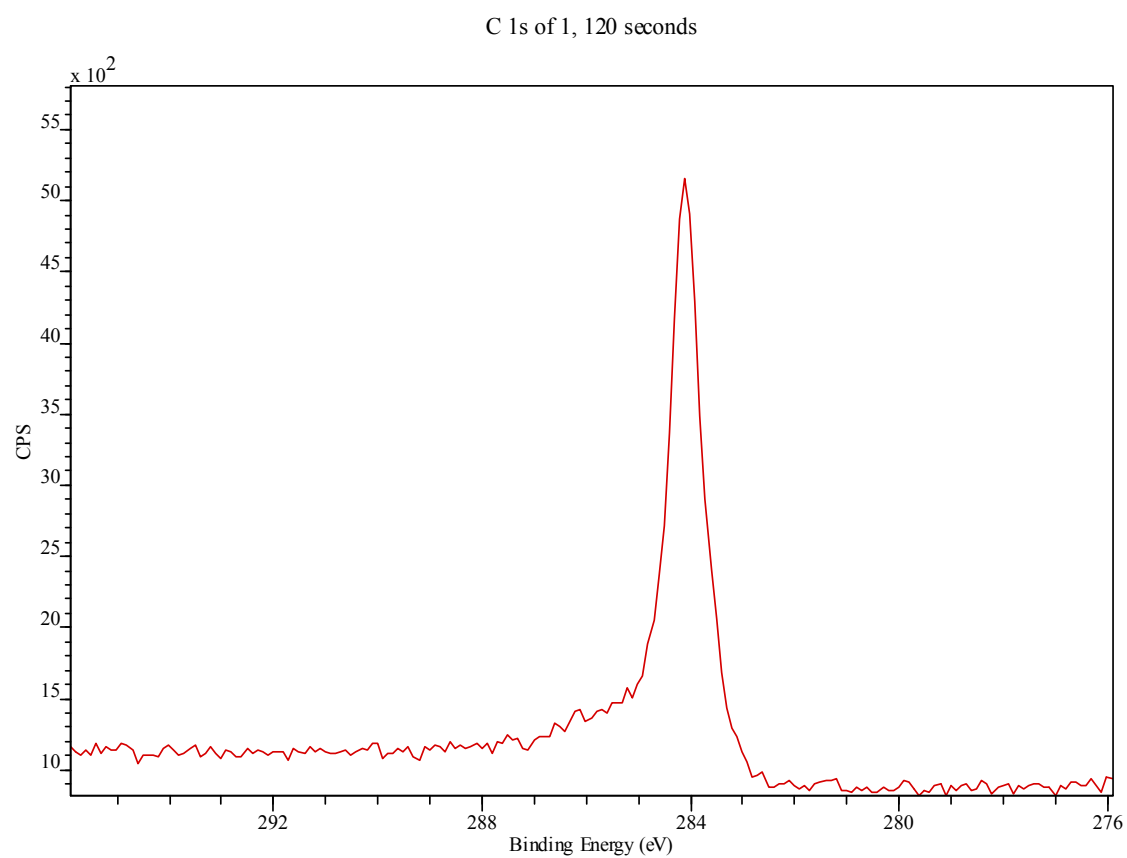




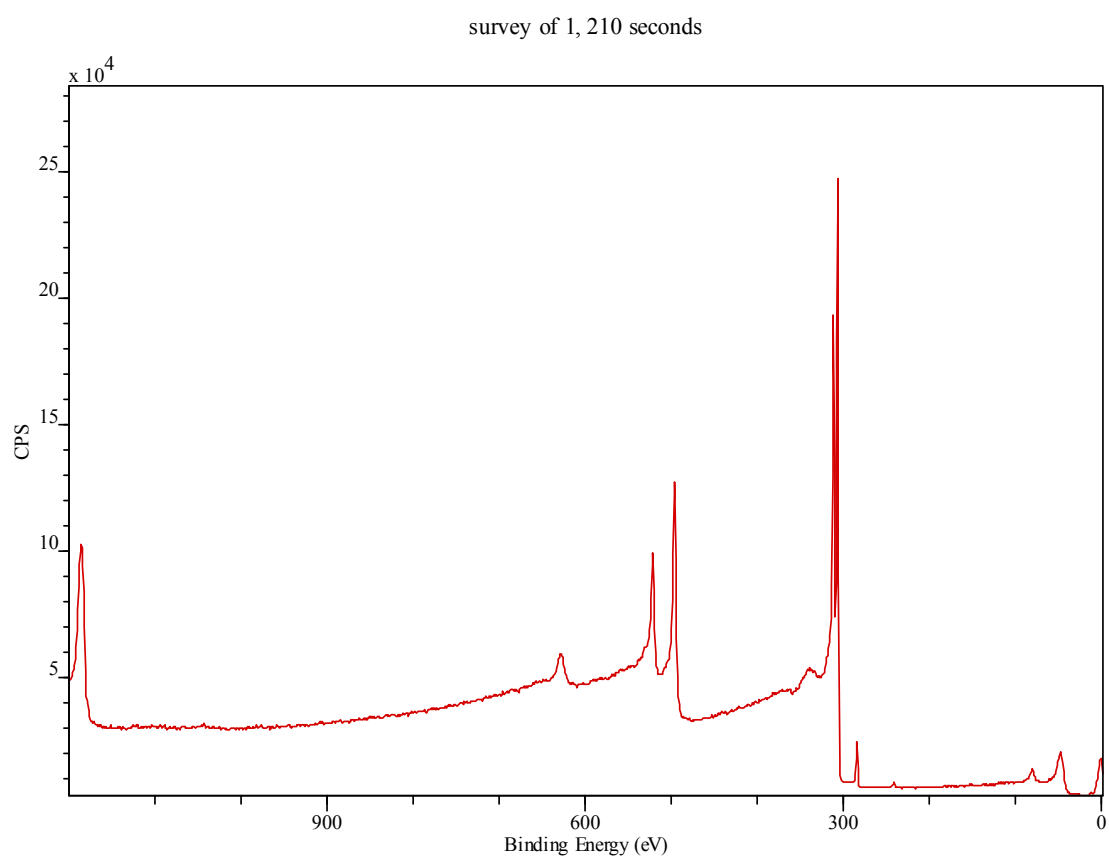
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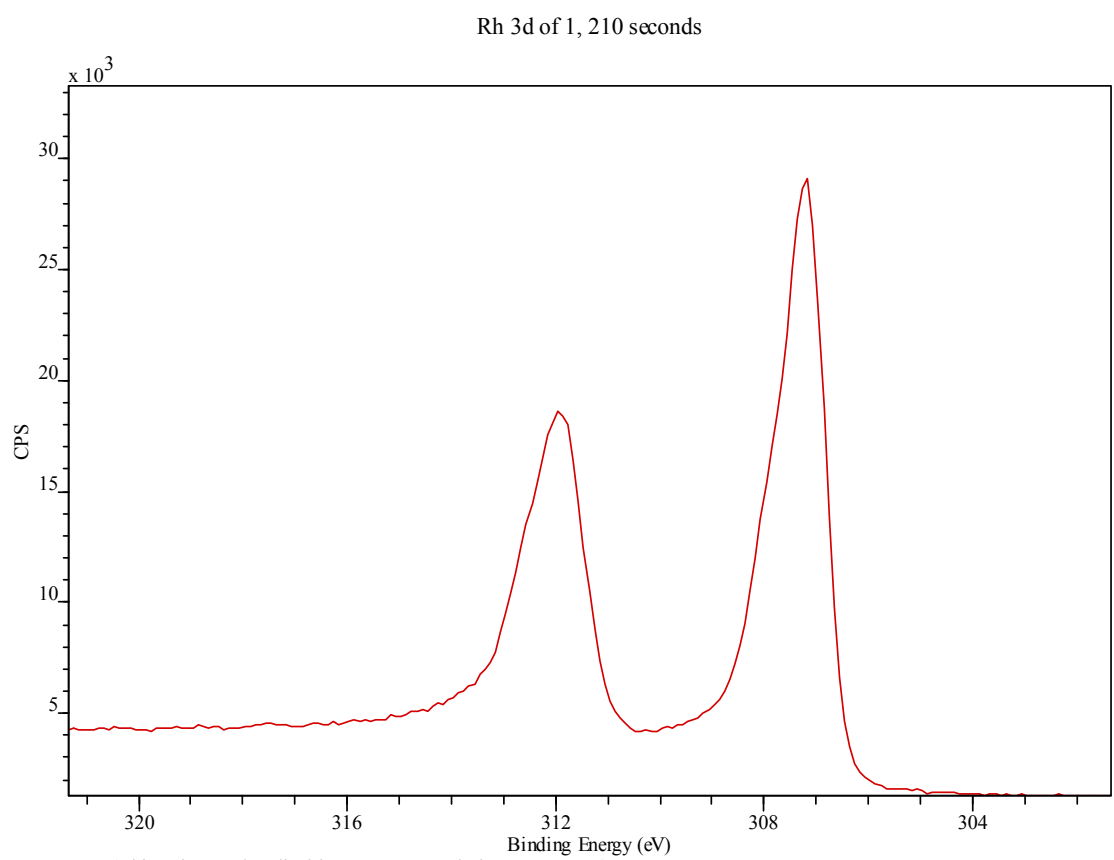


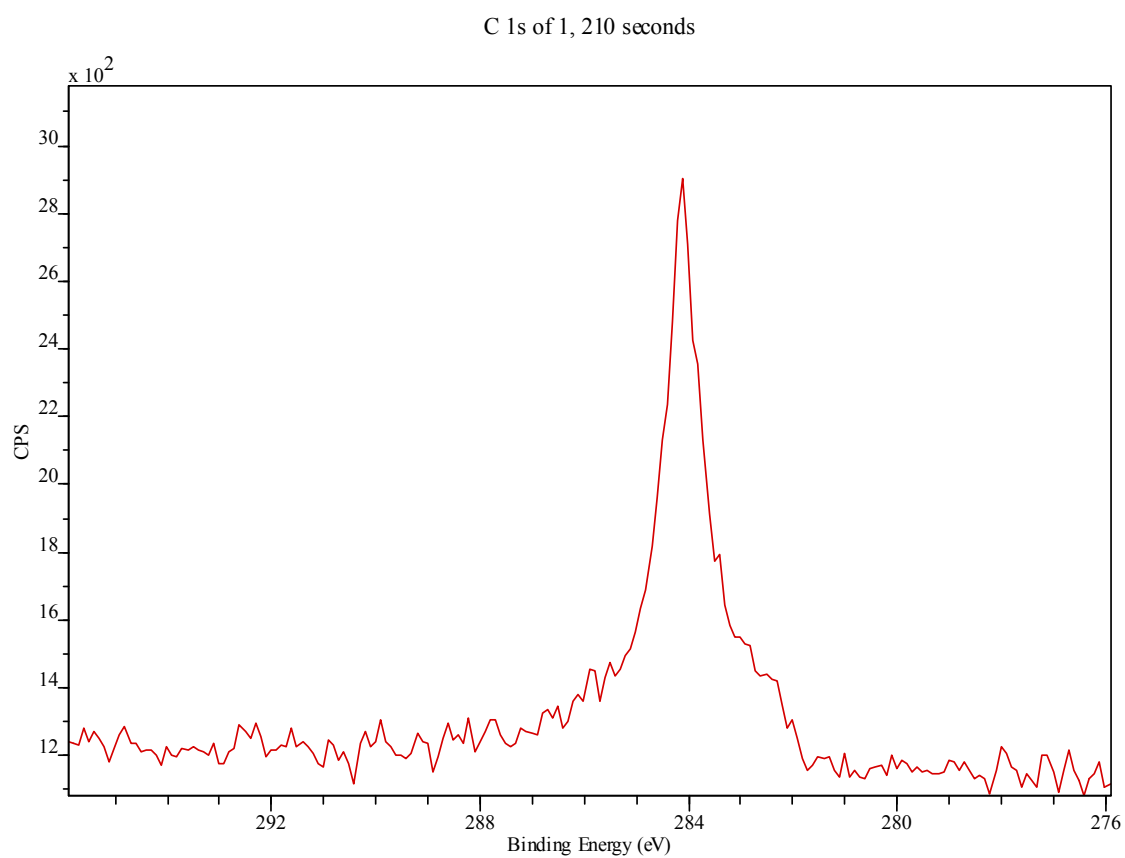


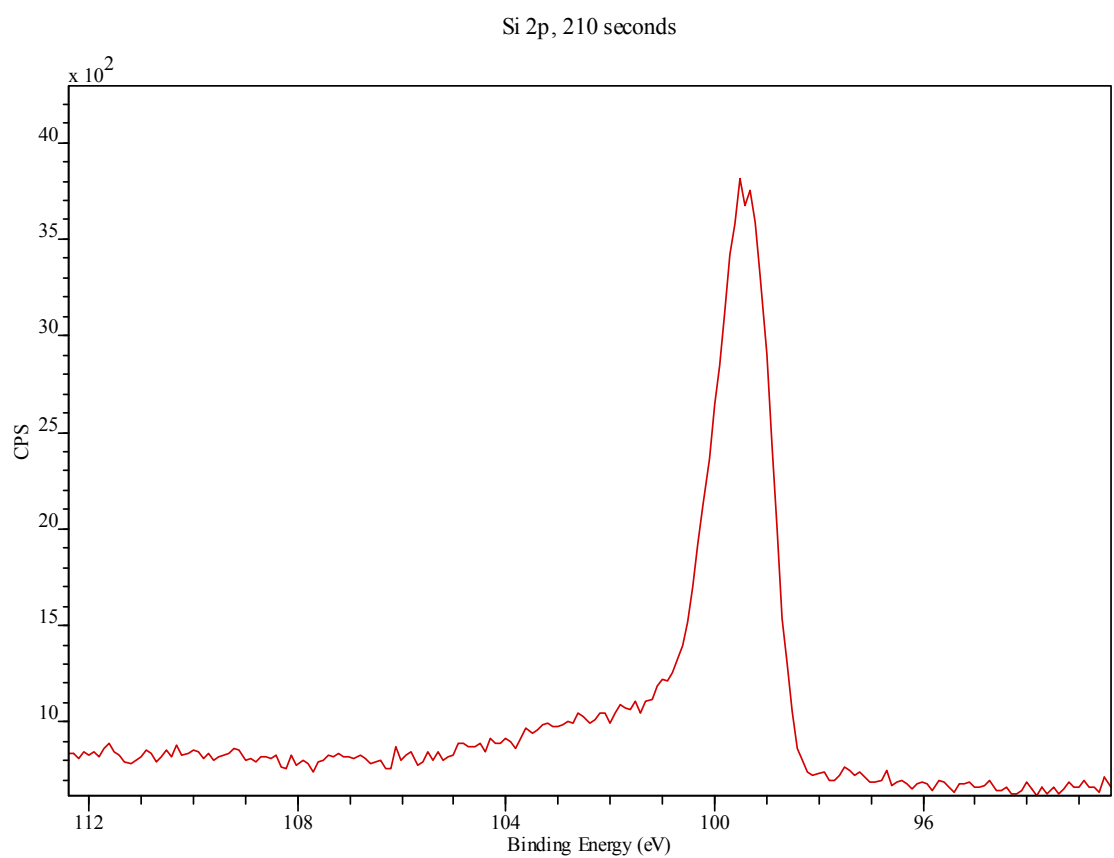


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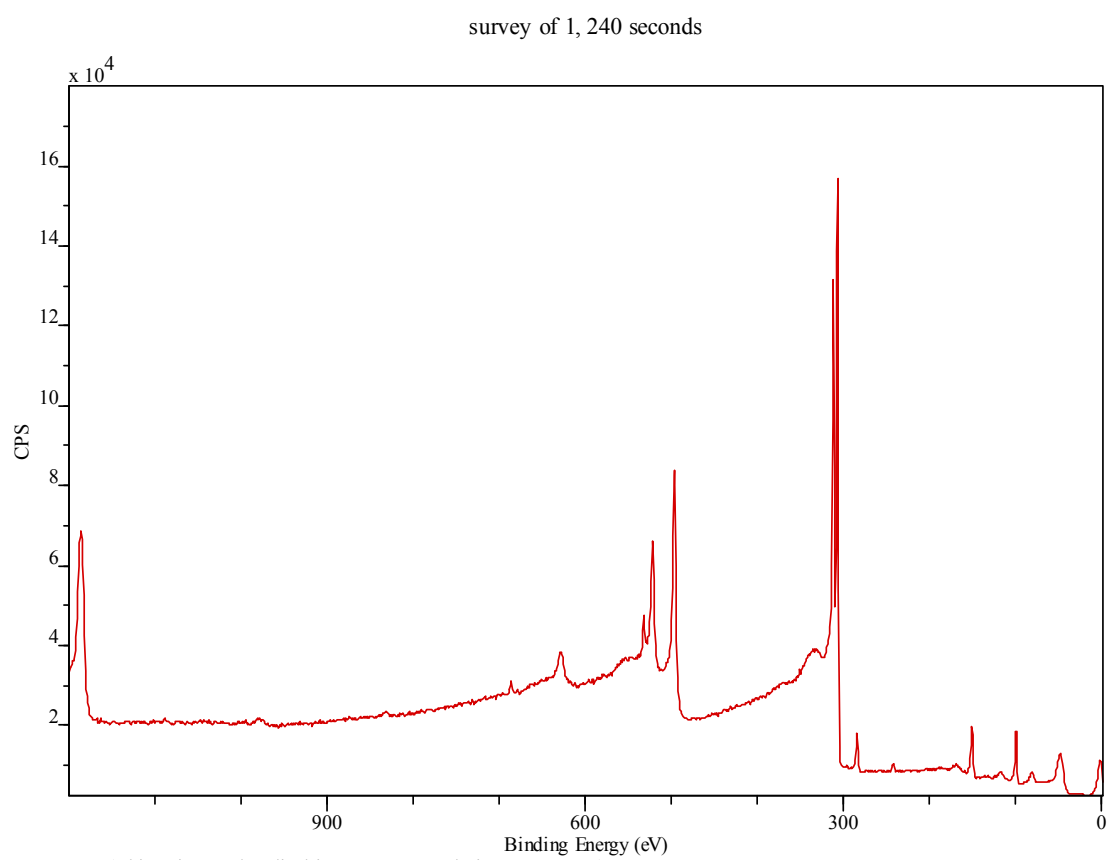


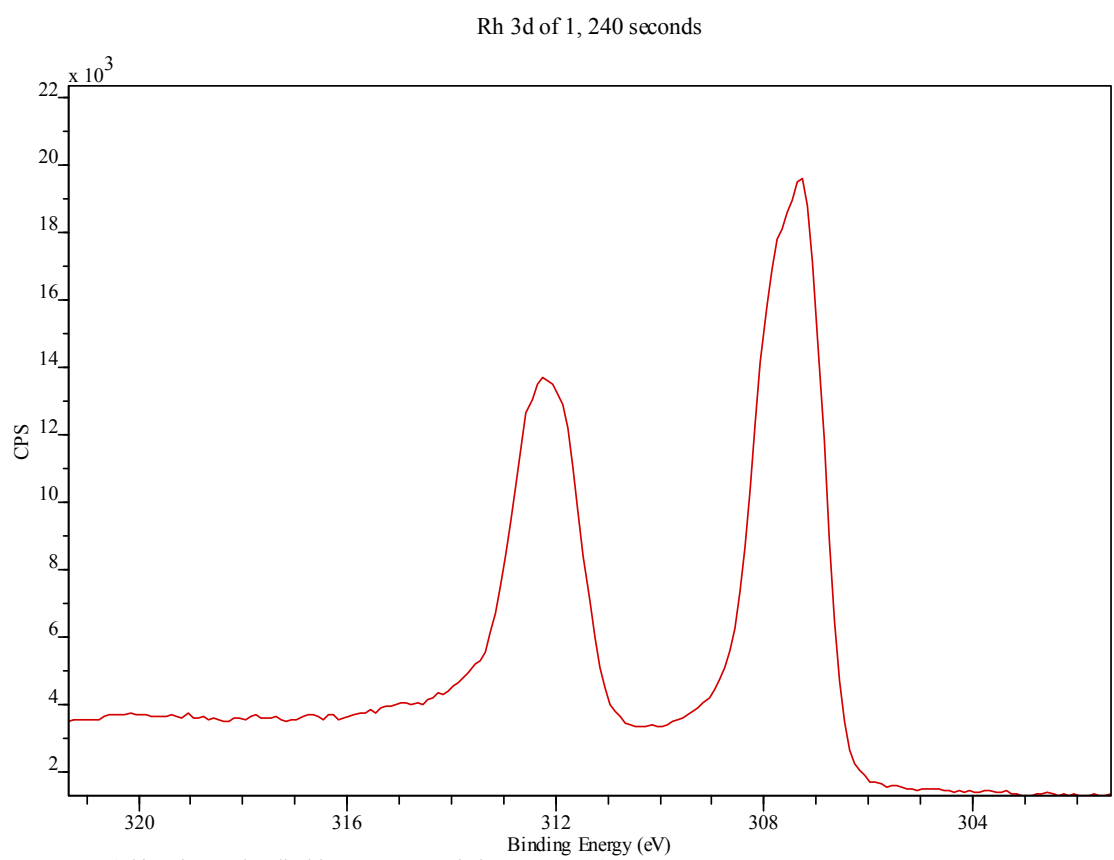


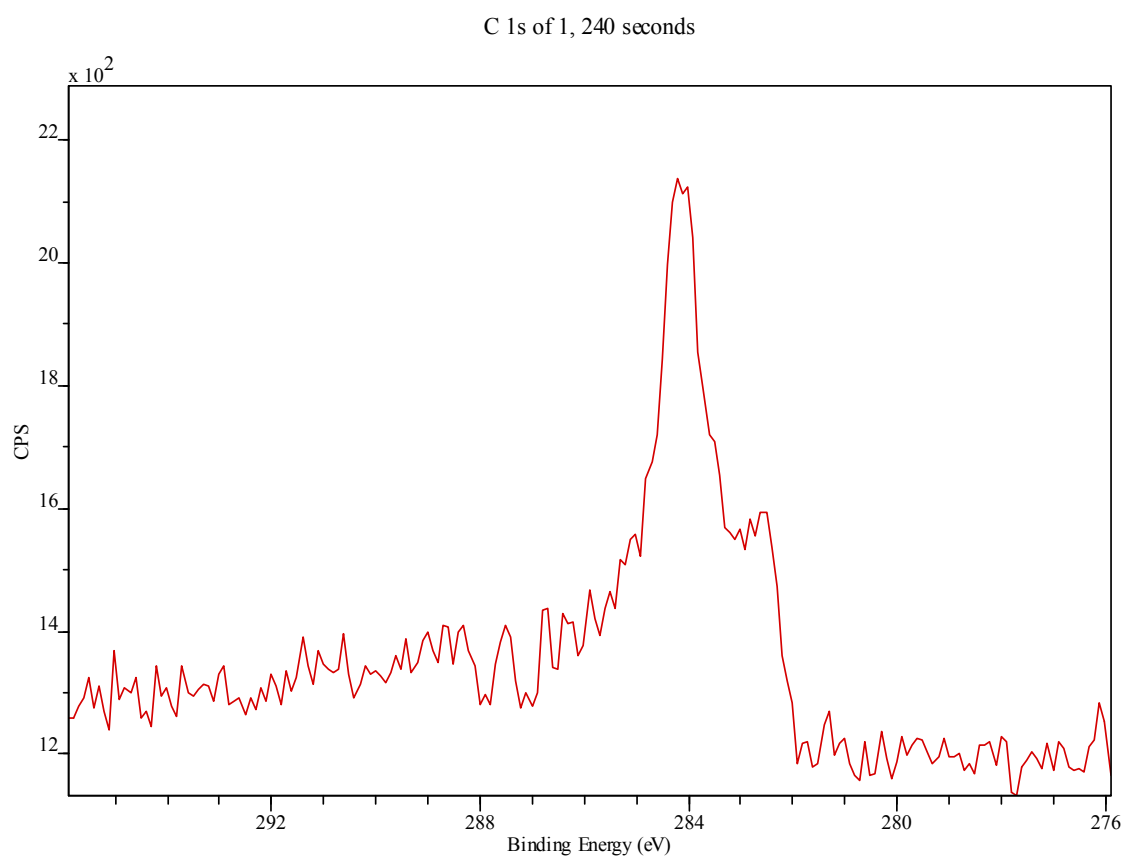


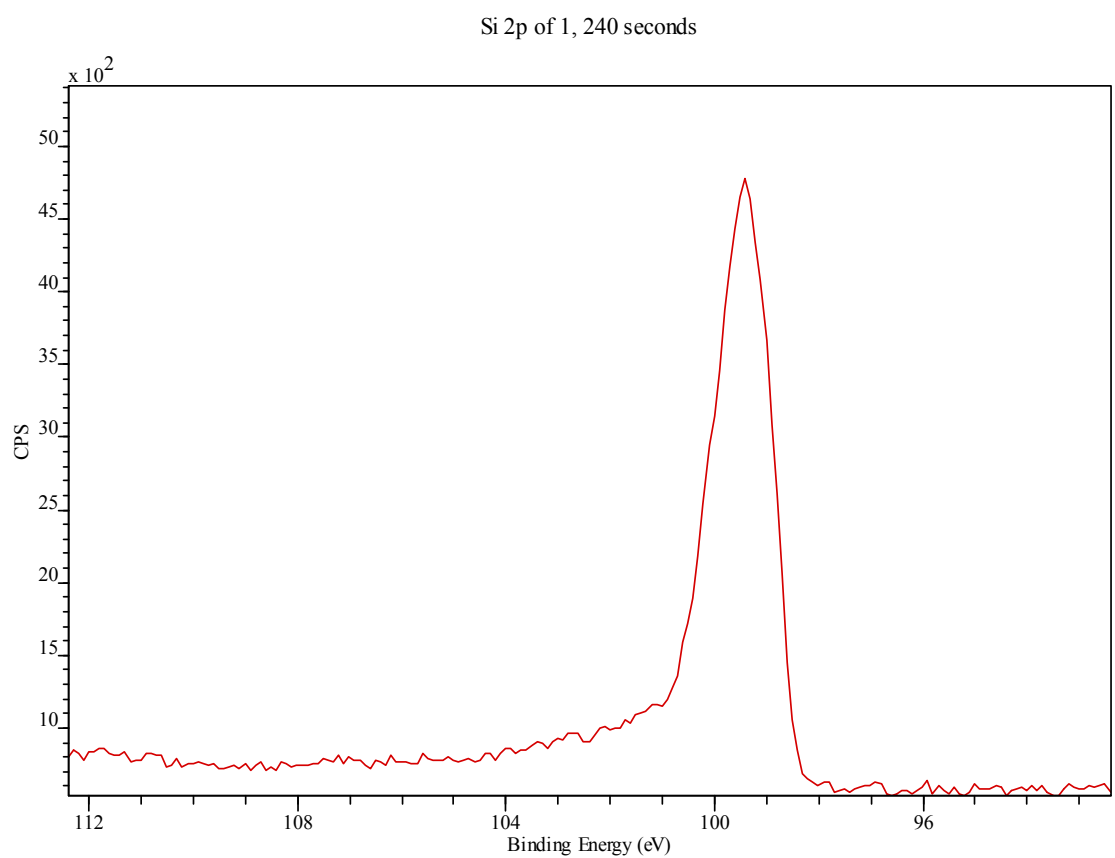


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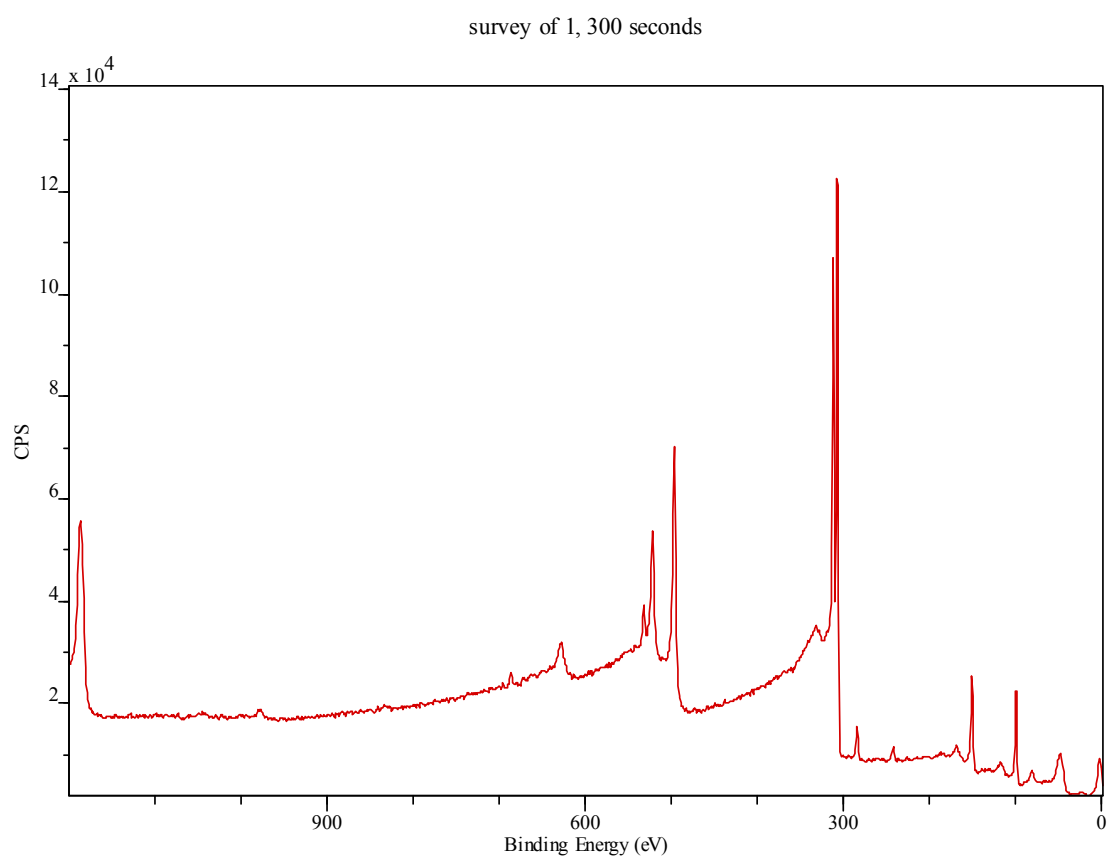


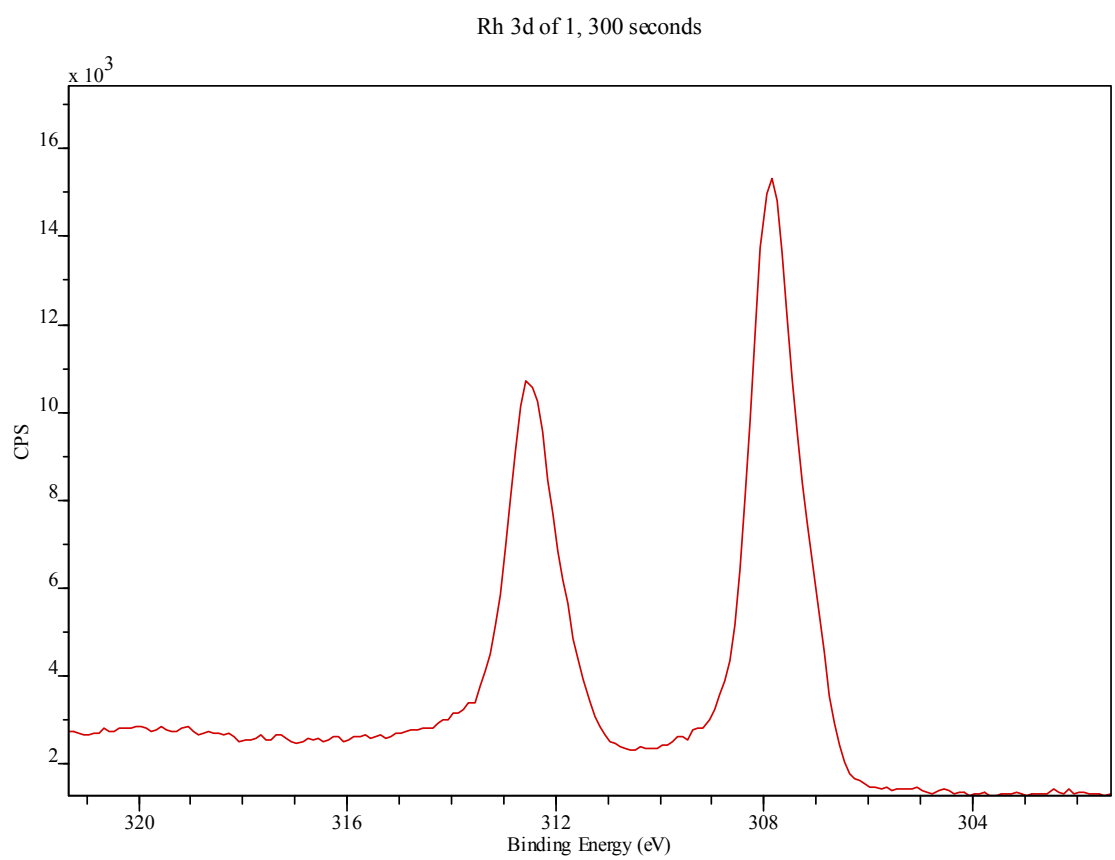


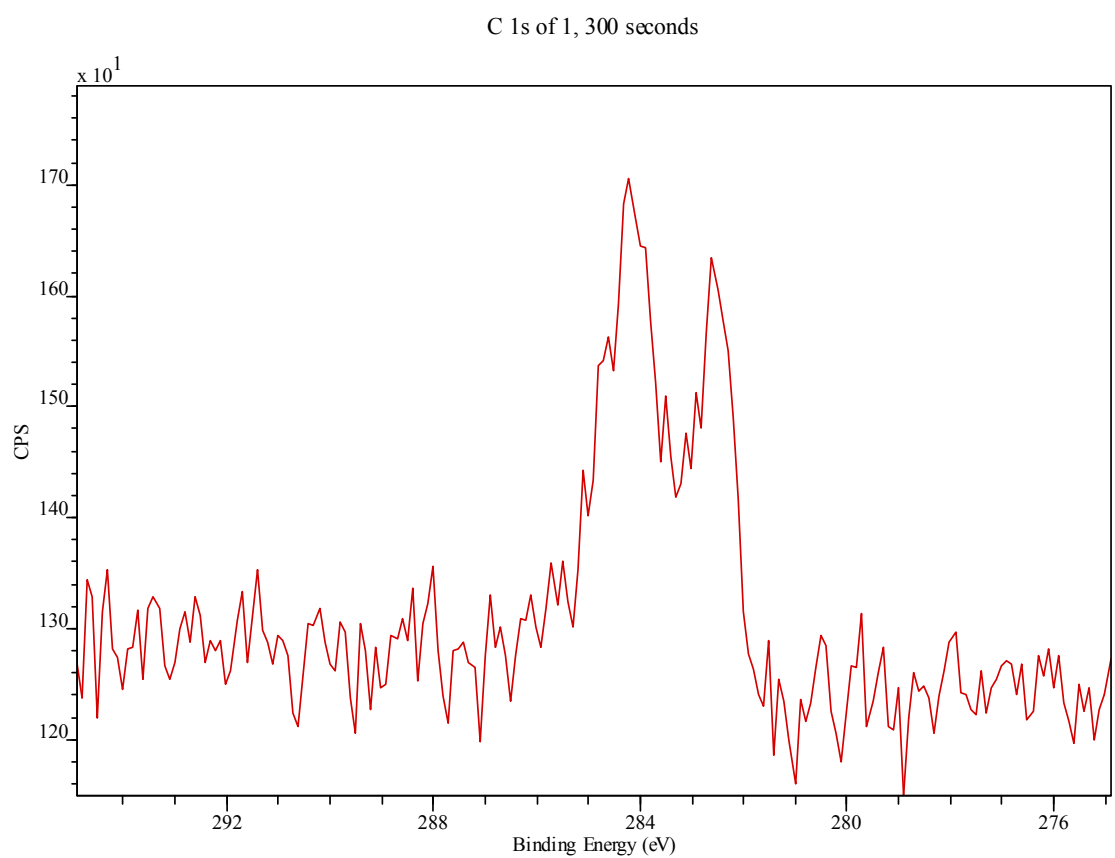


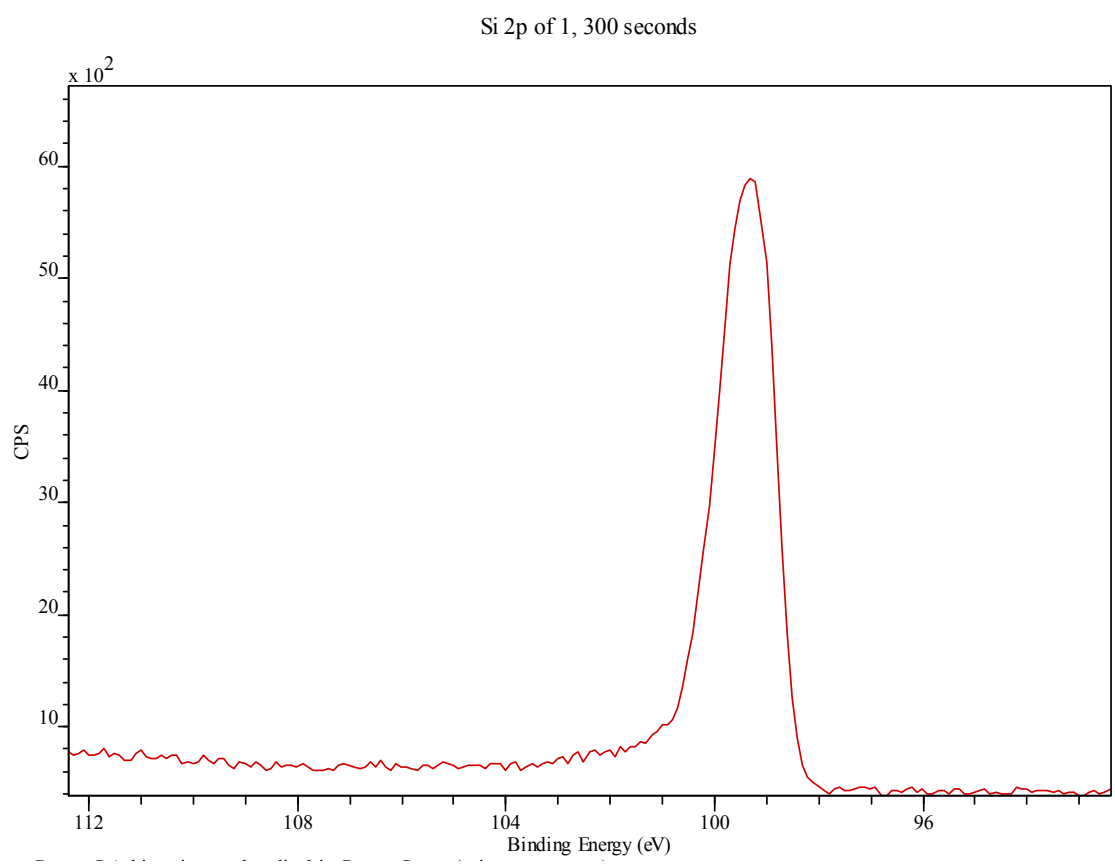


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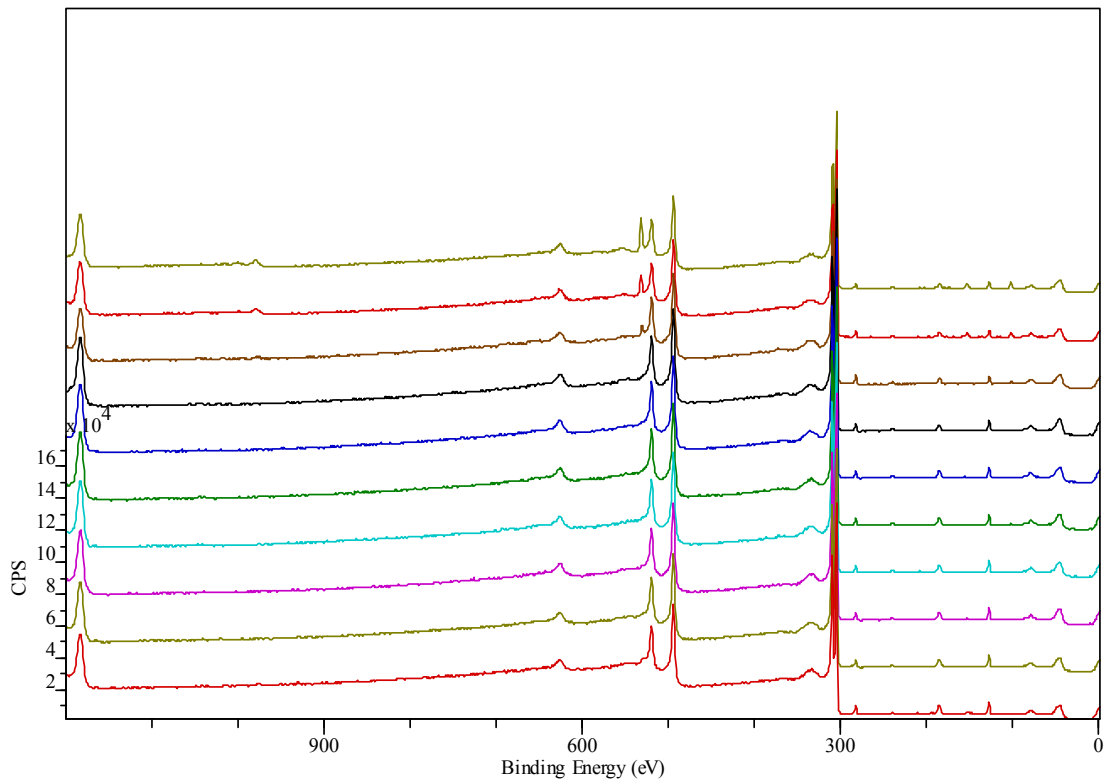




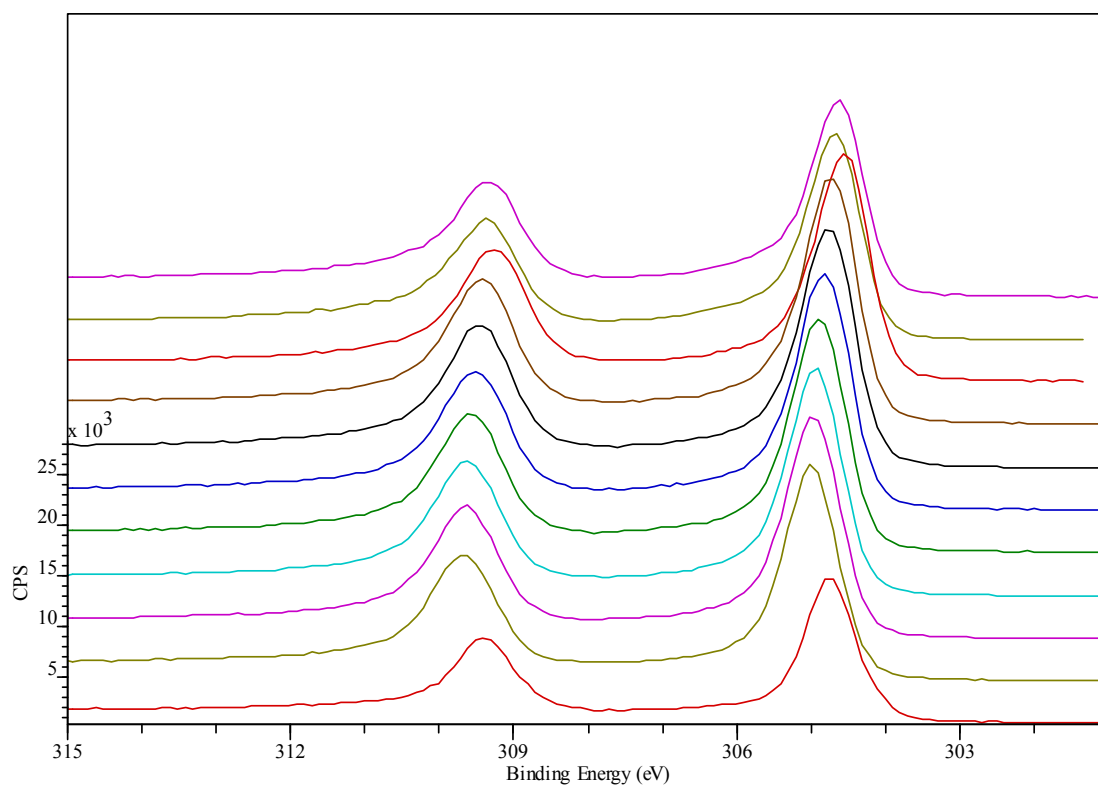


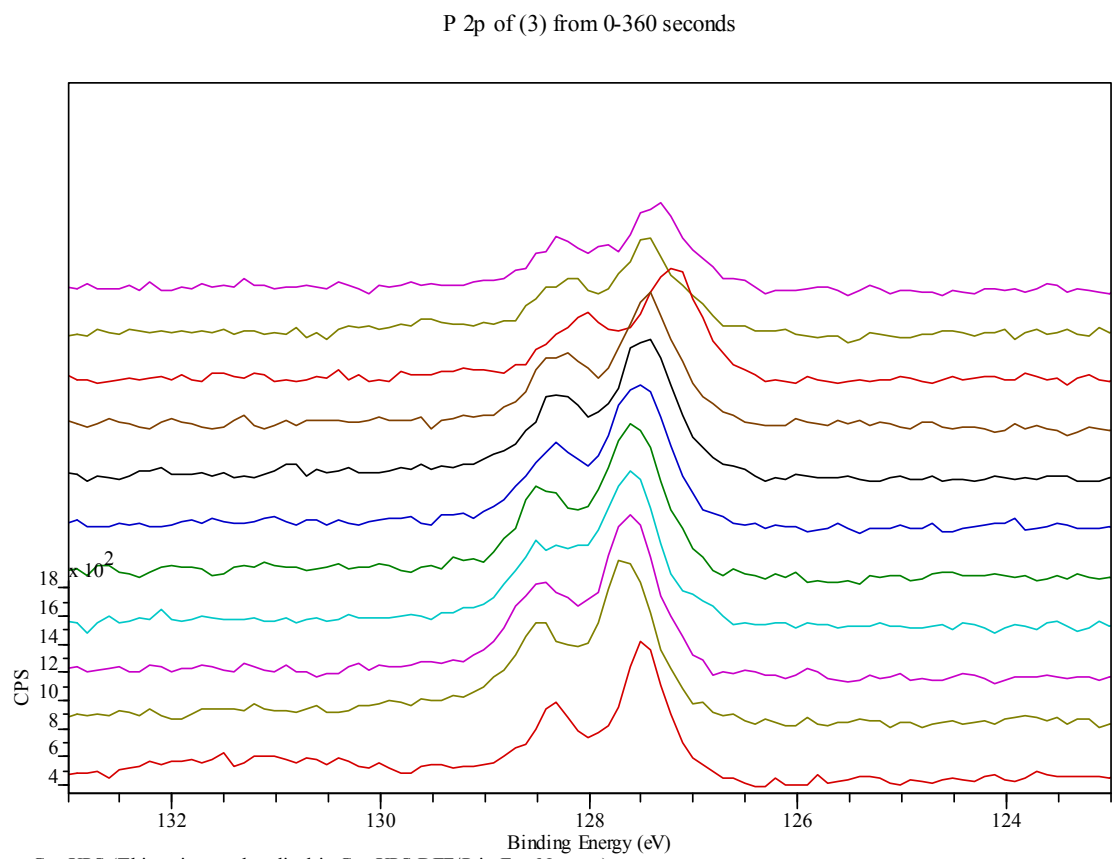
XPS spectroscopy of [Rh(3,5-(CF₃)₂-Pz)(PMe₃)₃] (**3**) using hydrogen carrier gas

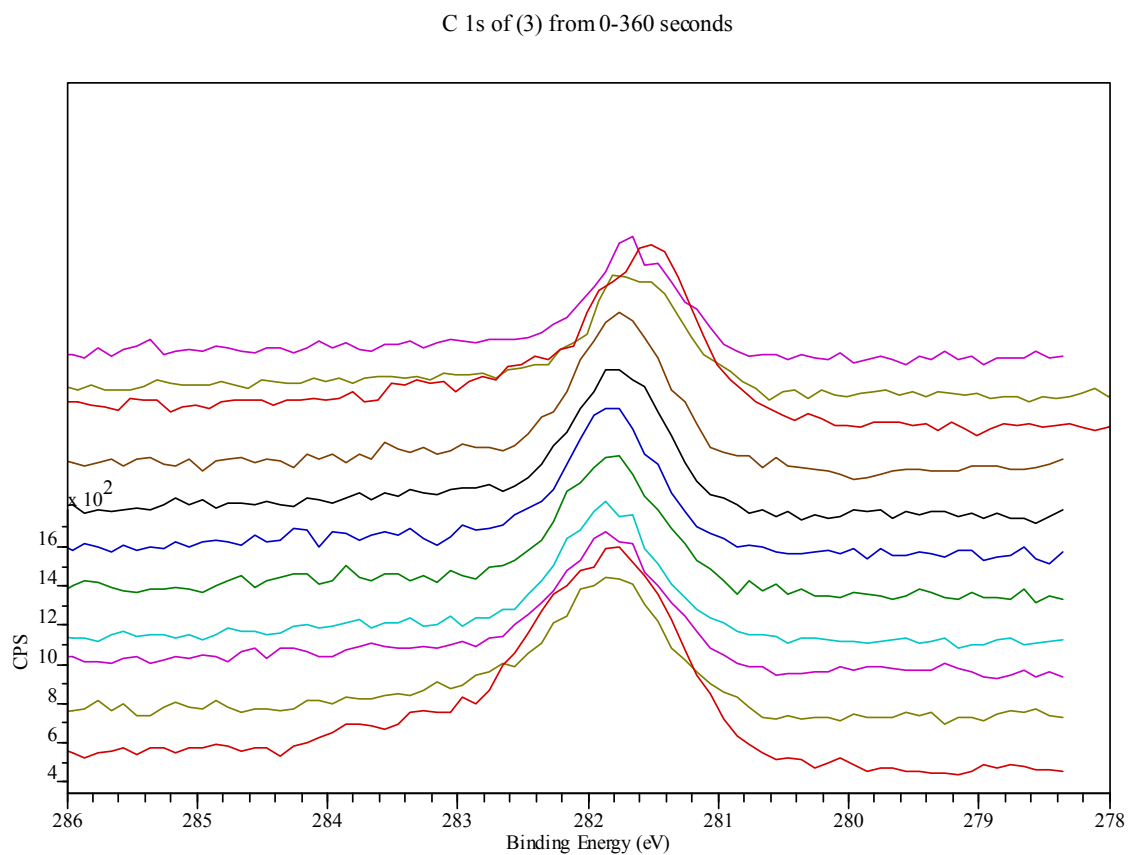
surveys of (**3**) from 0-360 seconds

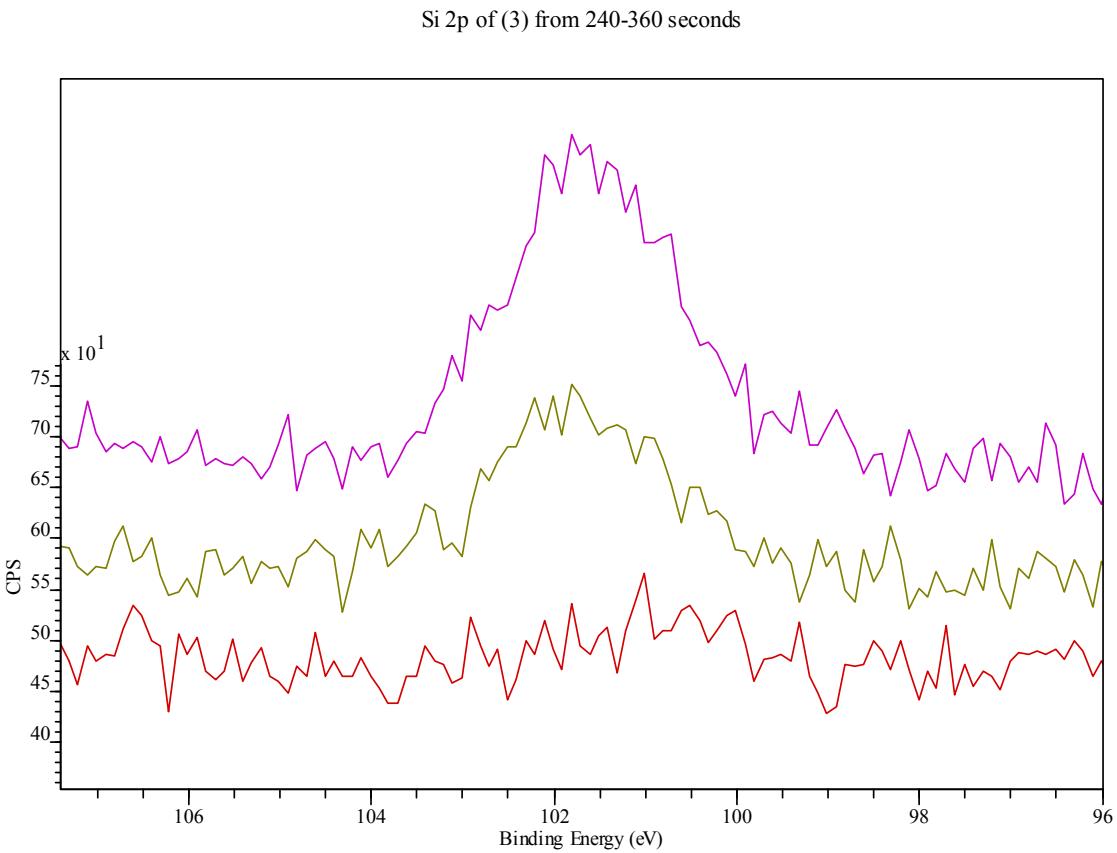


Rh 3d of (3) from 0-360 seconds of sputtering

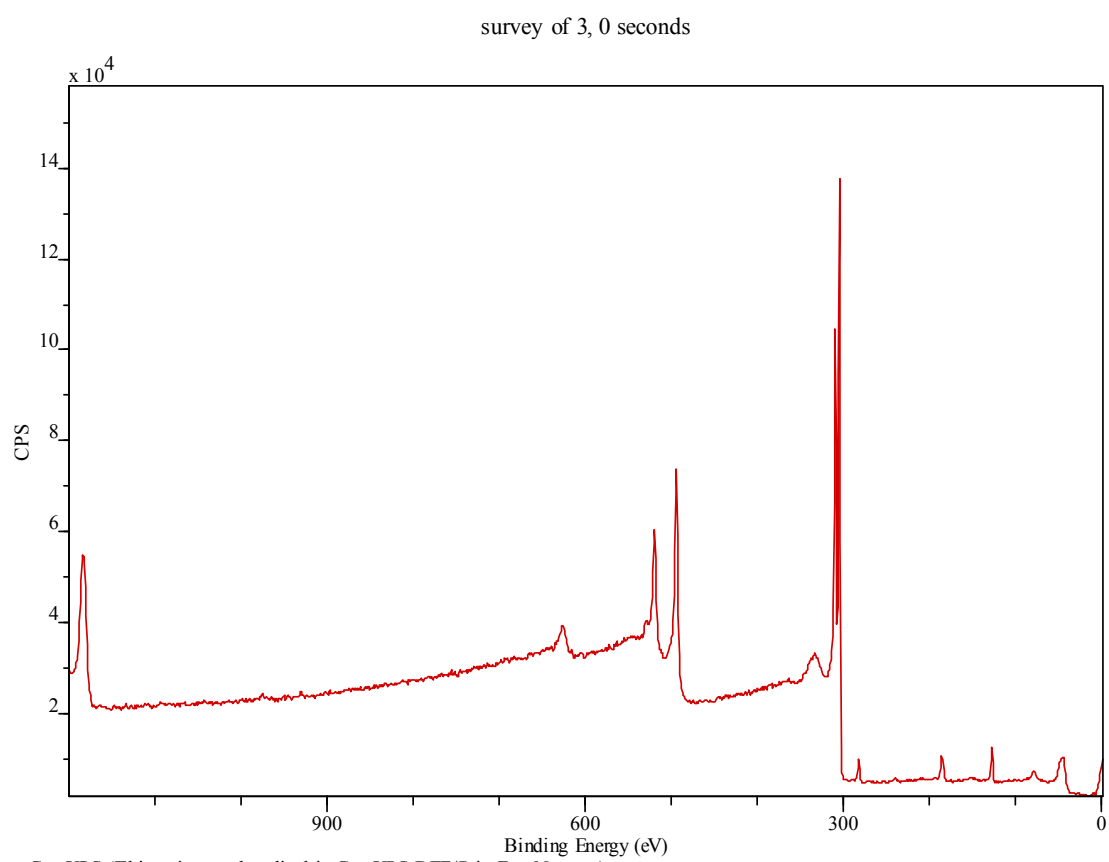


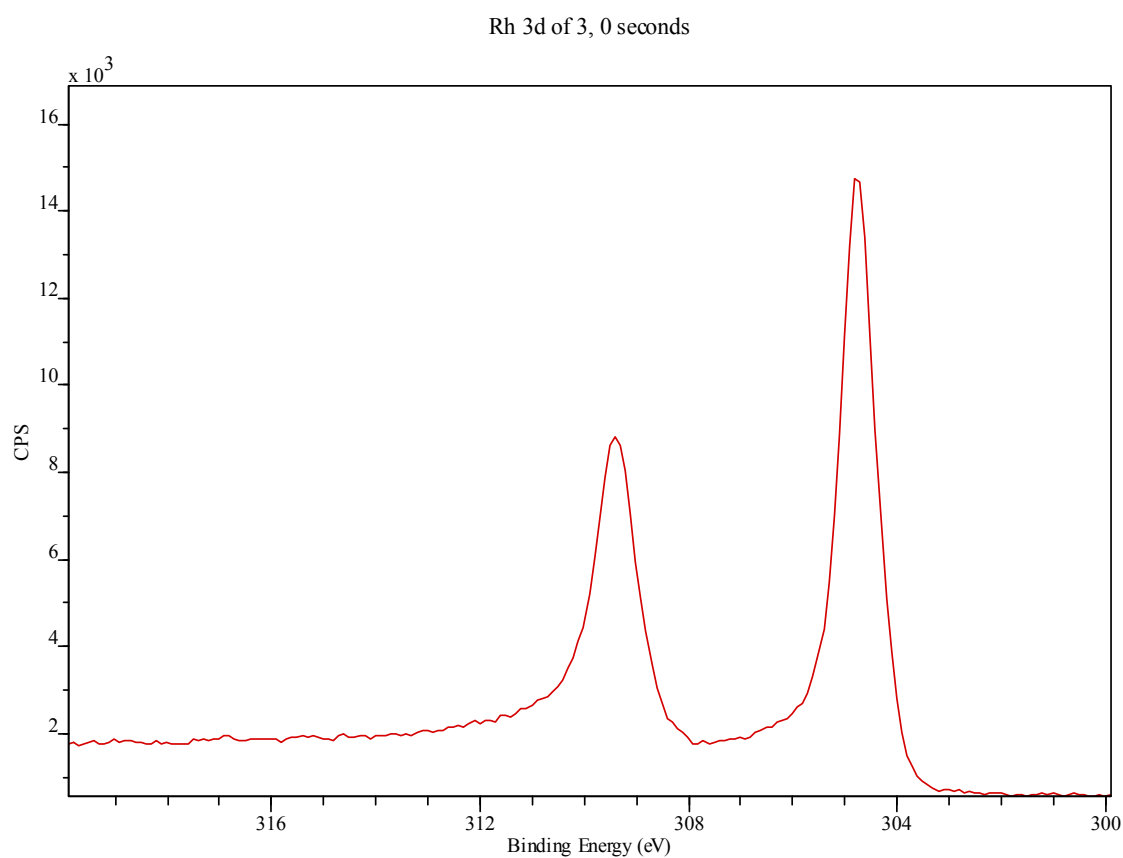


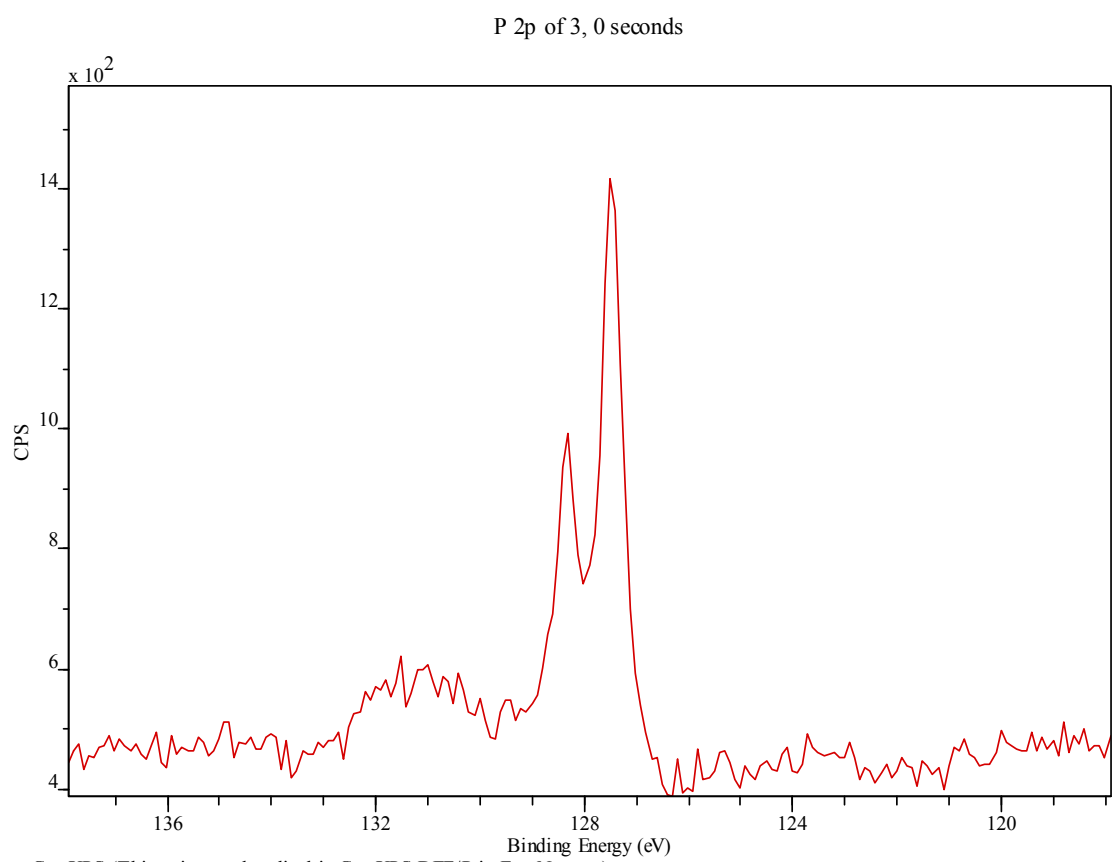


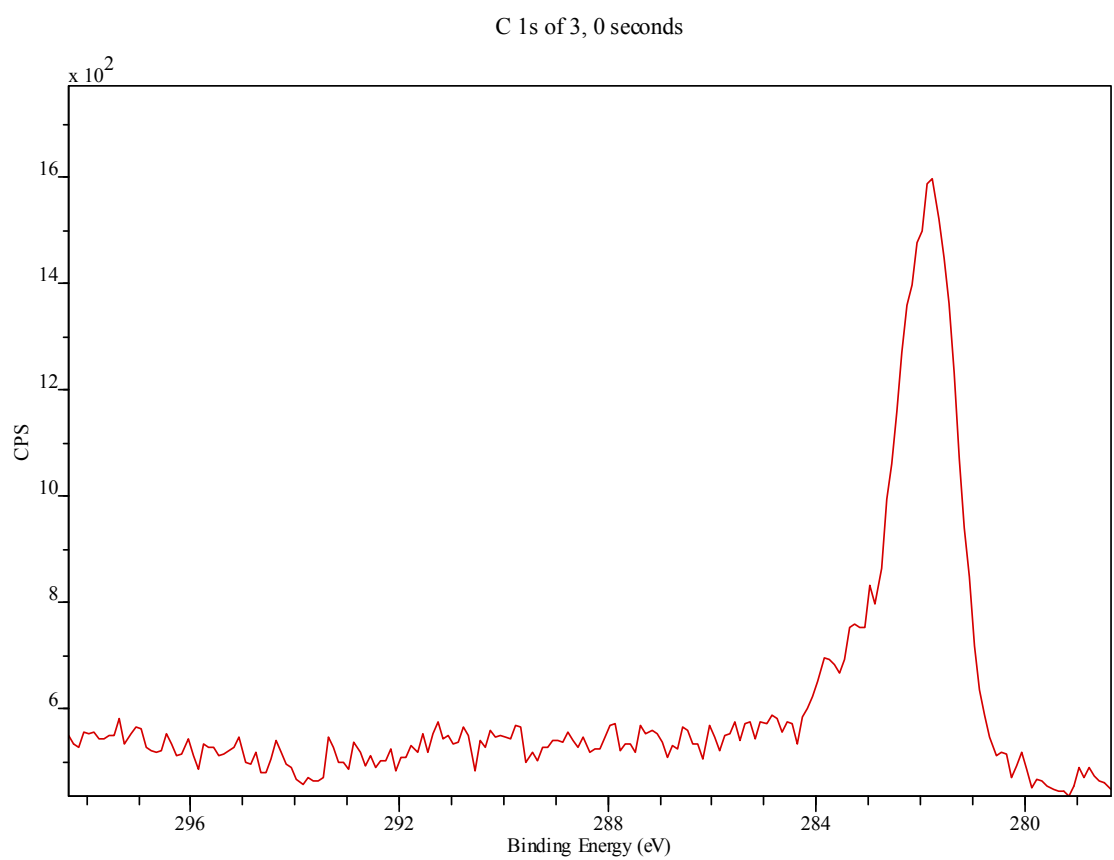


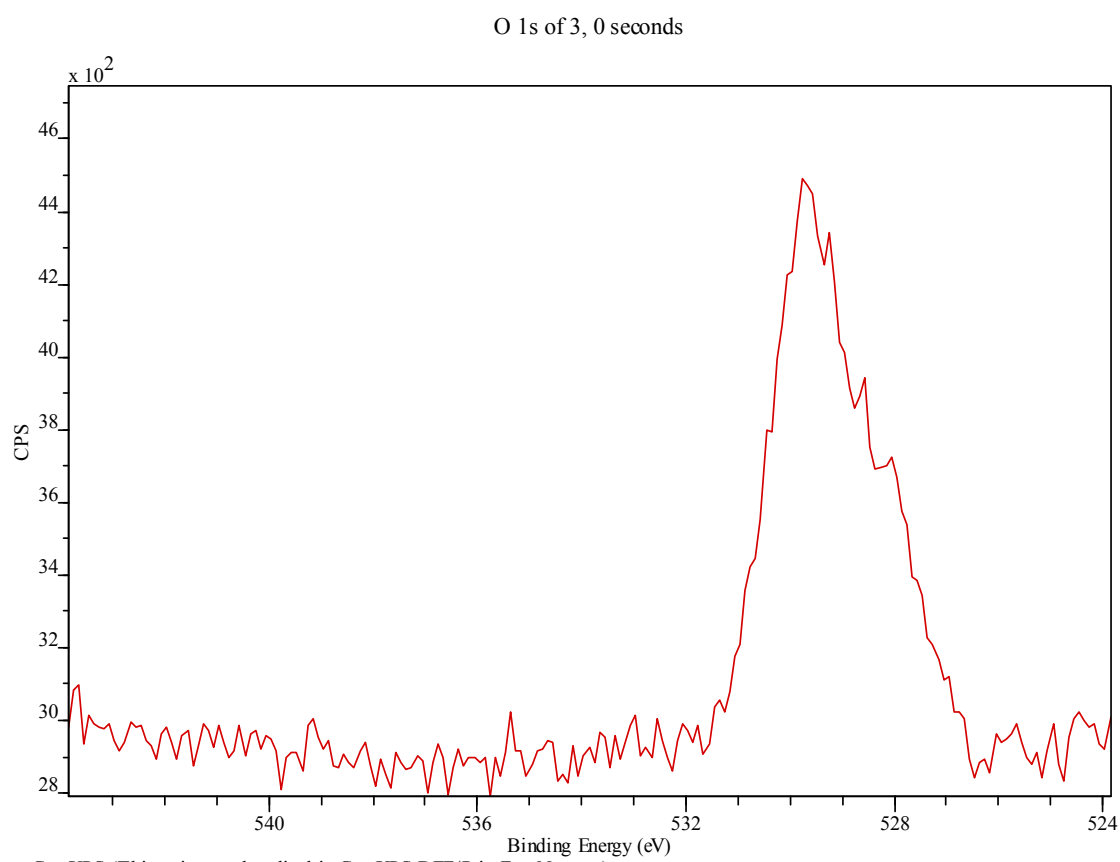
0 seconds of sputtering:

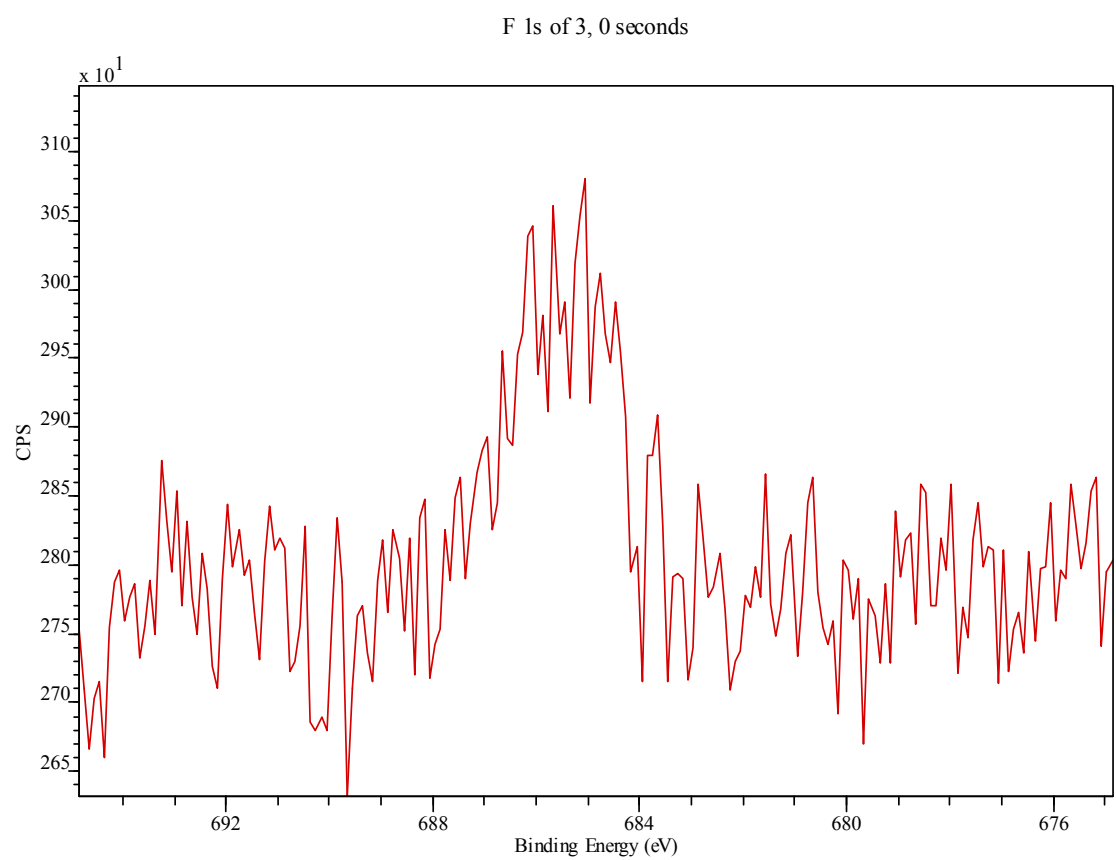




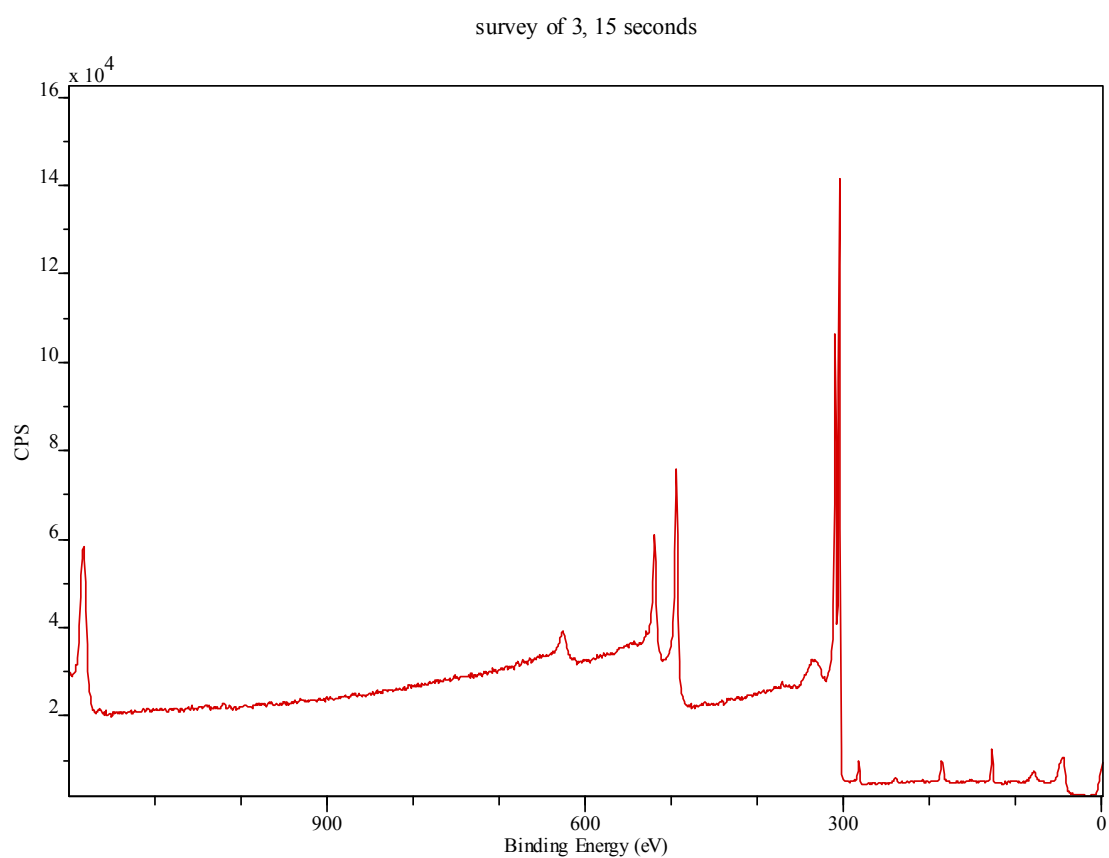


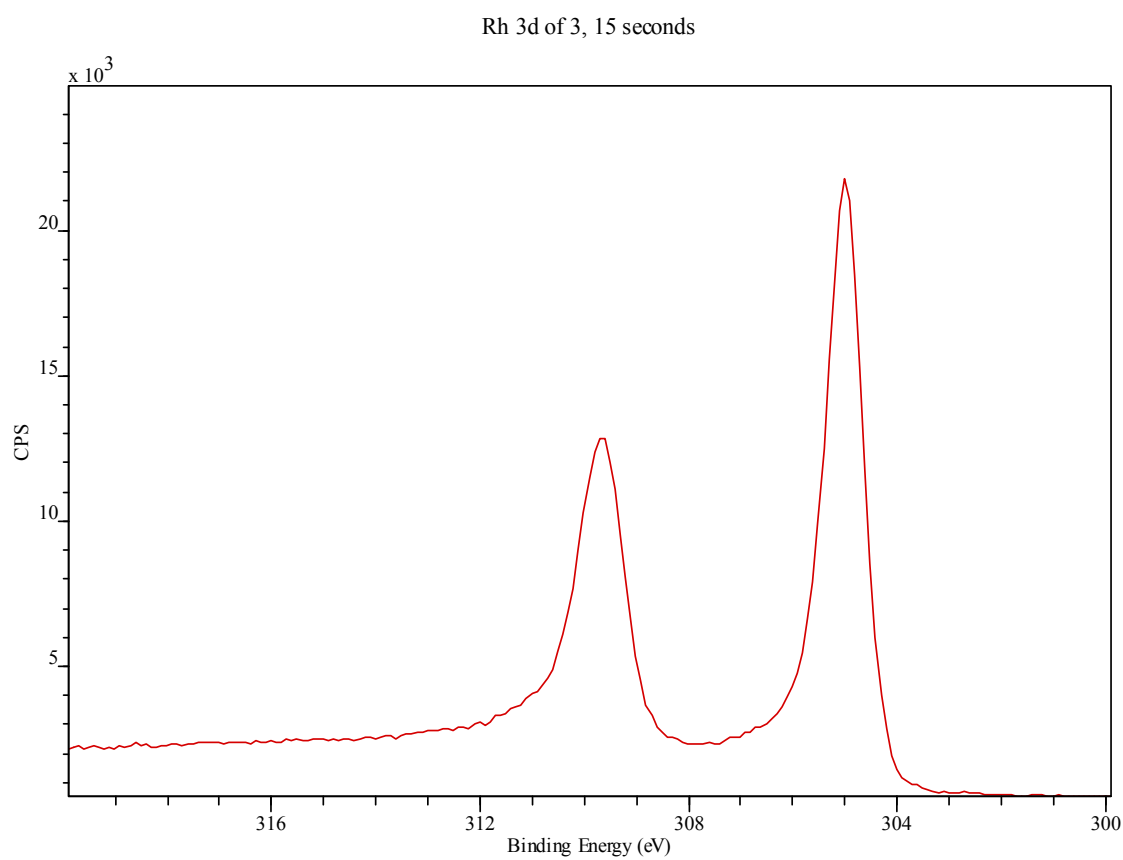


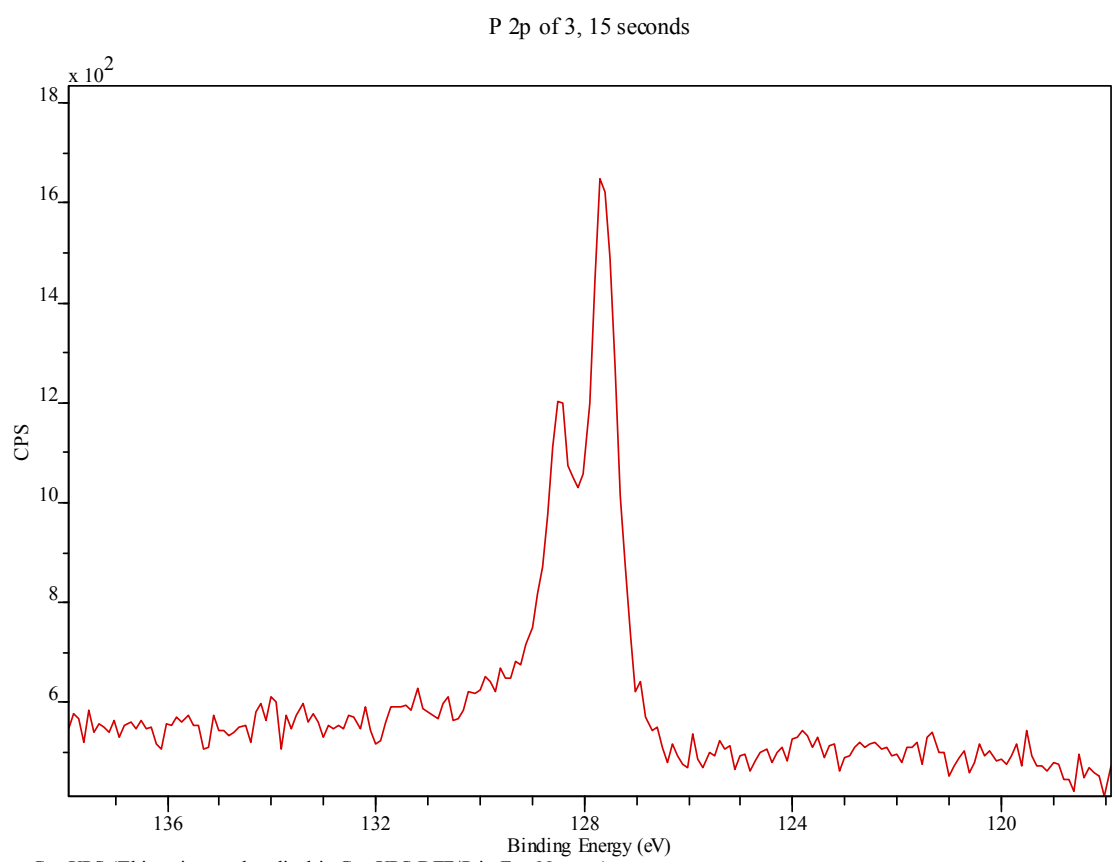


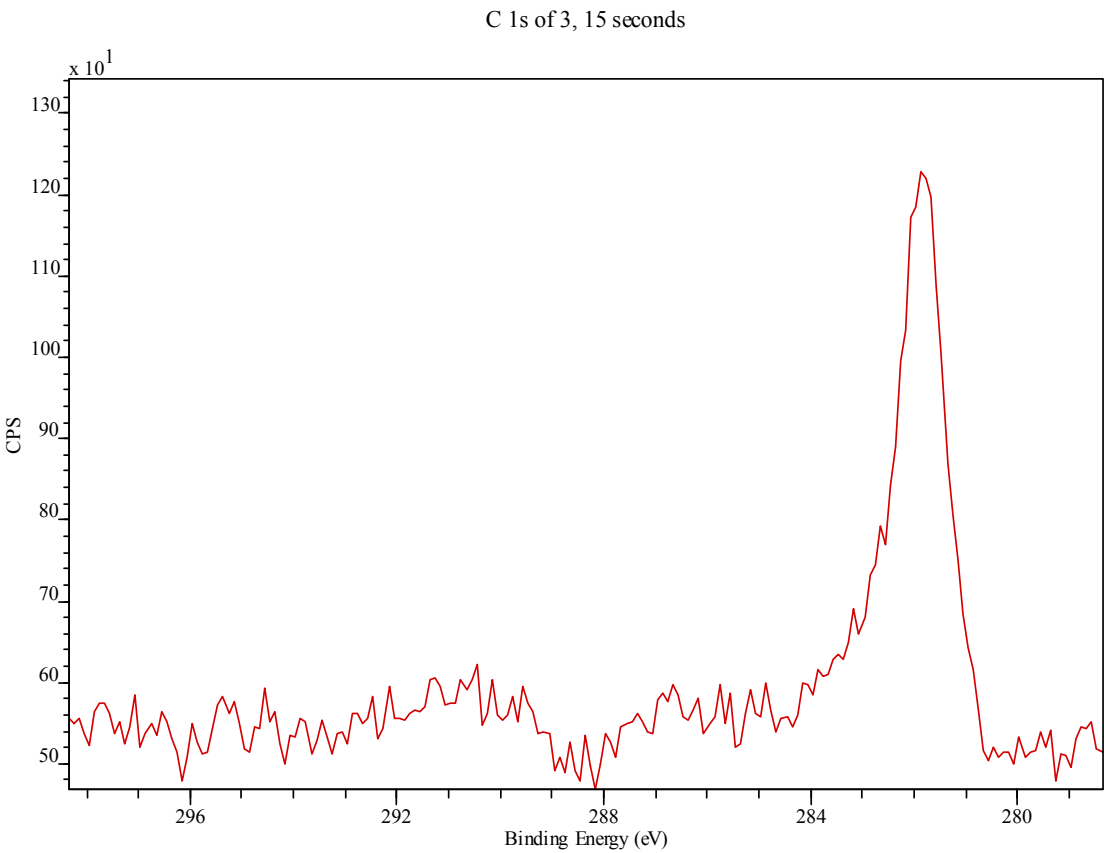


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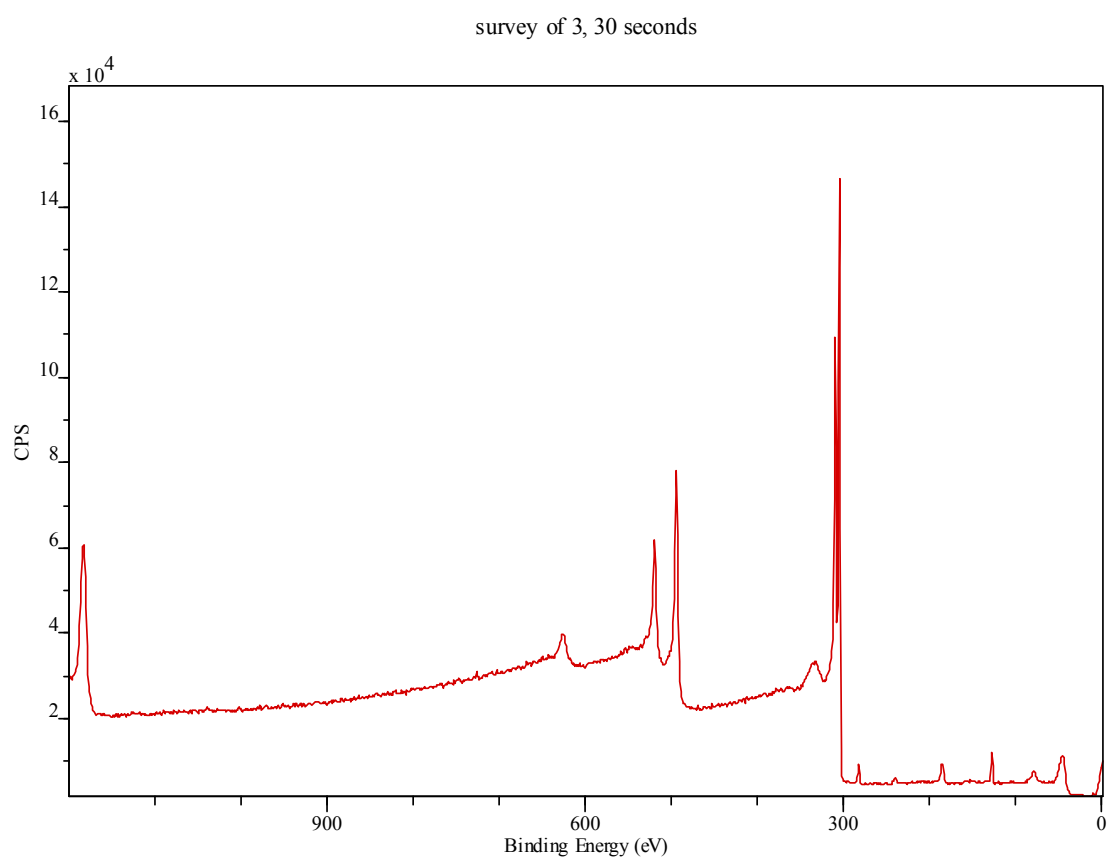


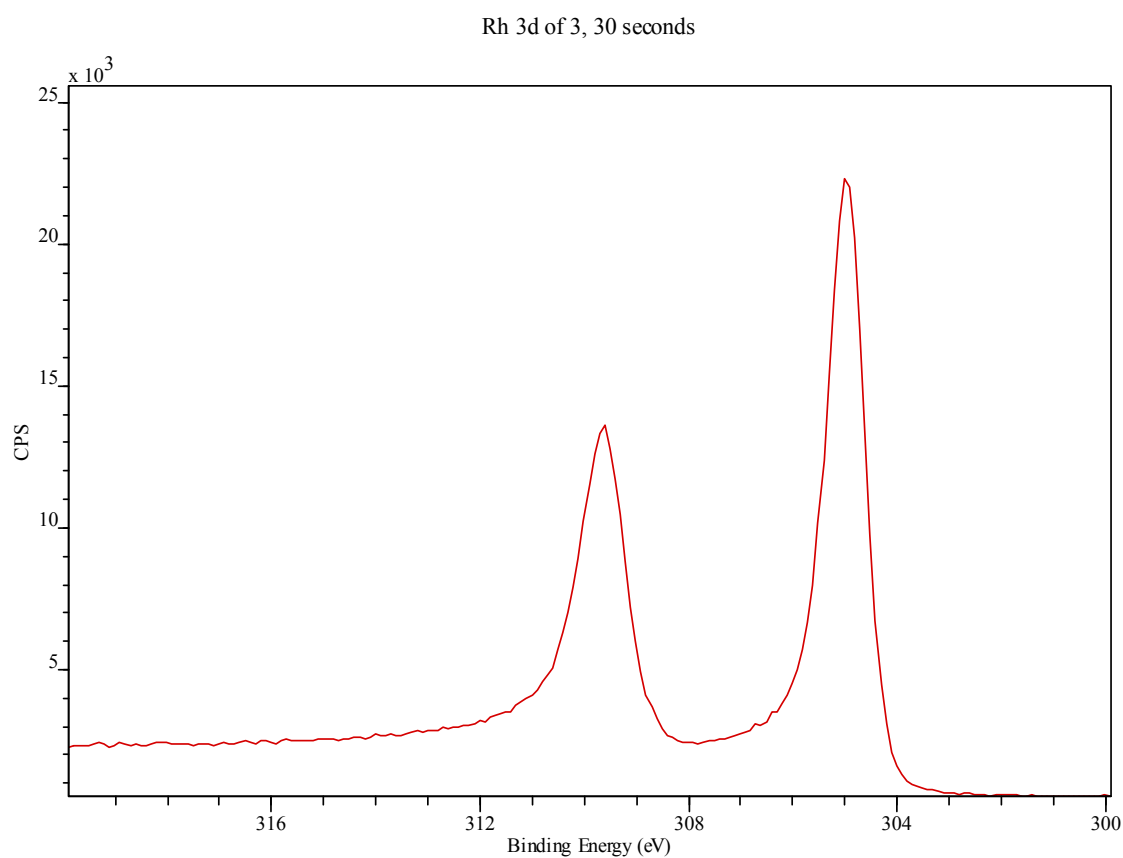


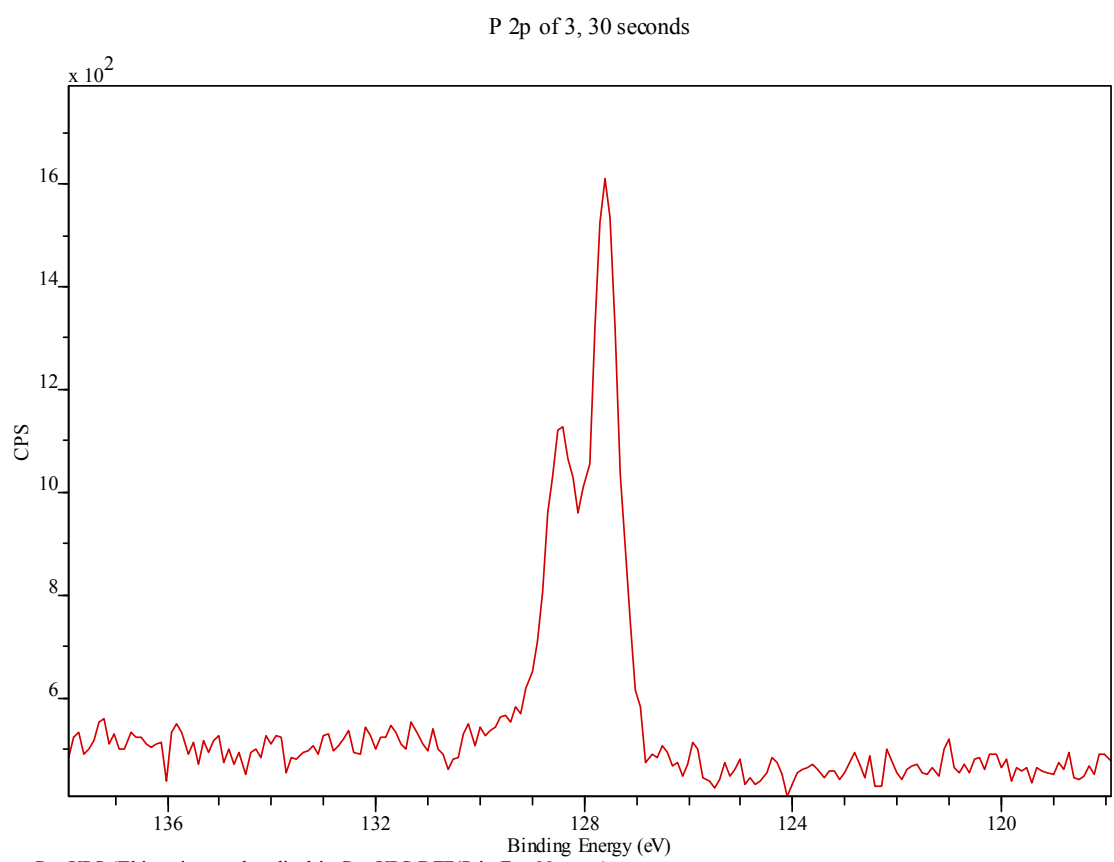


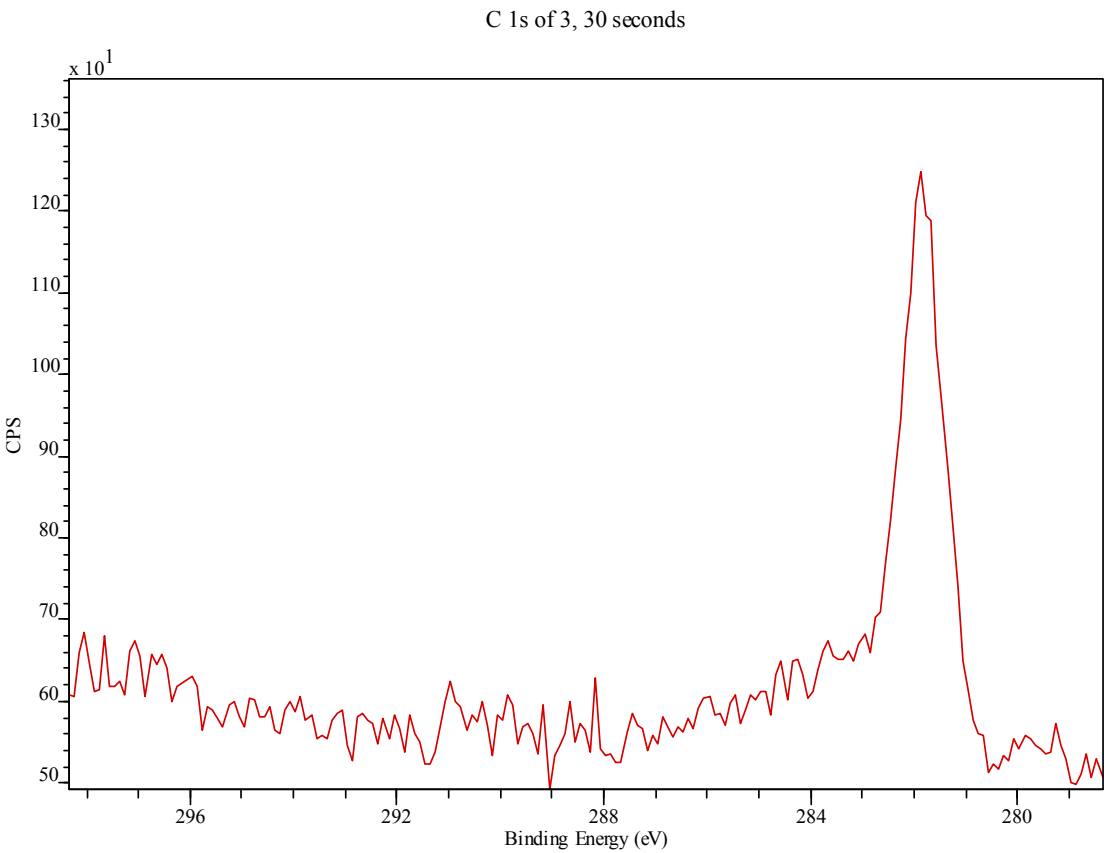


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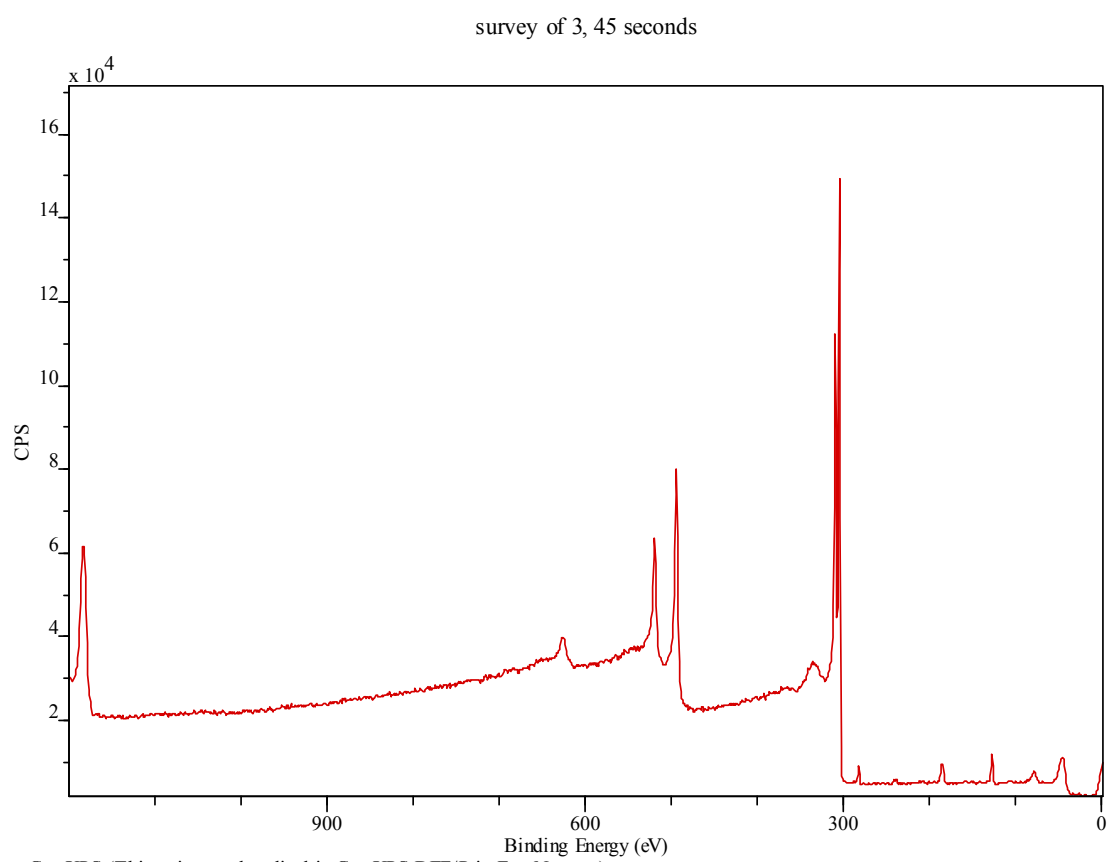


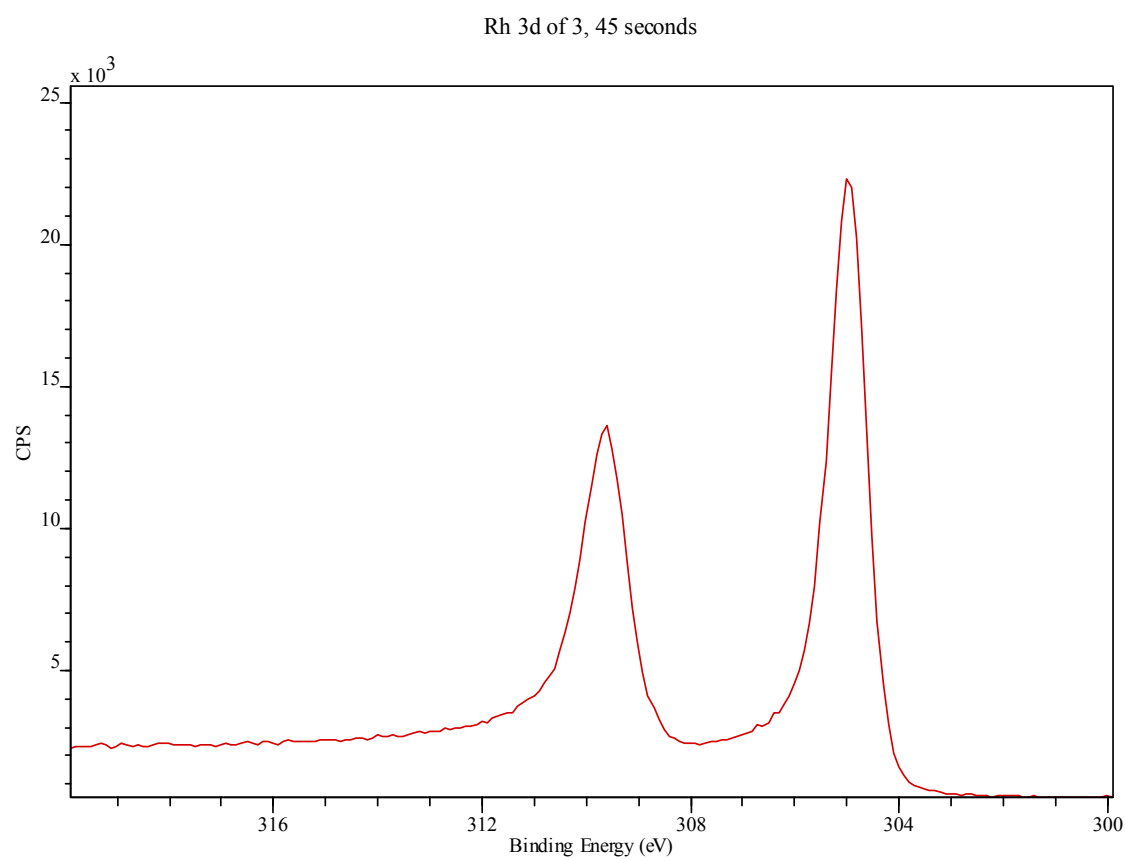


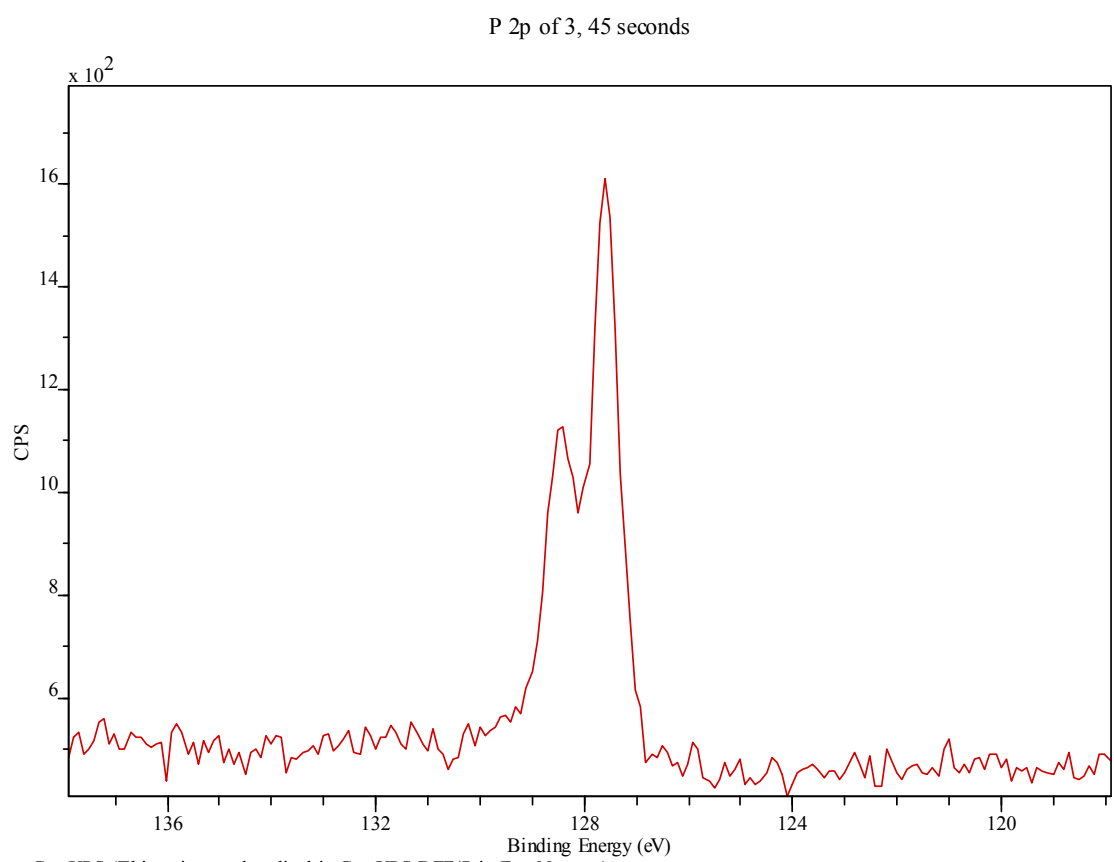


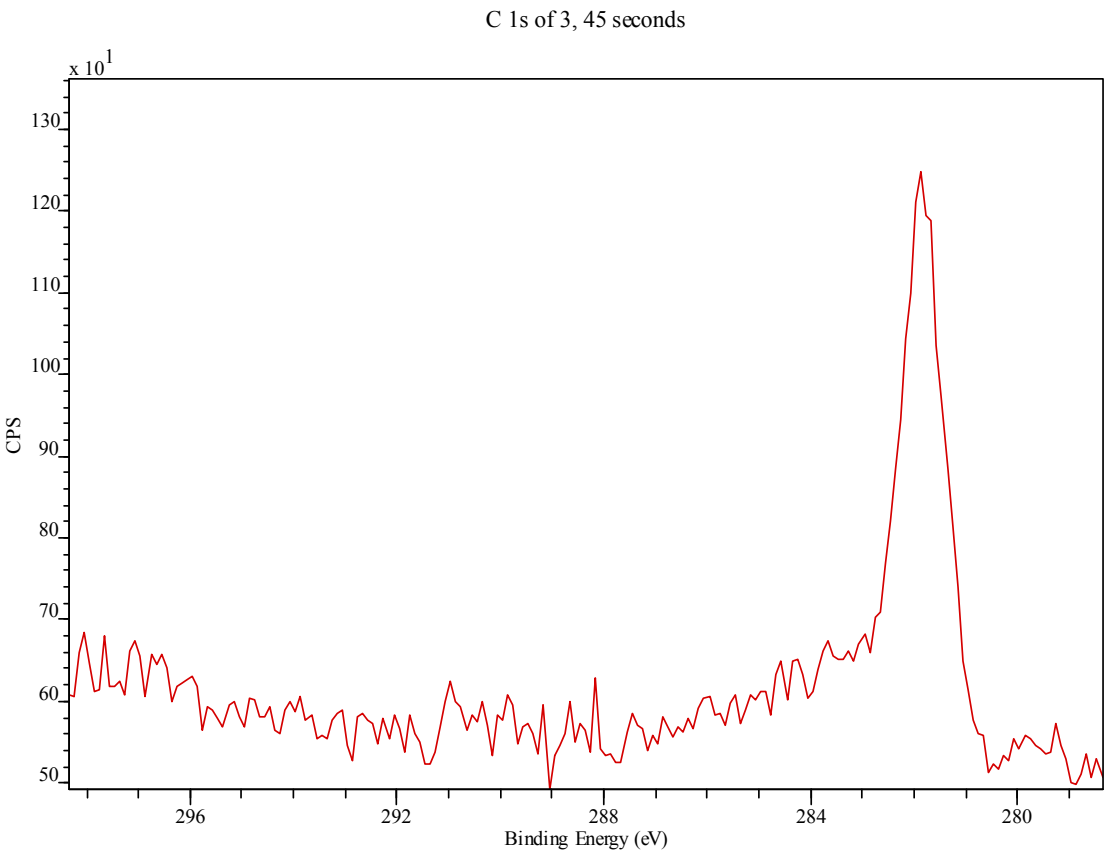


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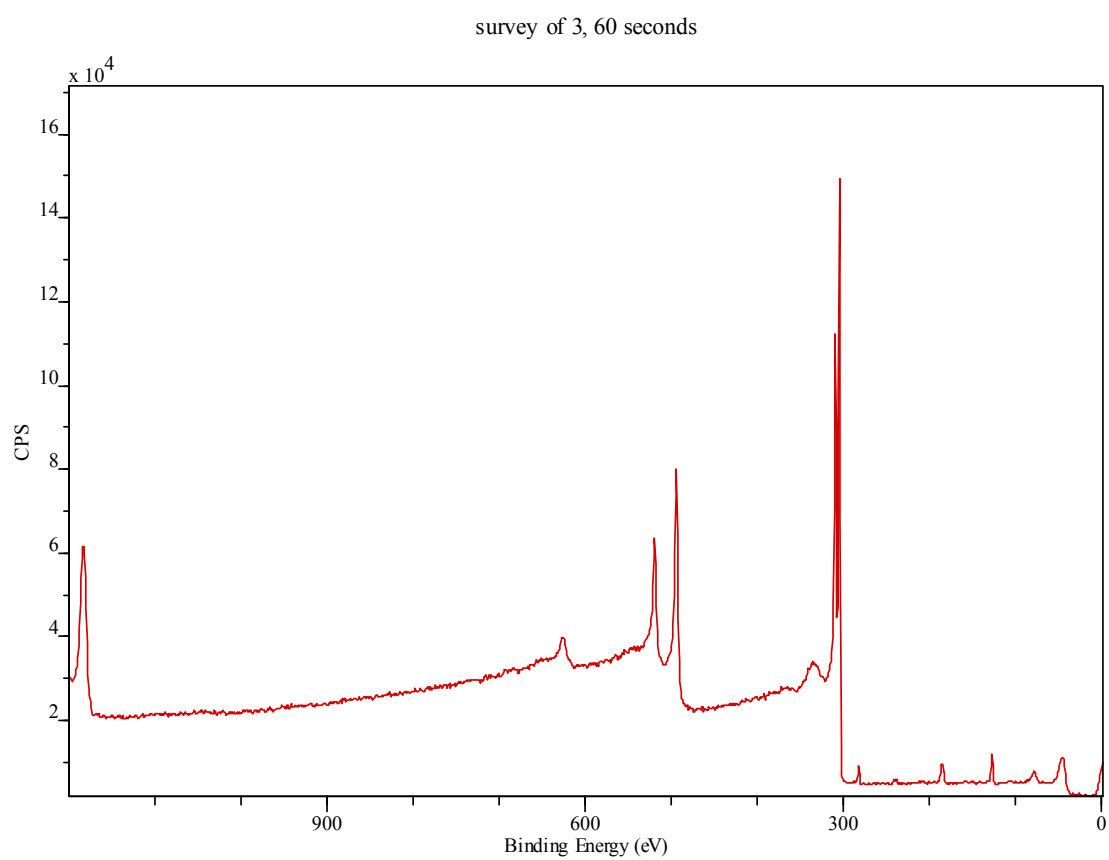


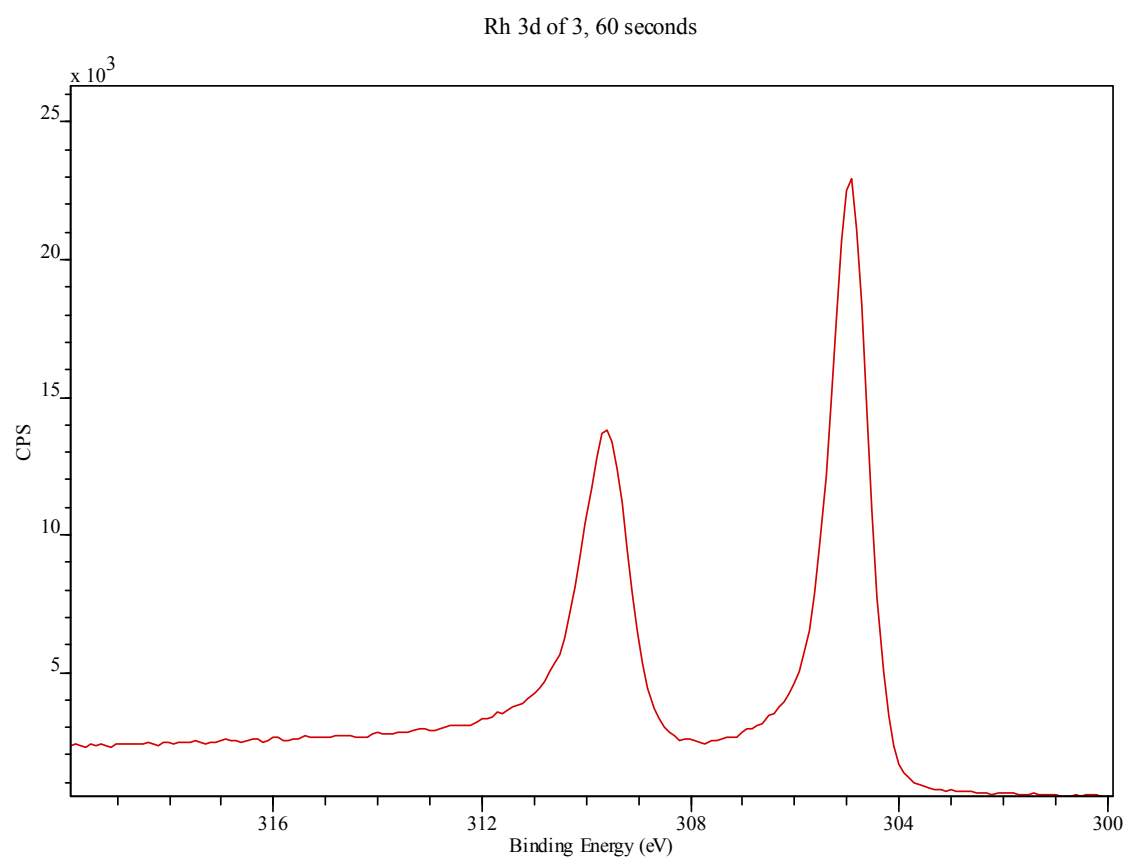


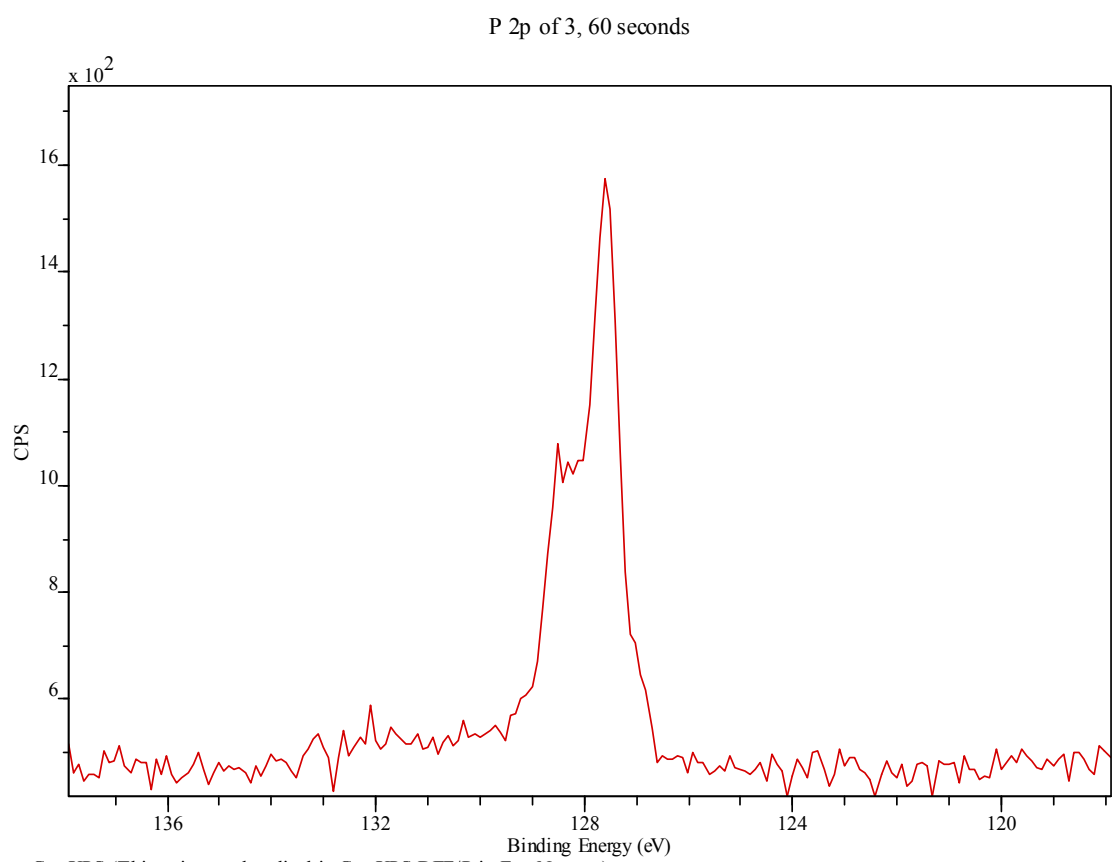


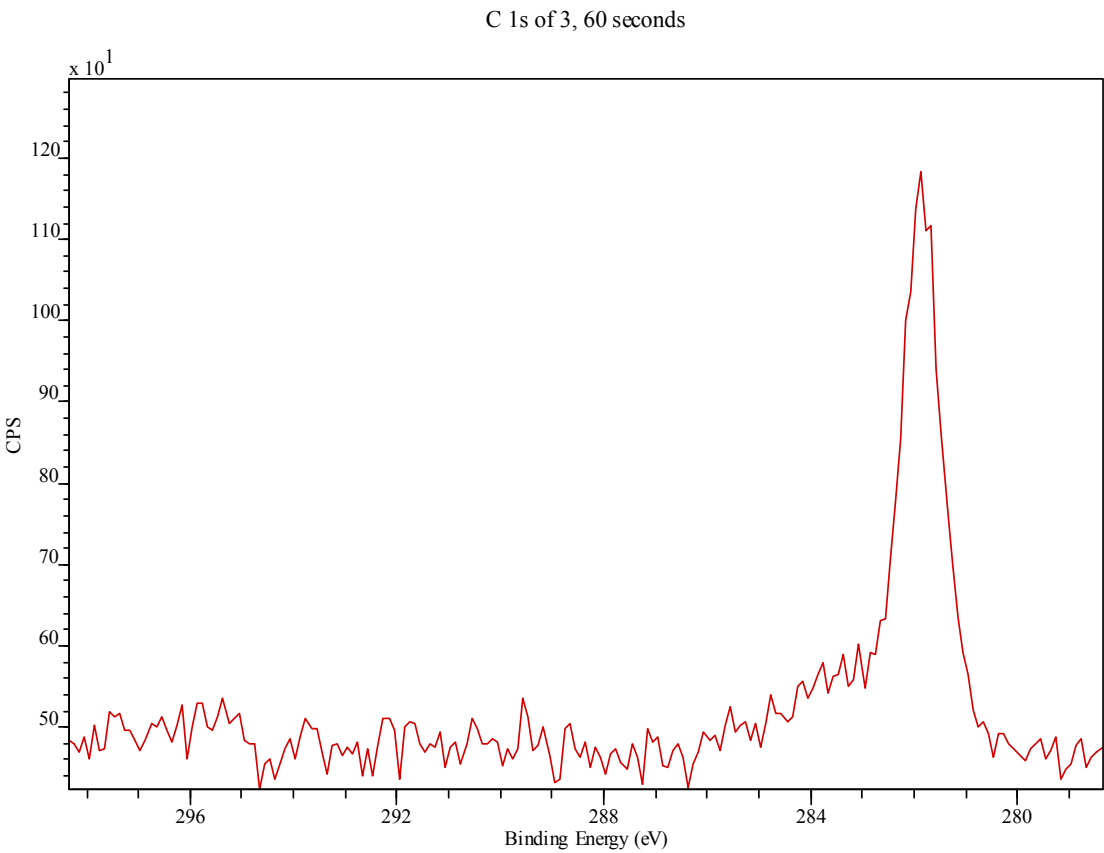


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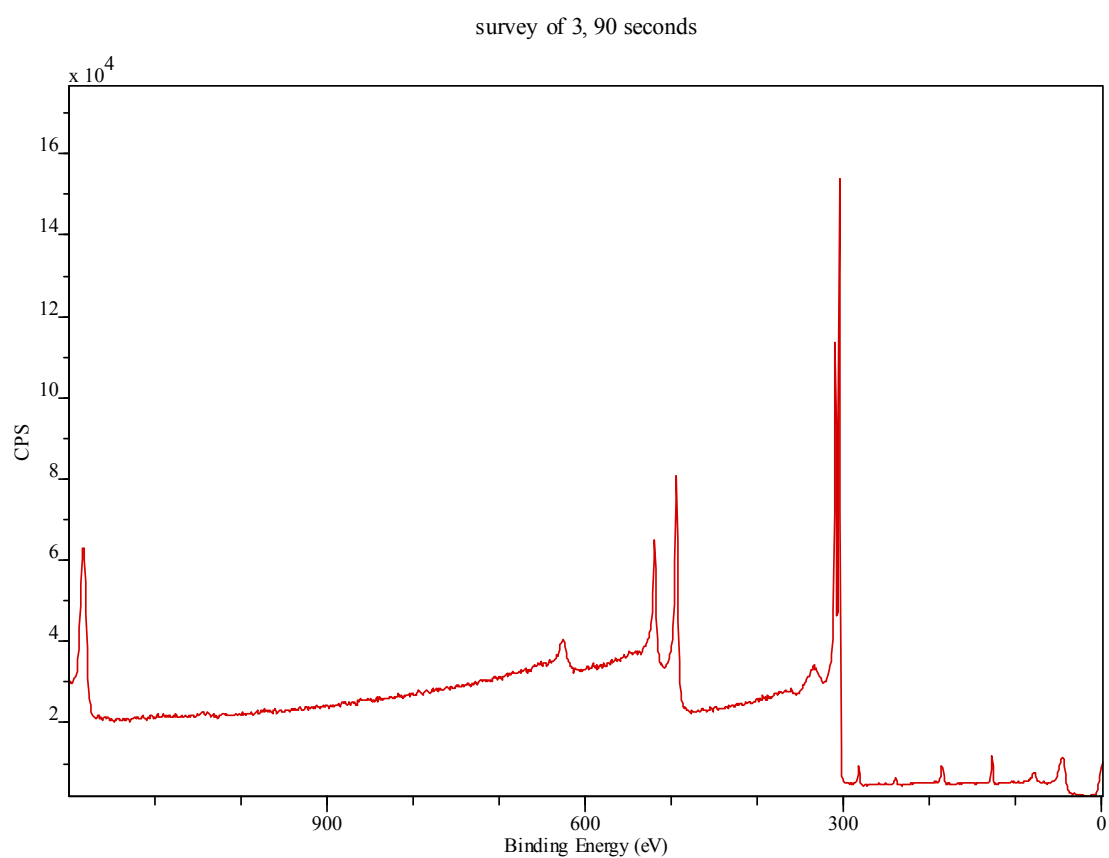


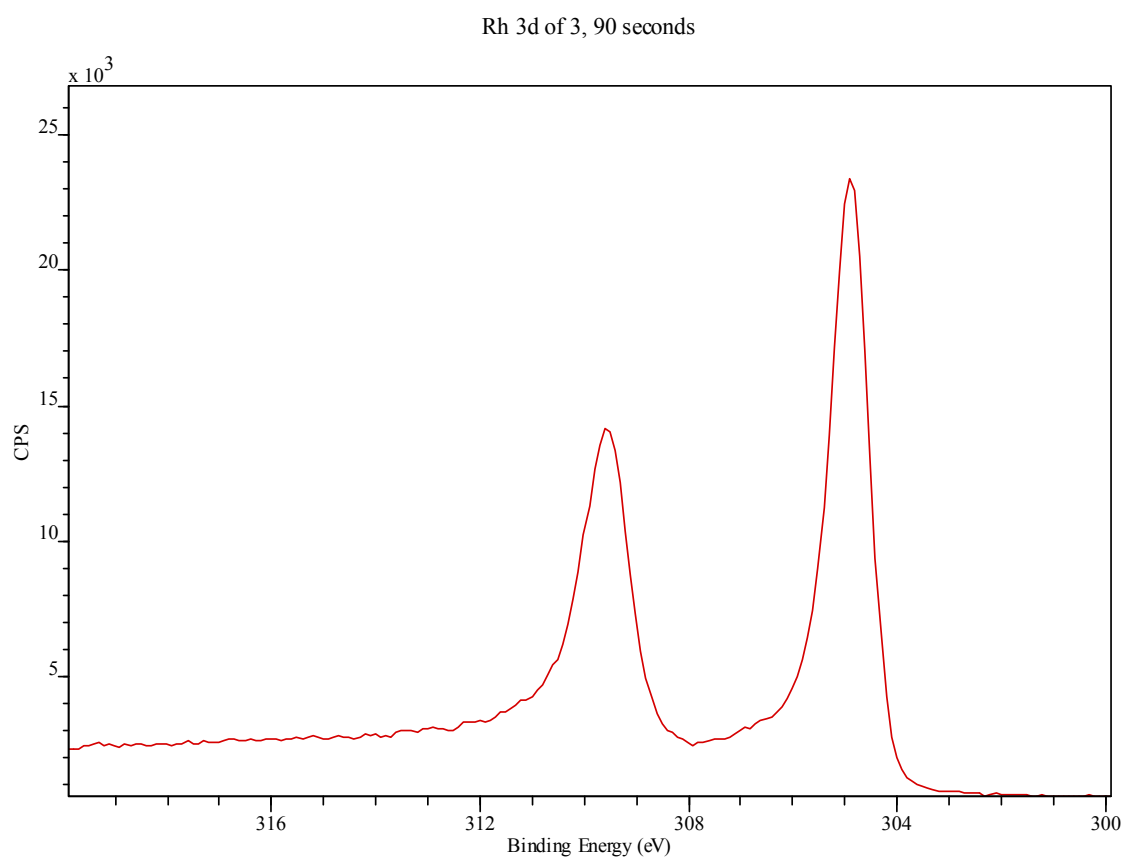


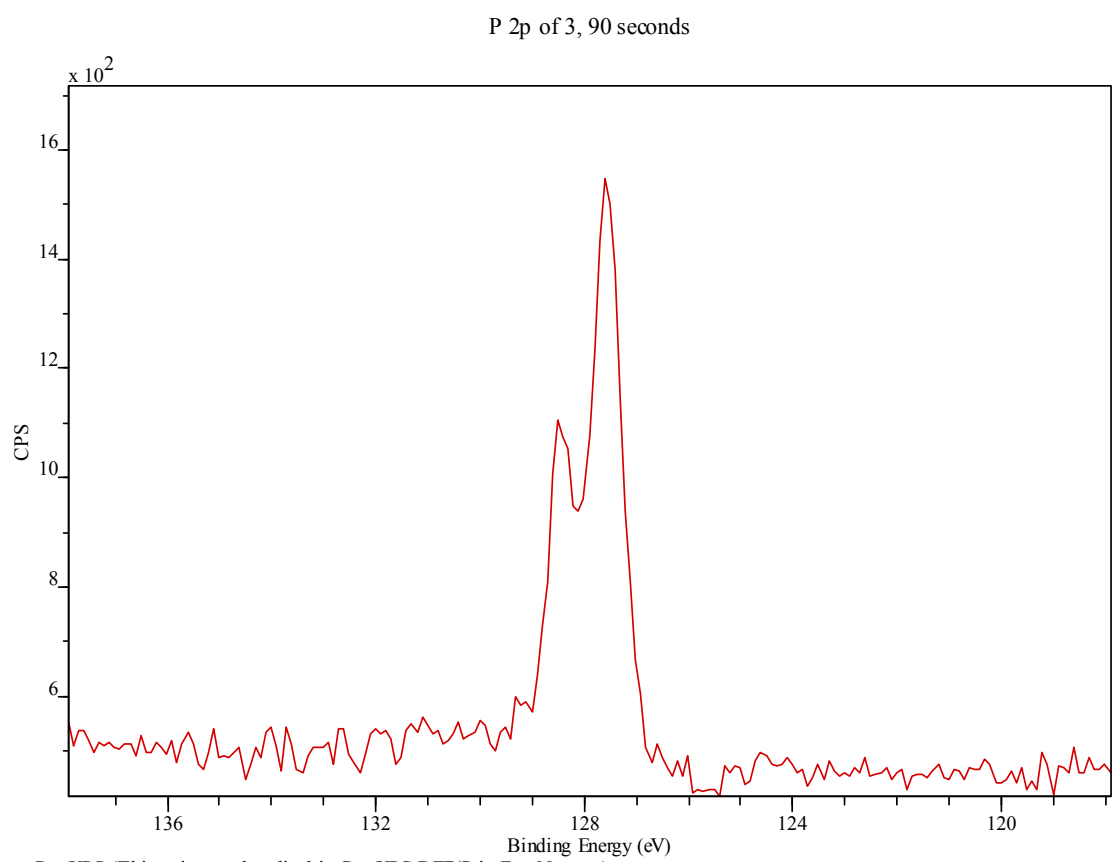


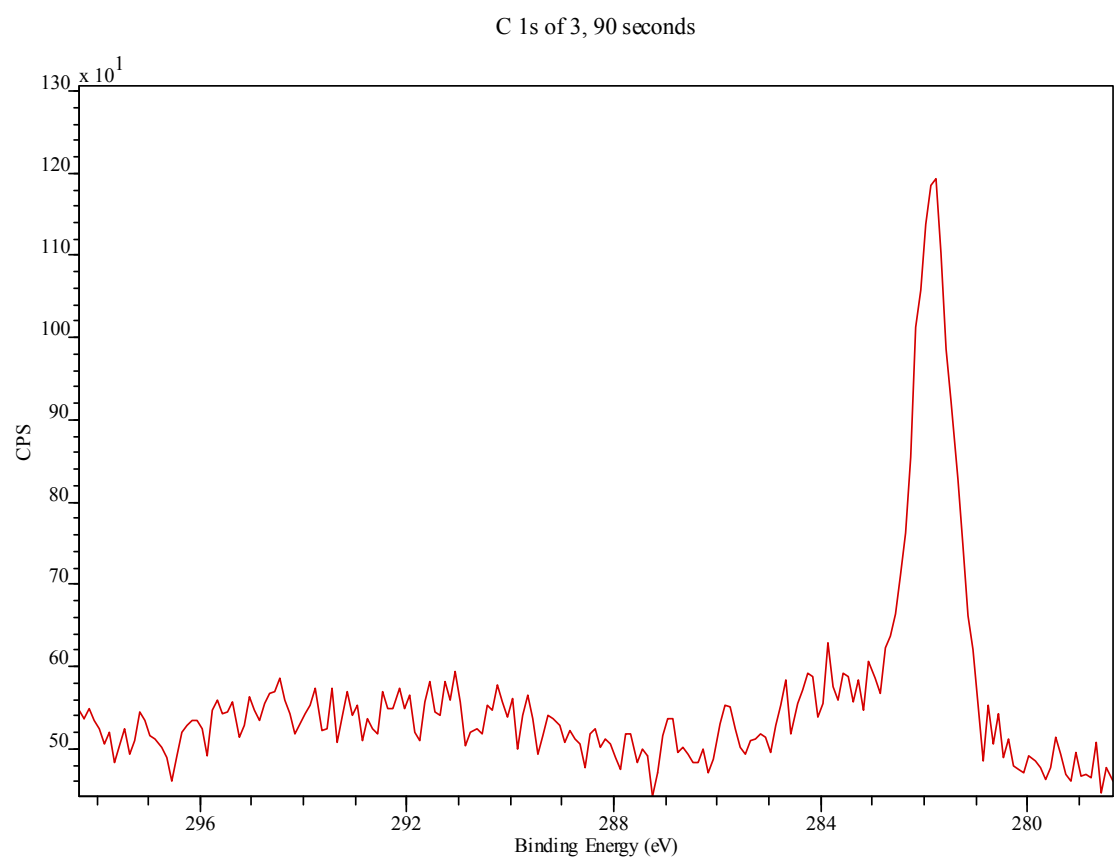


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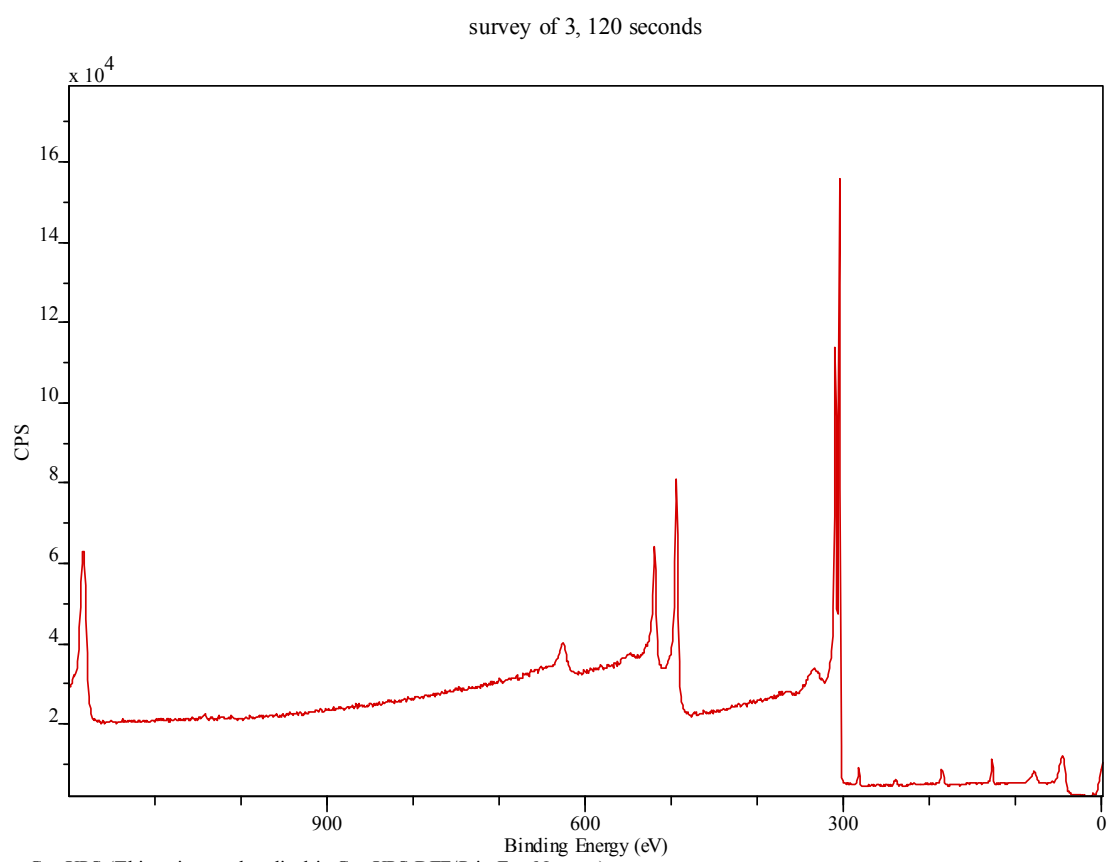


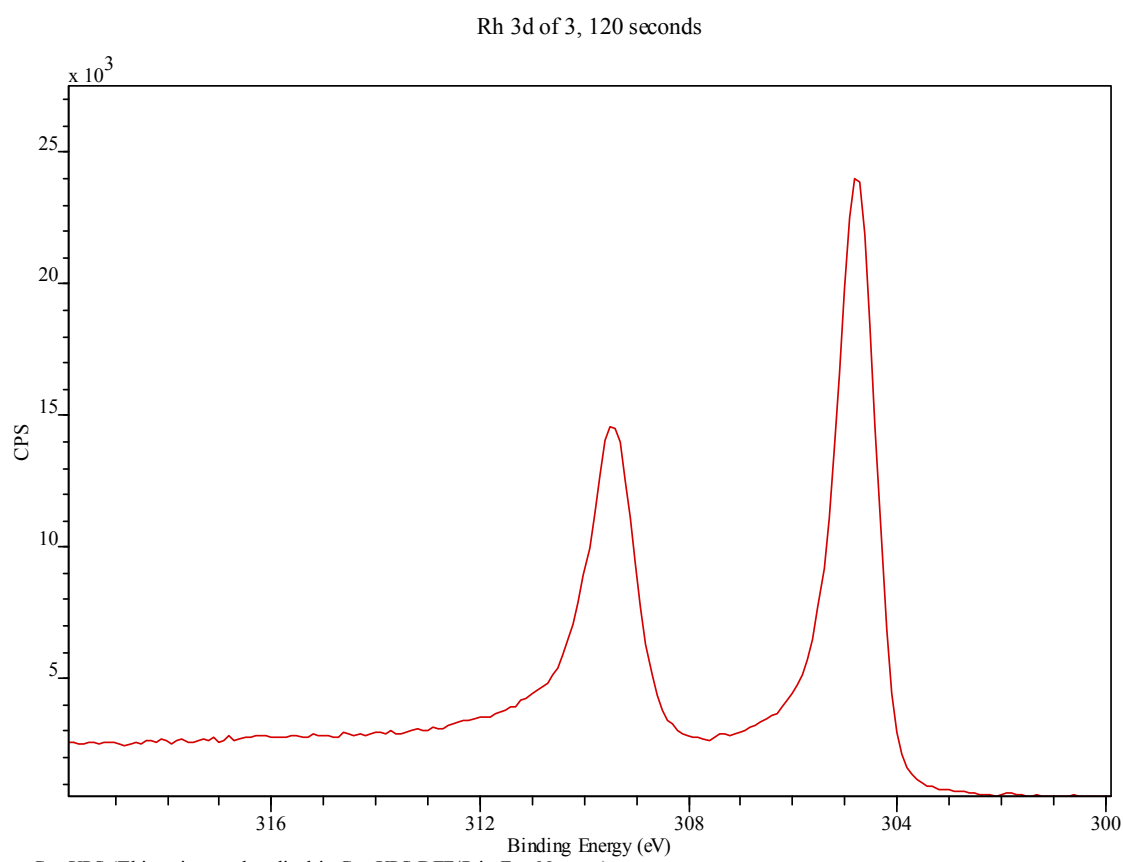


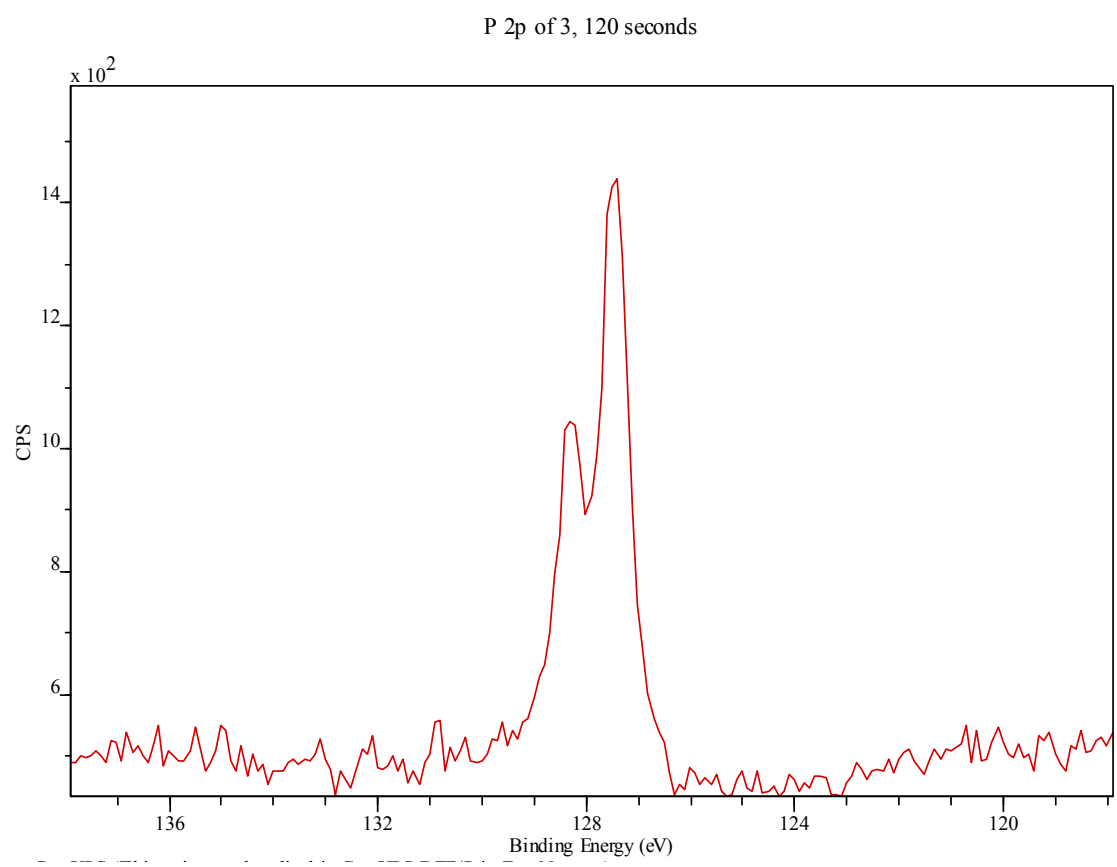


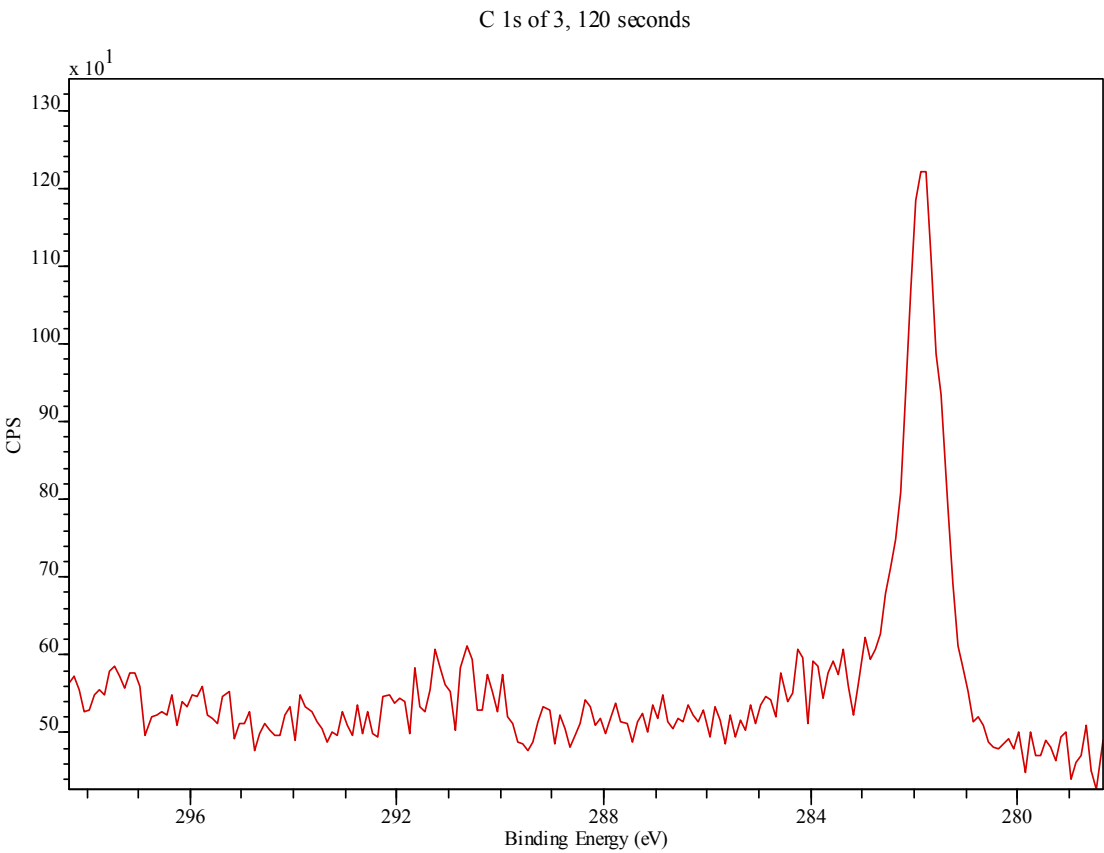


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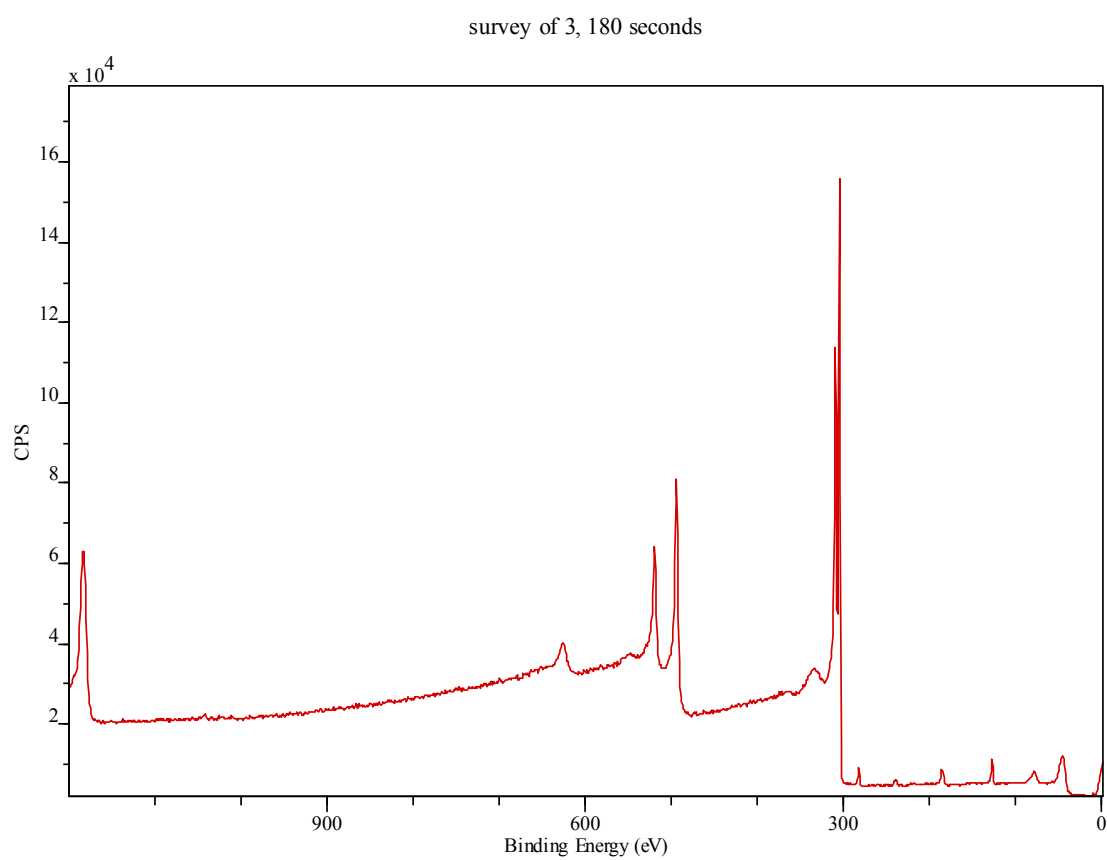


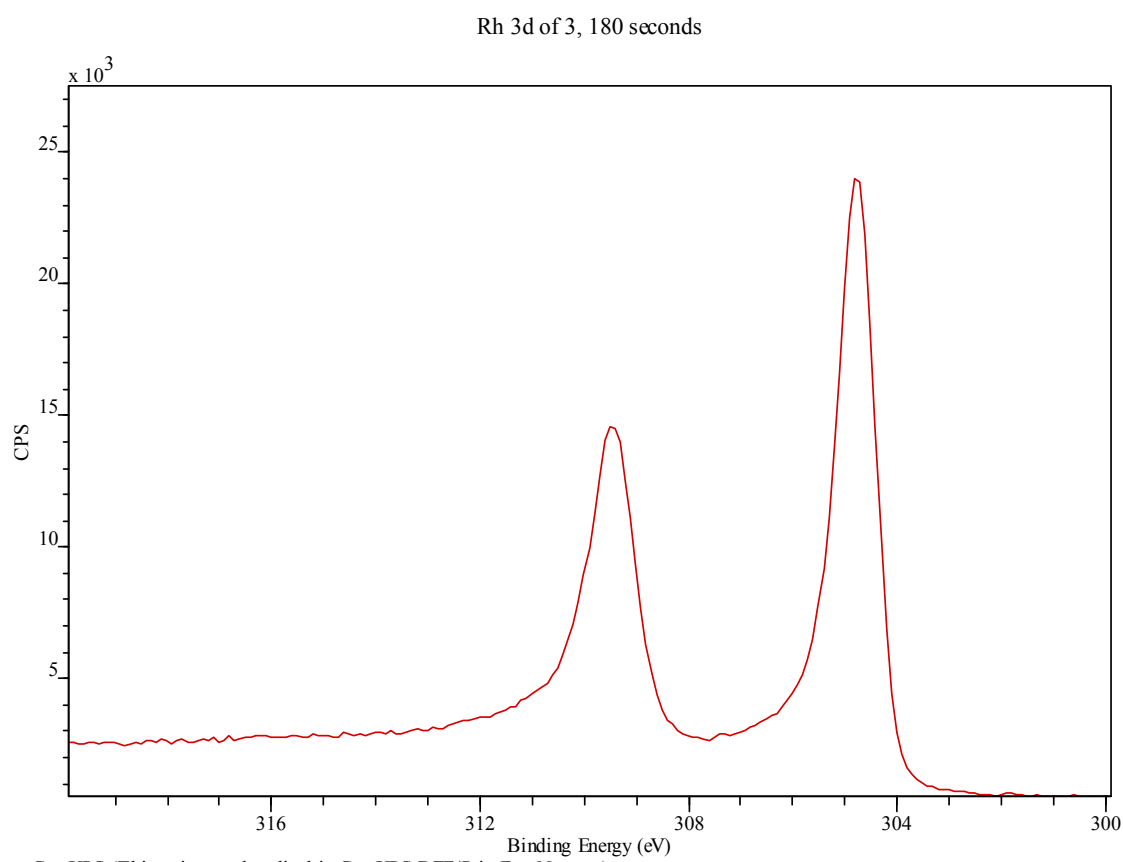


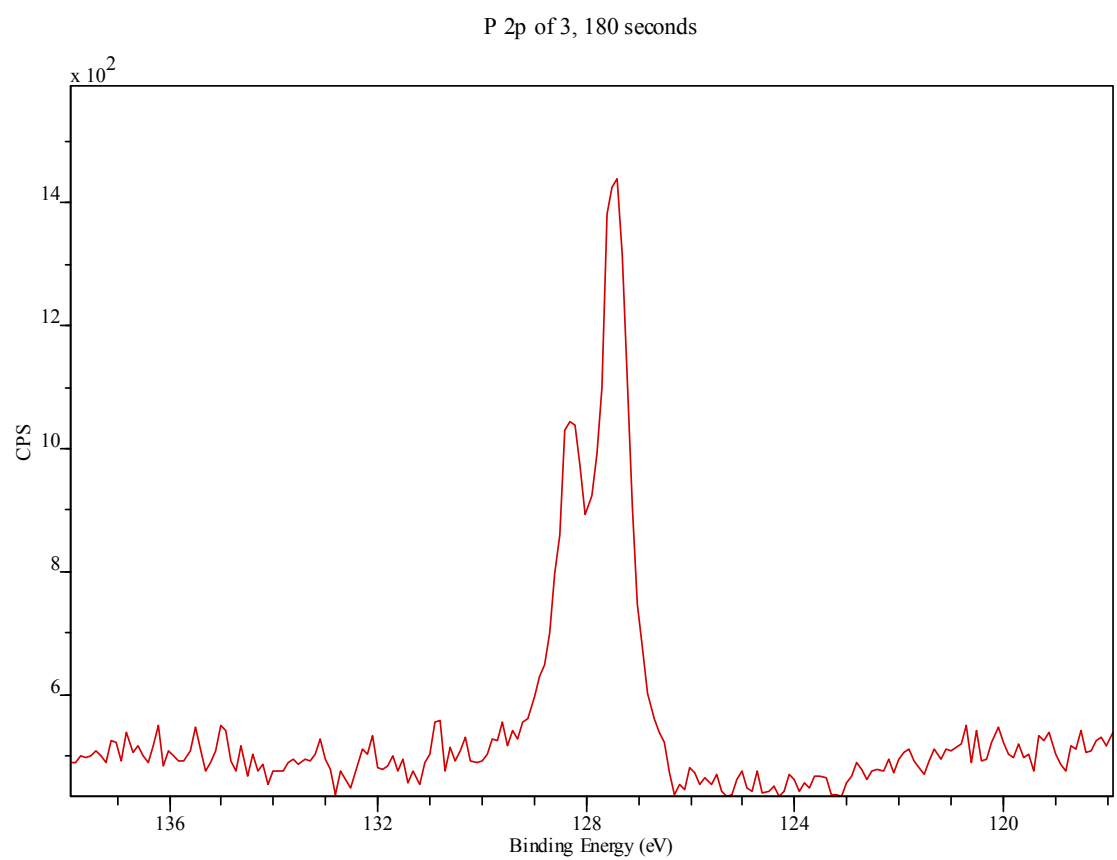


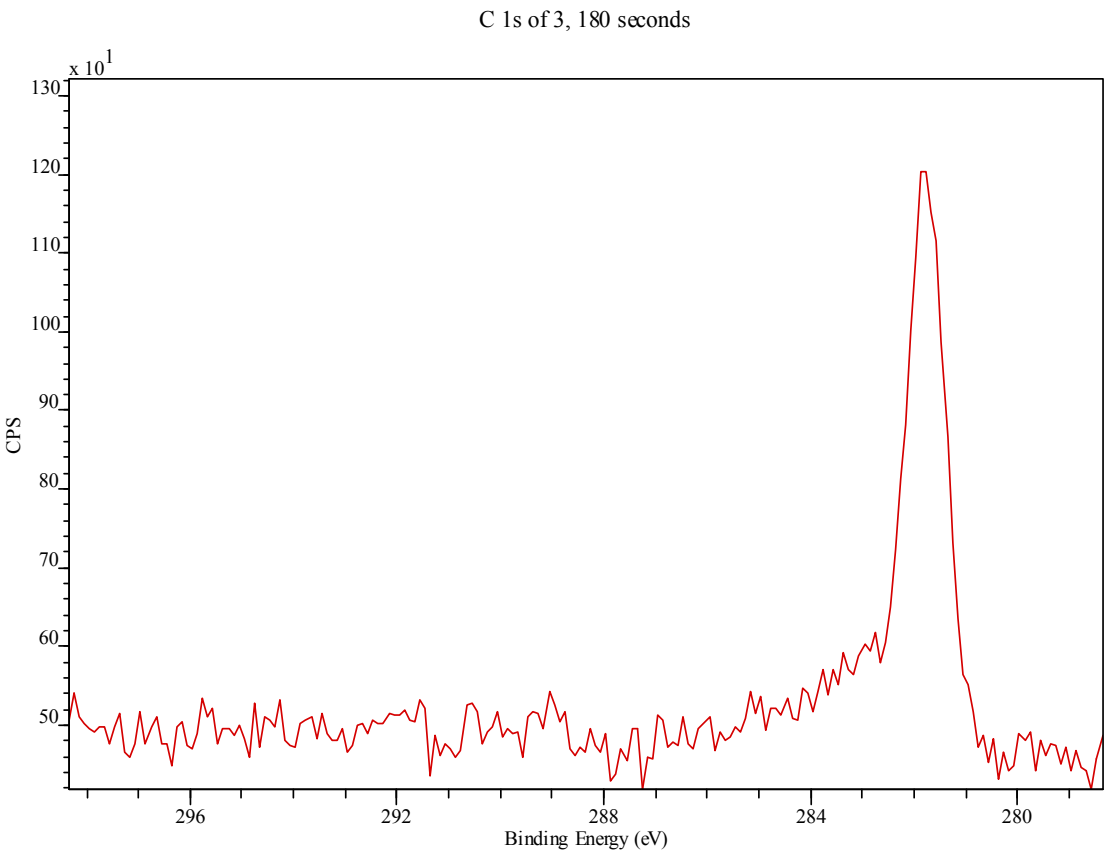


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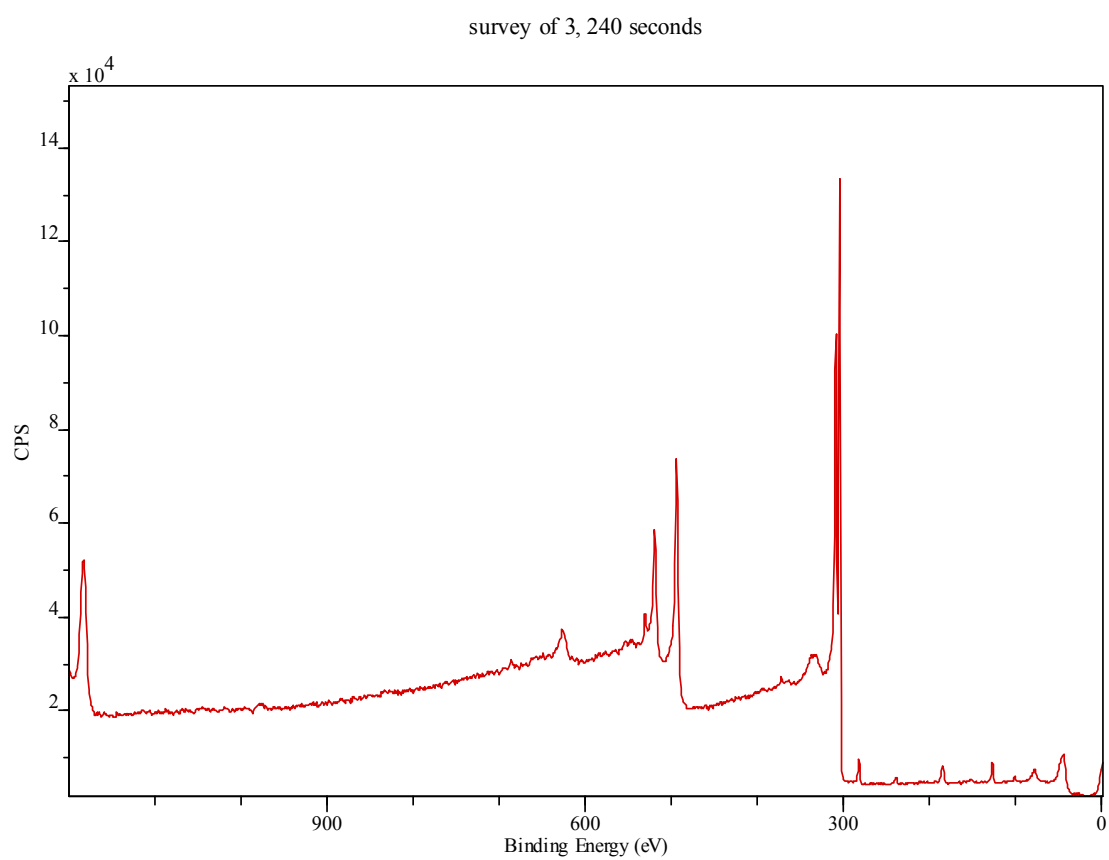


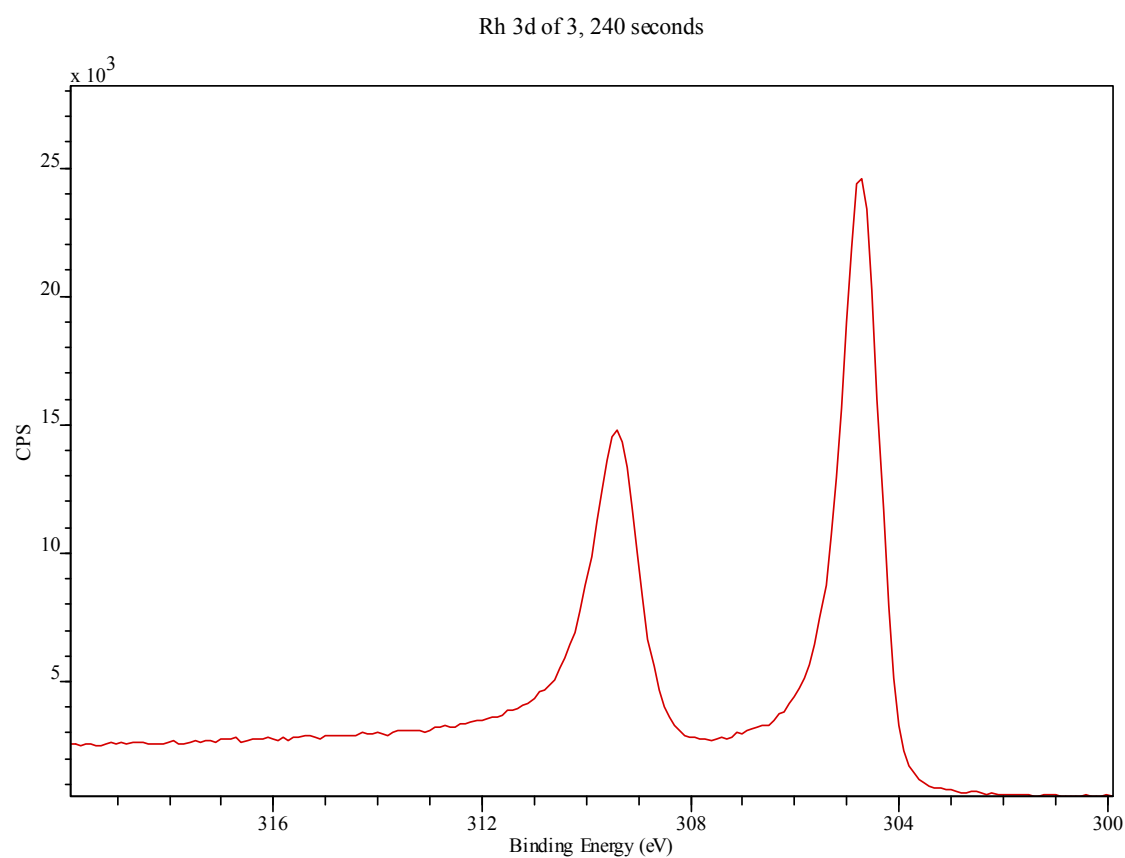


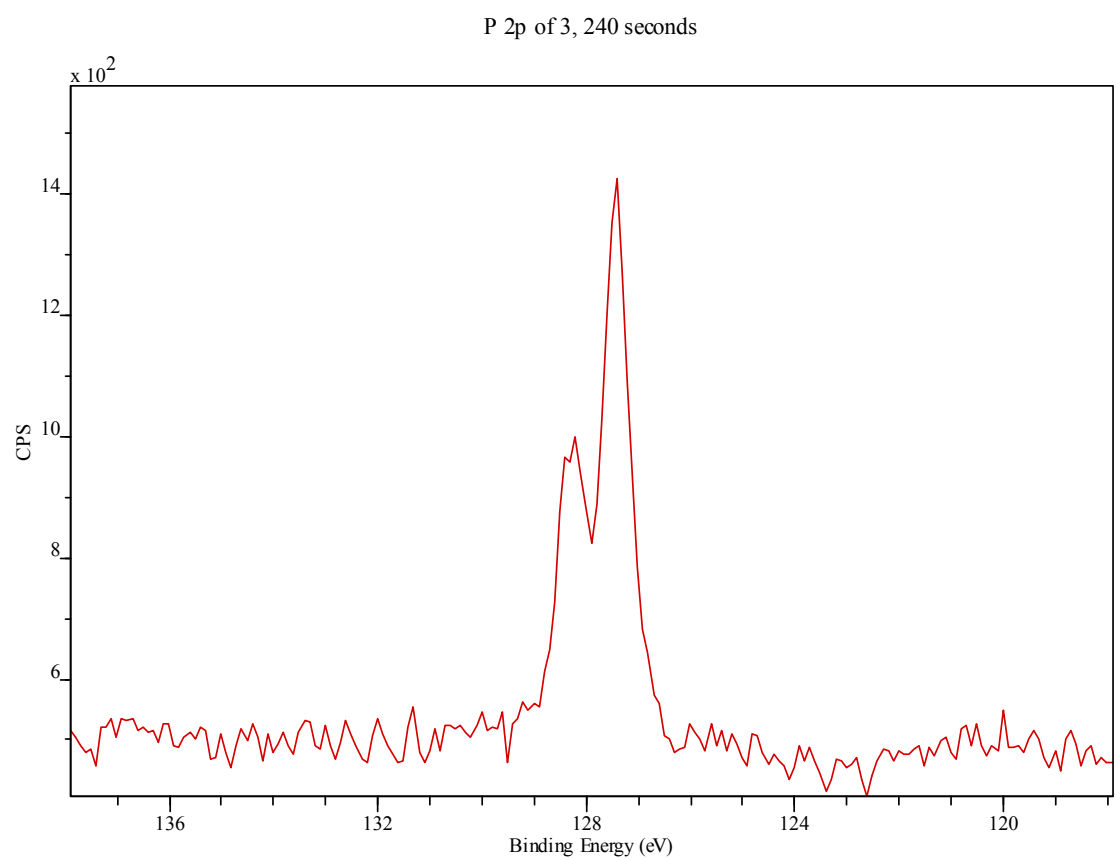


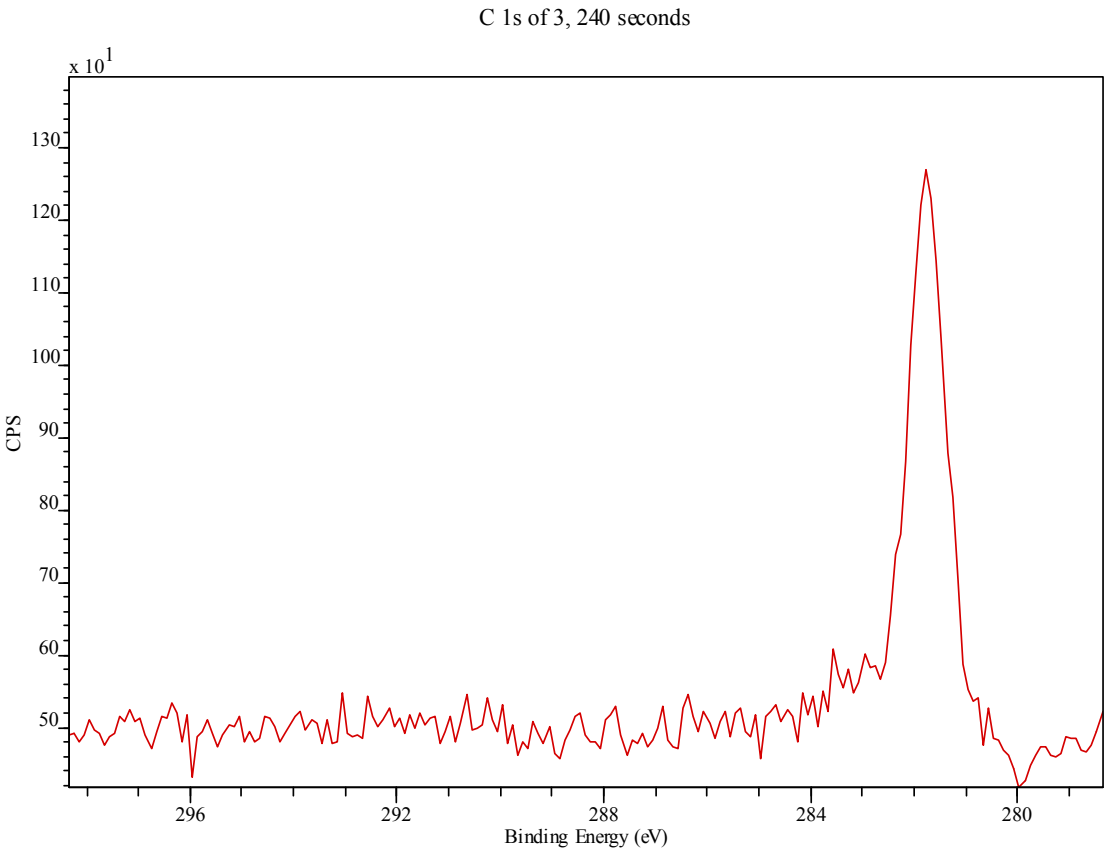


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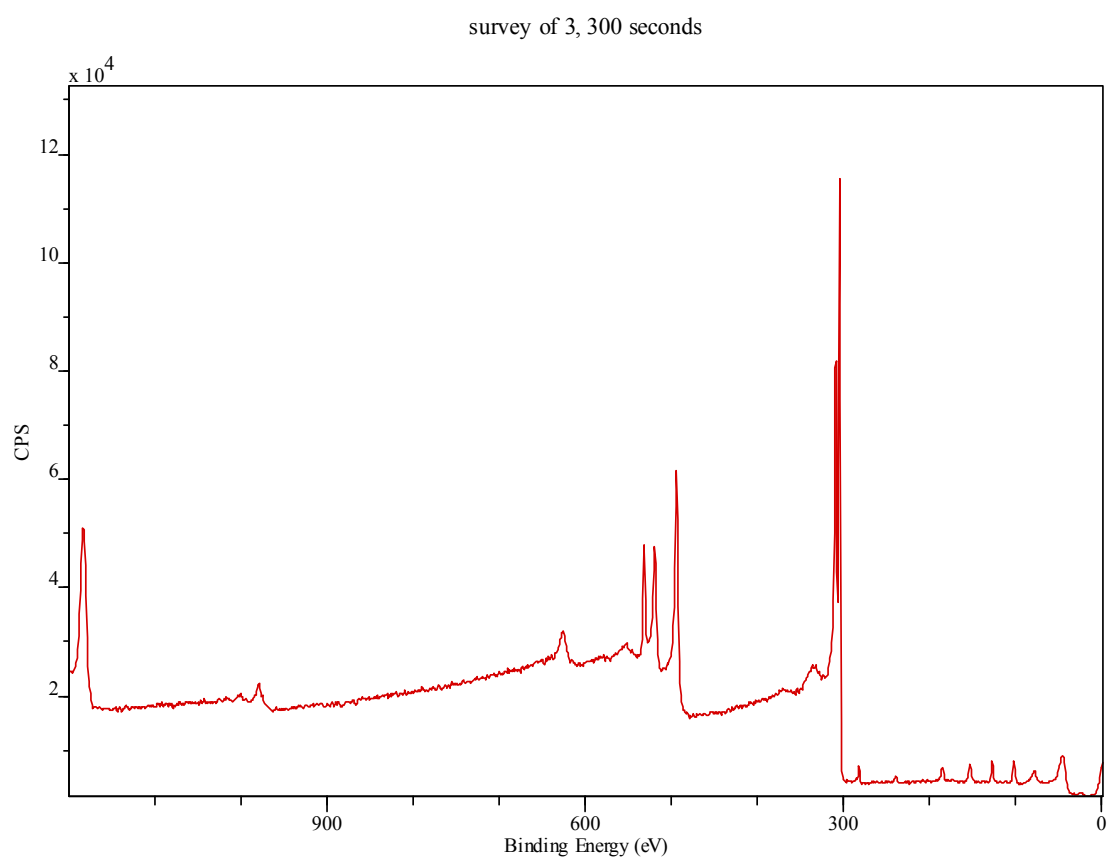


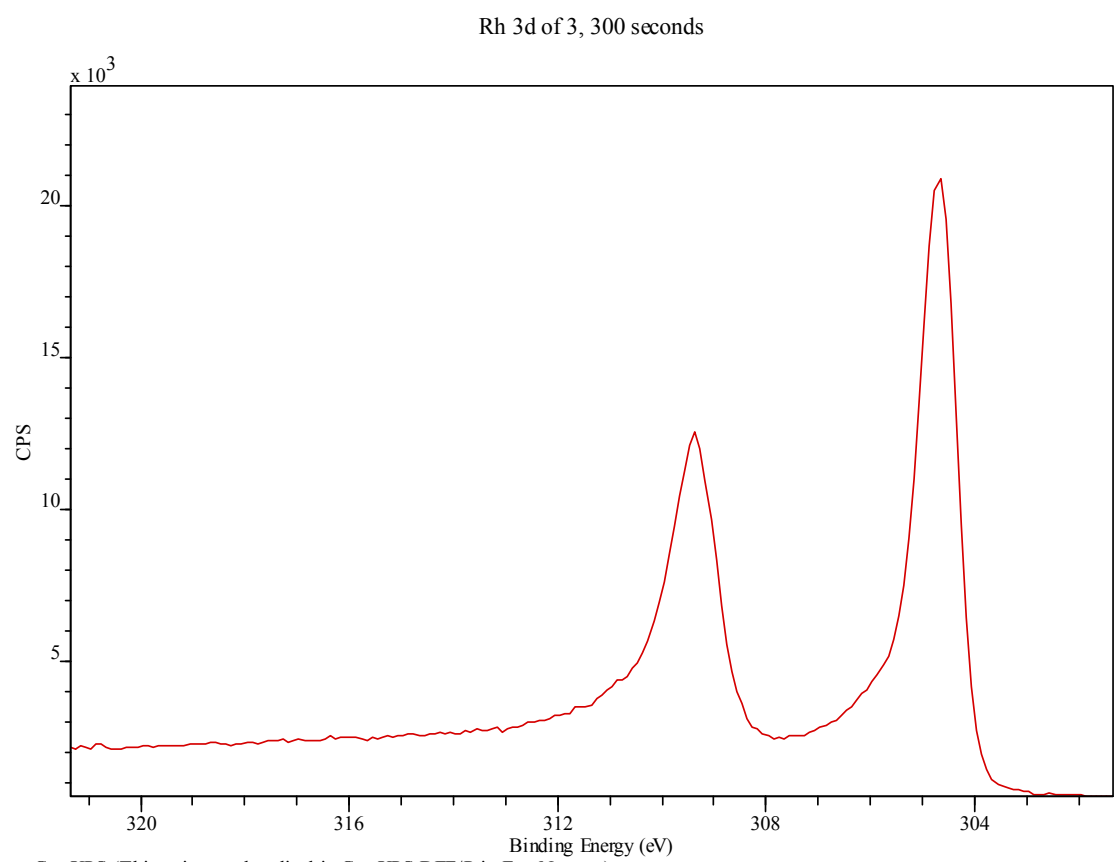


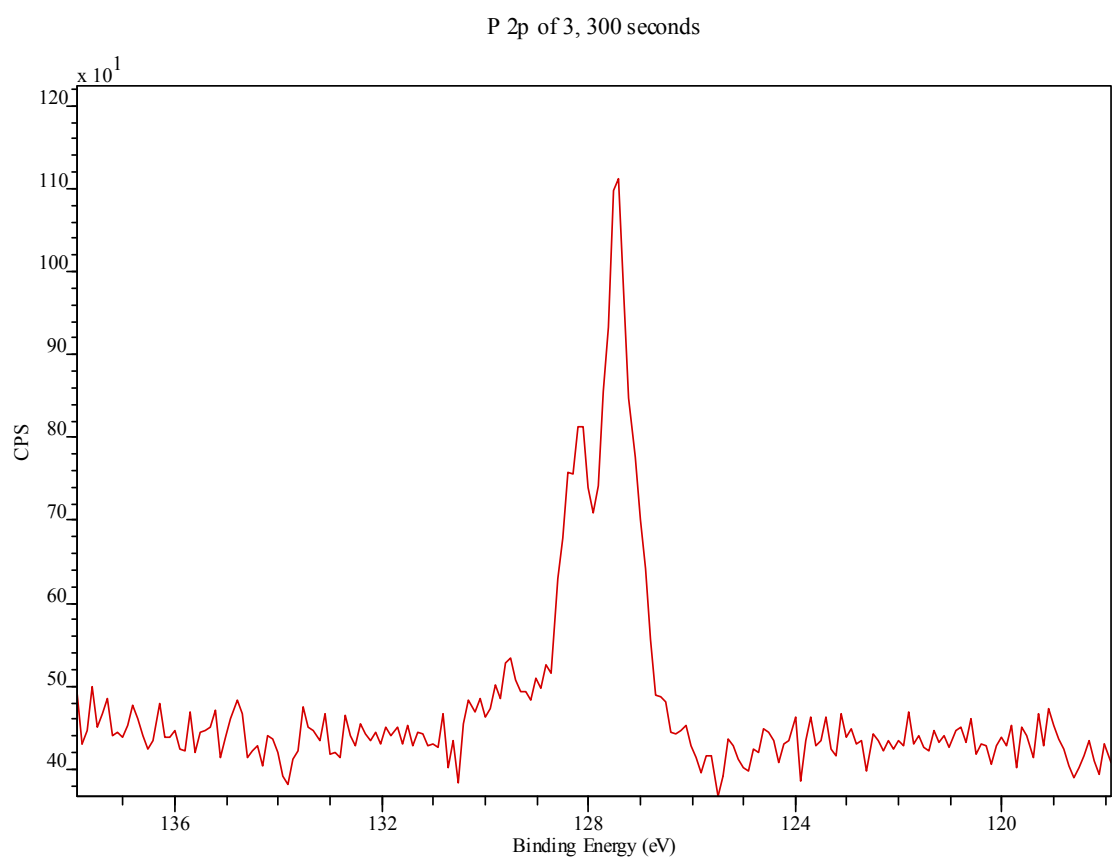


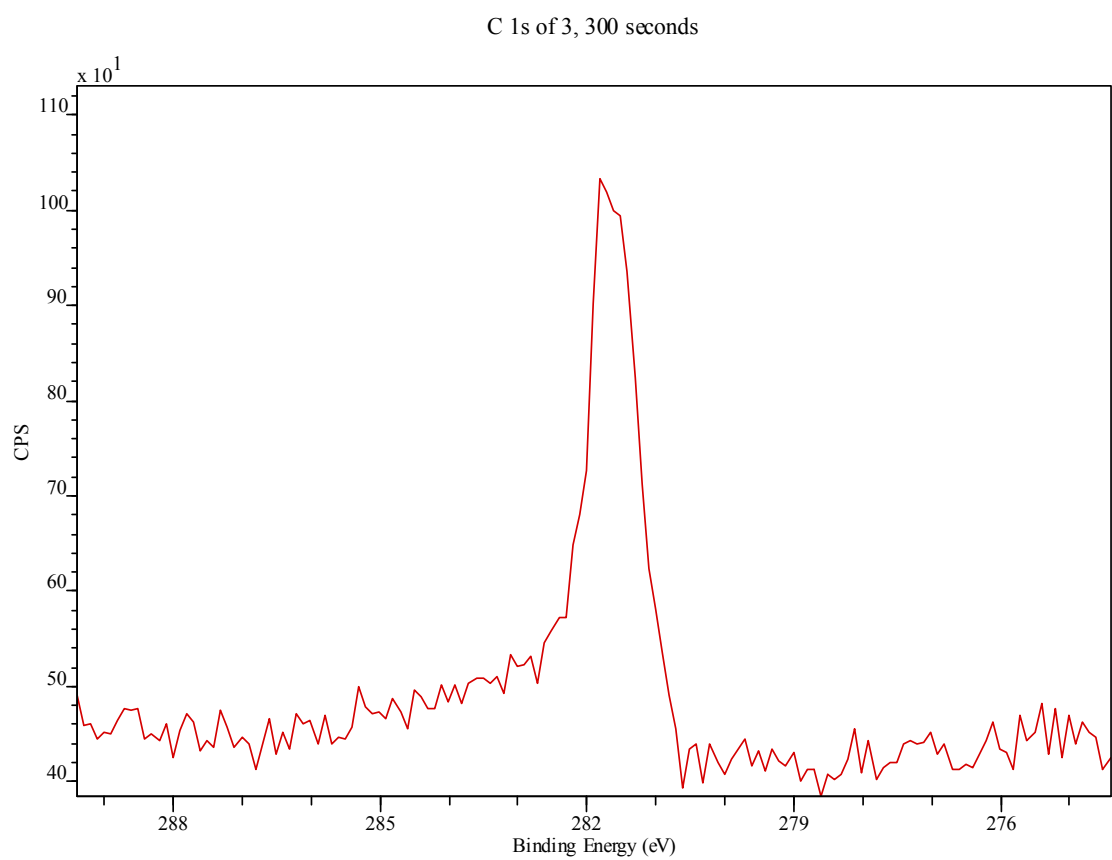


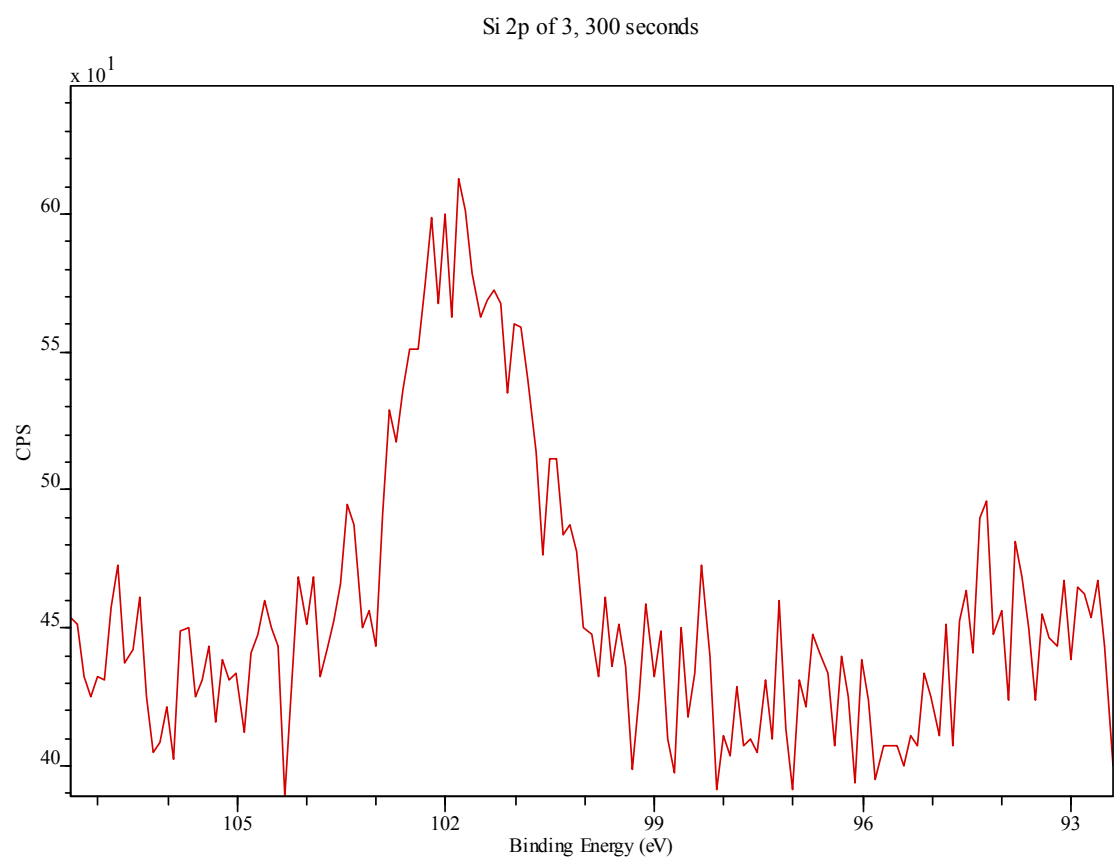
300 seconds of sputtering:



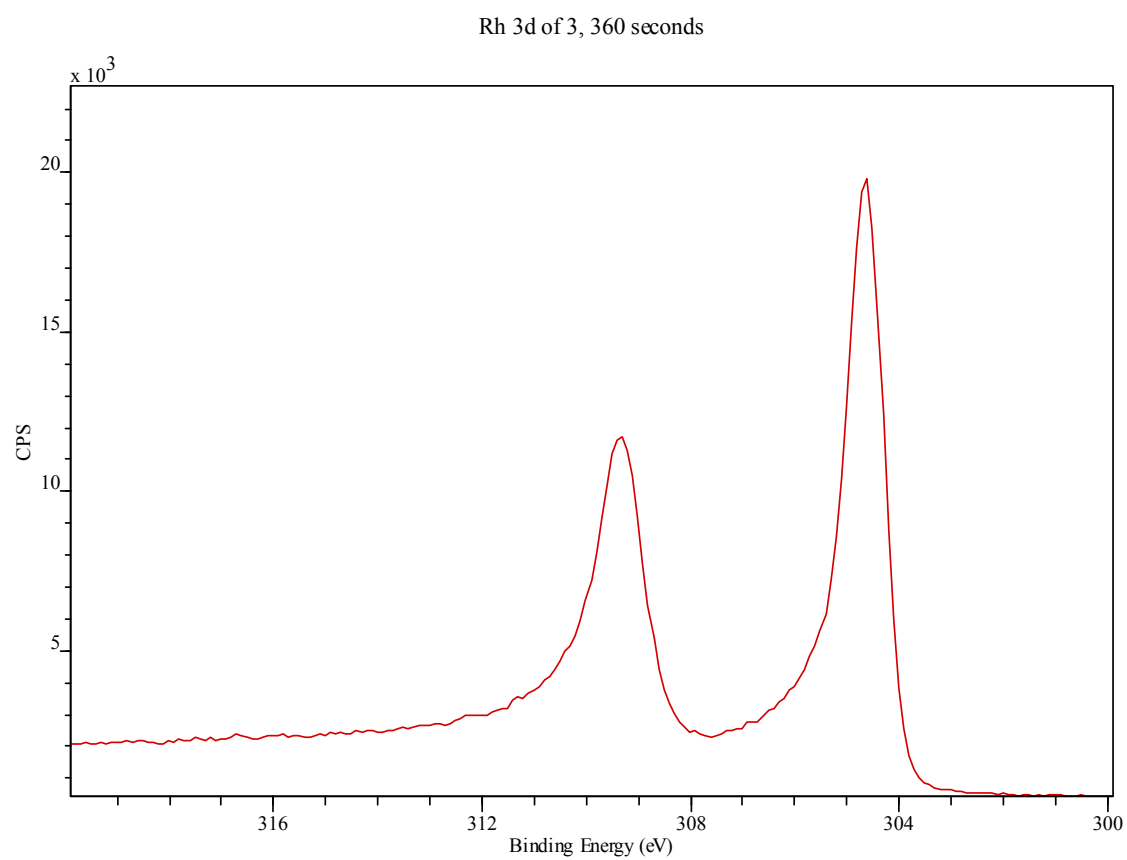


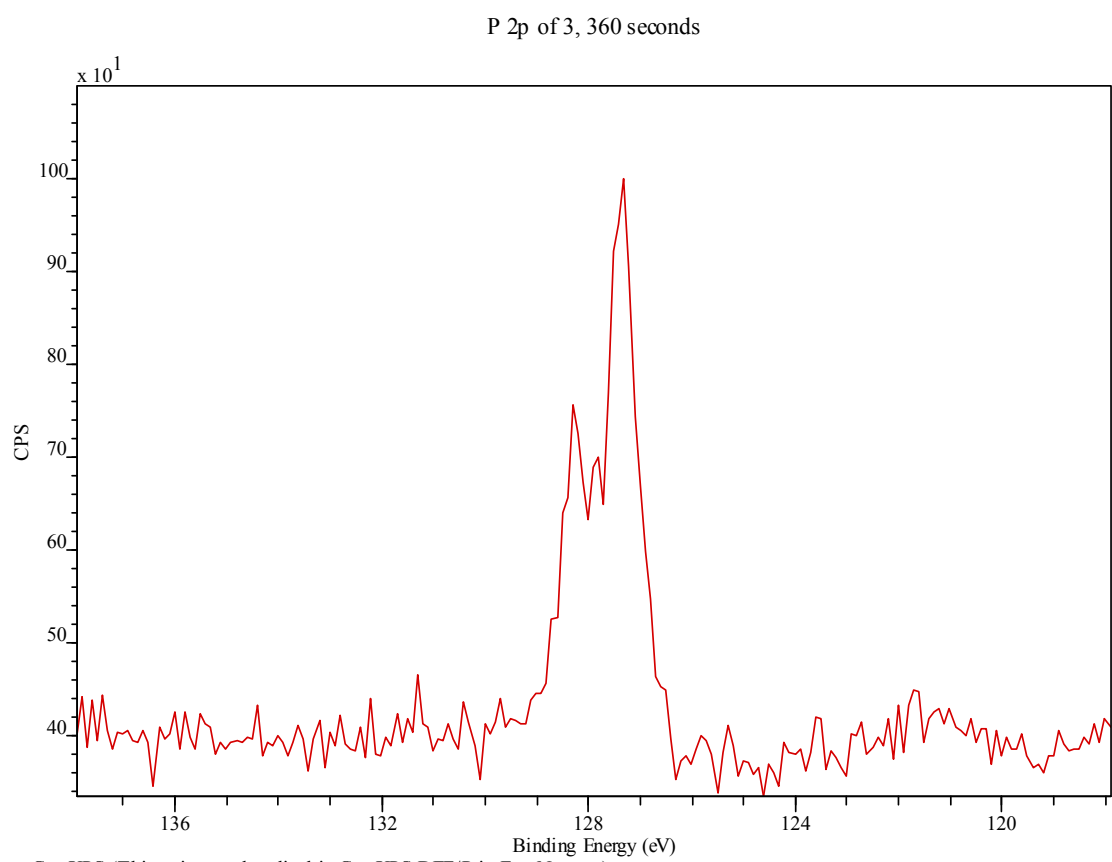


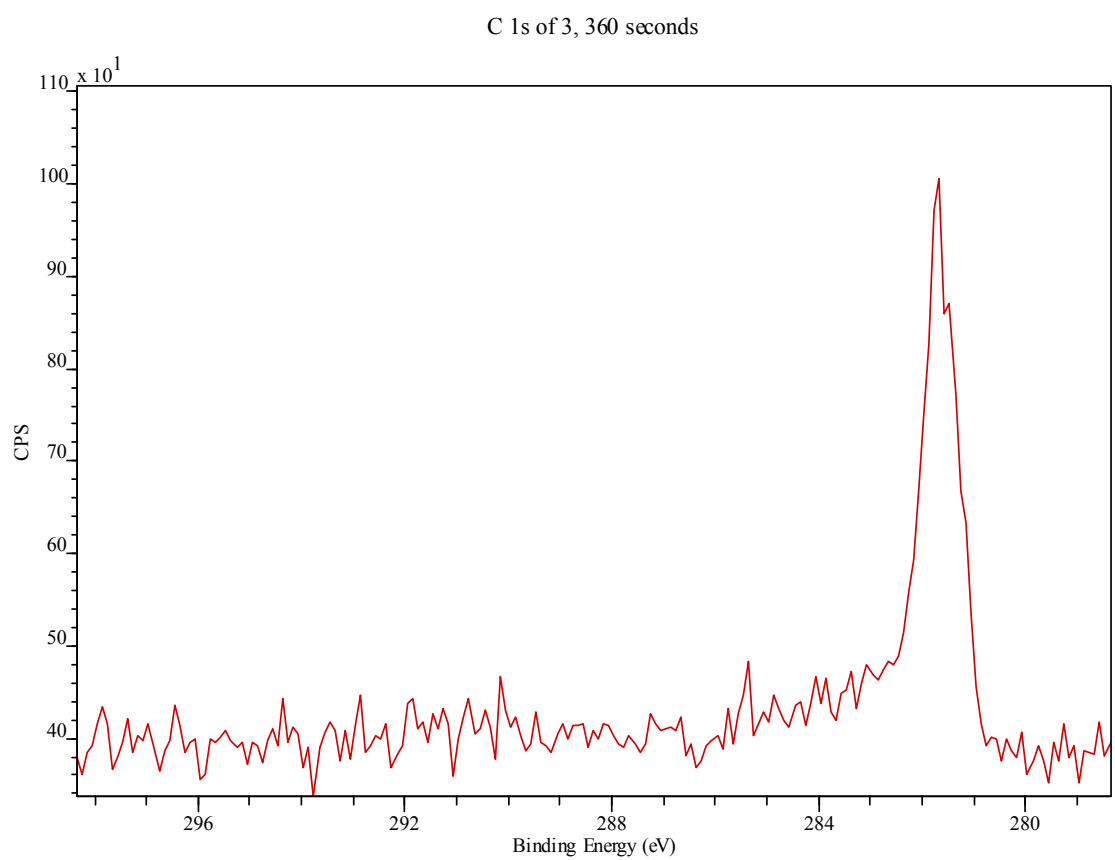


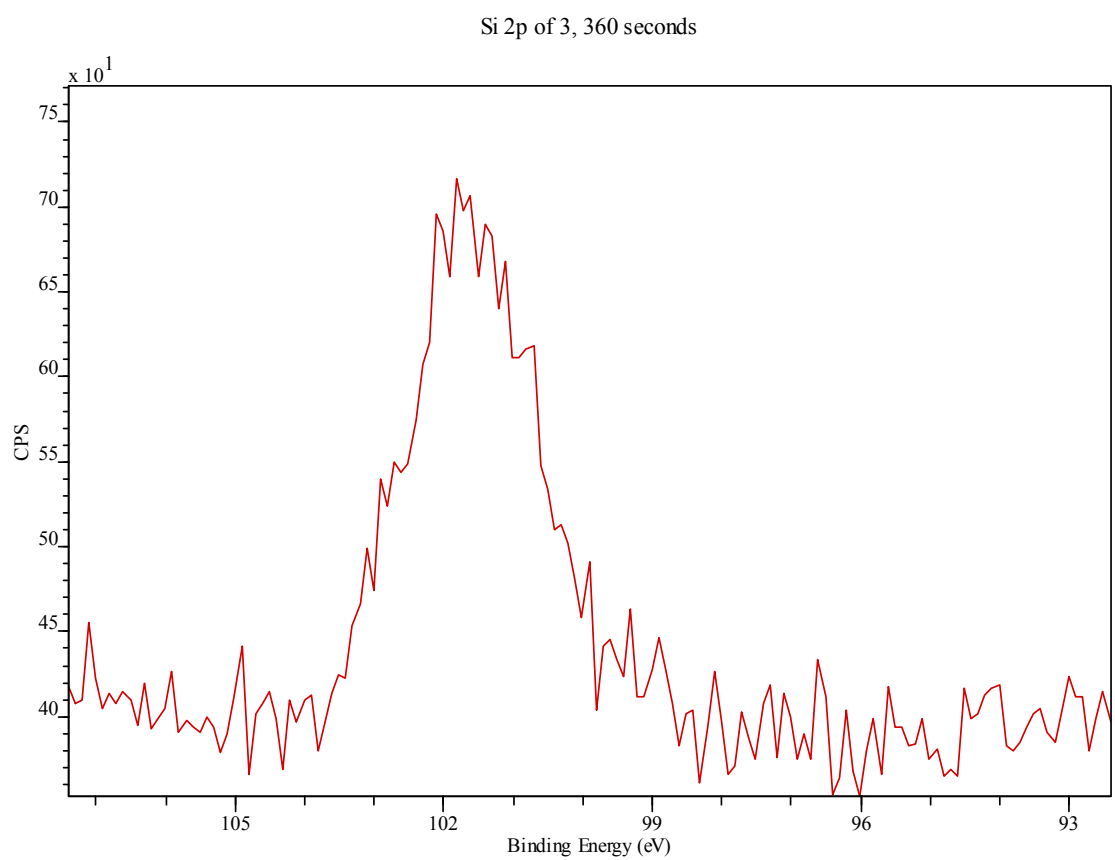


360 seconds of sputtering:

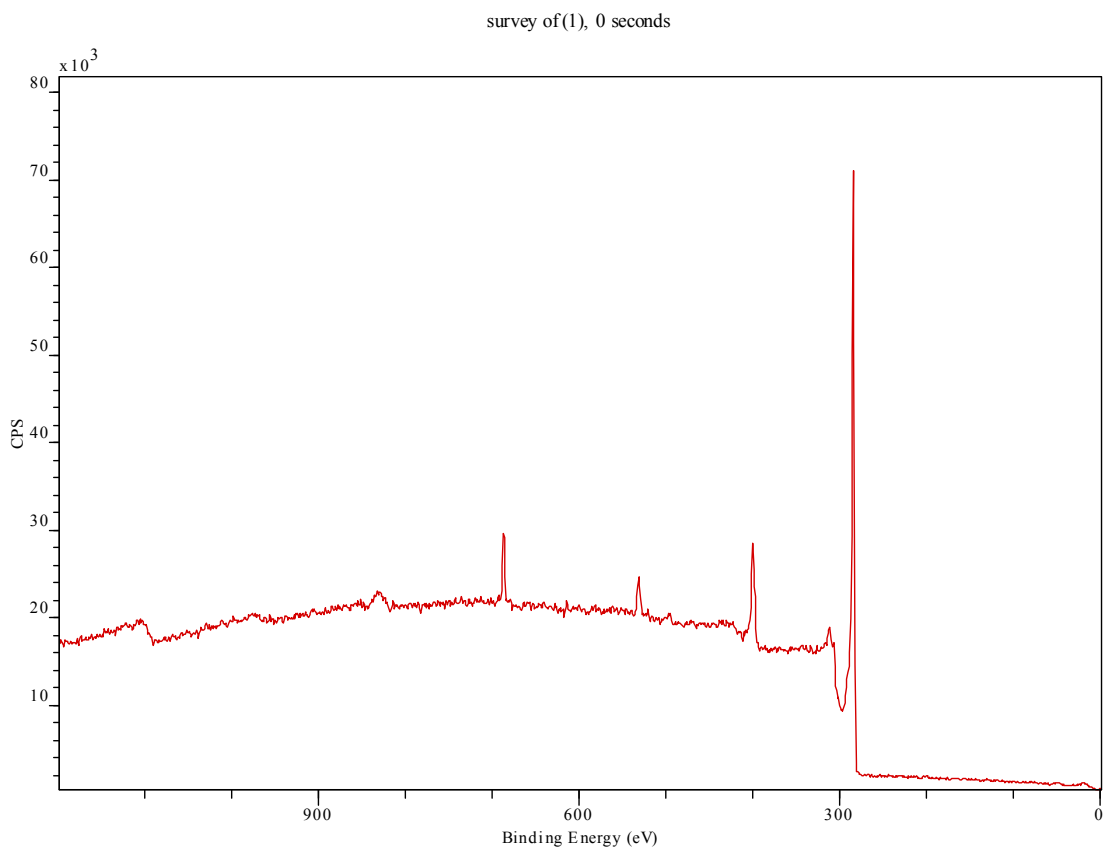


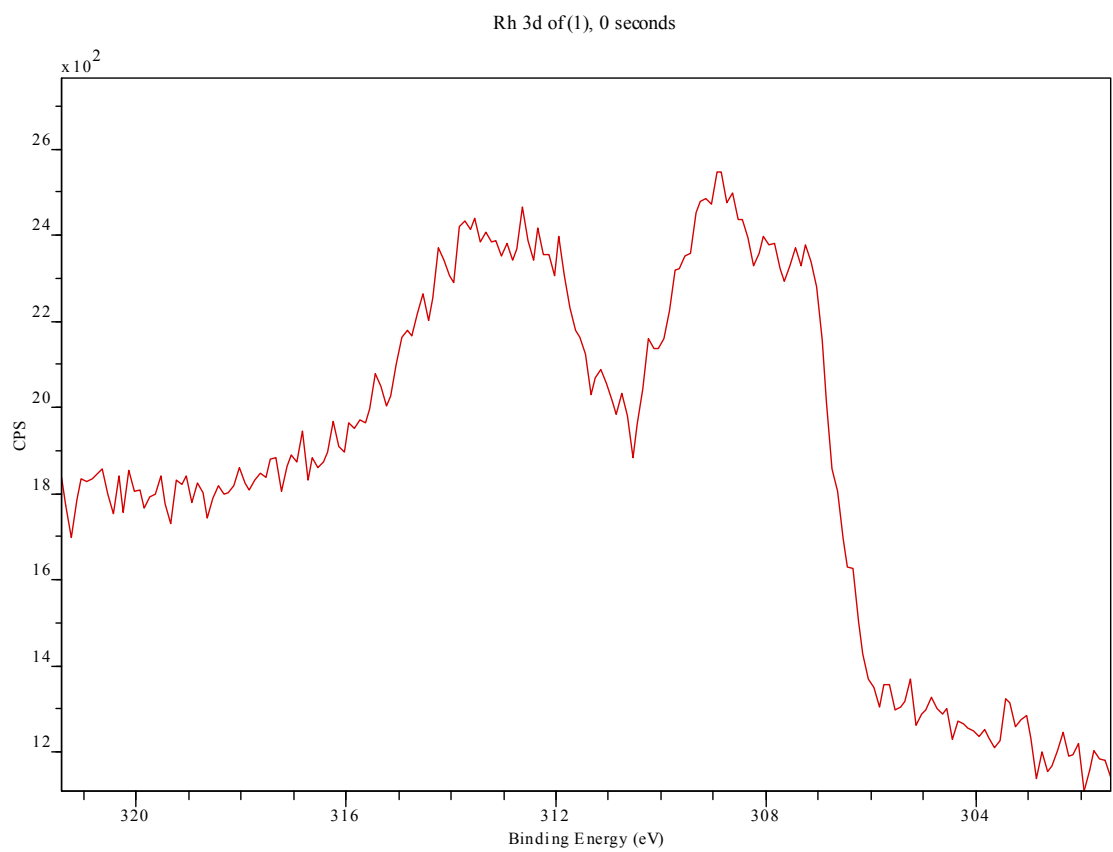


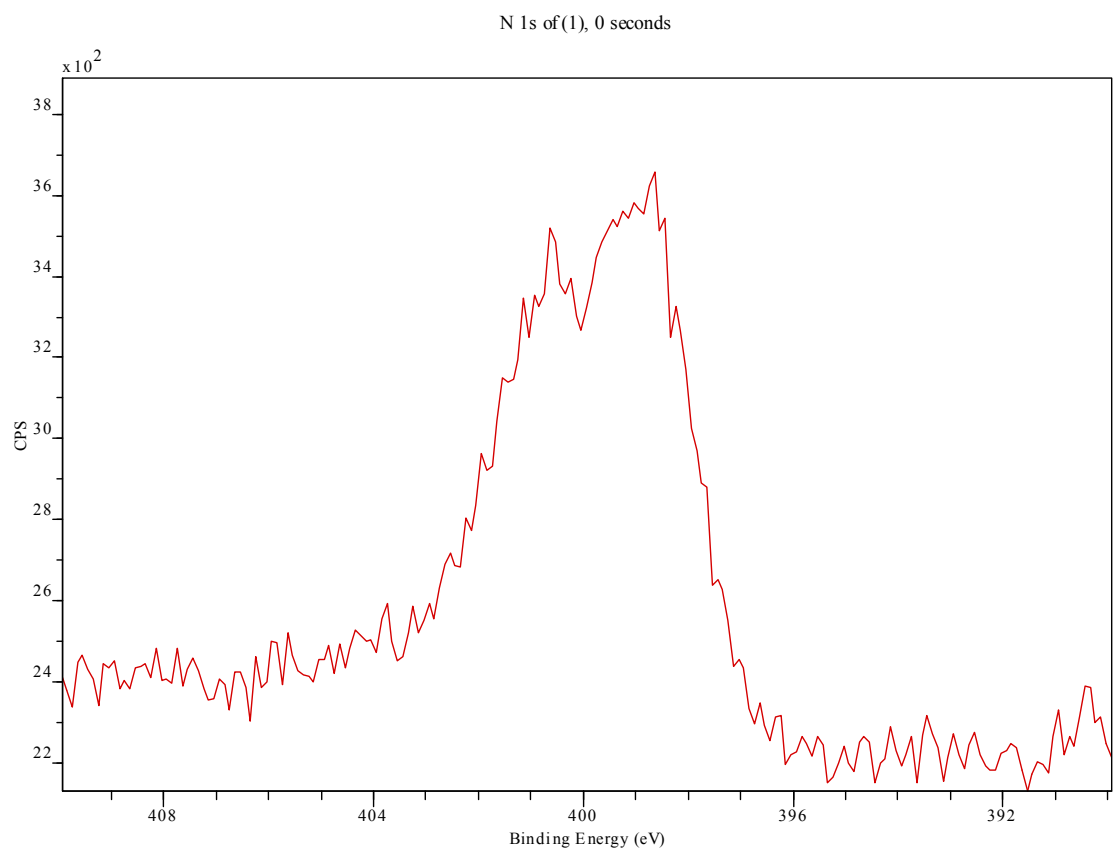


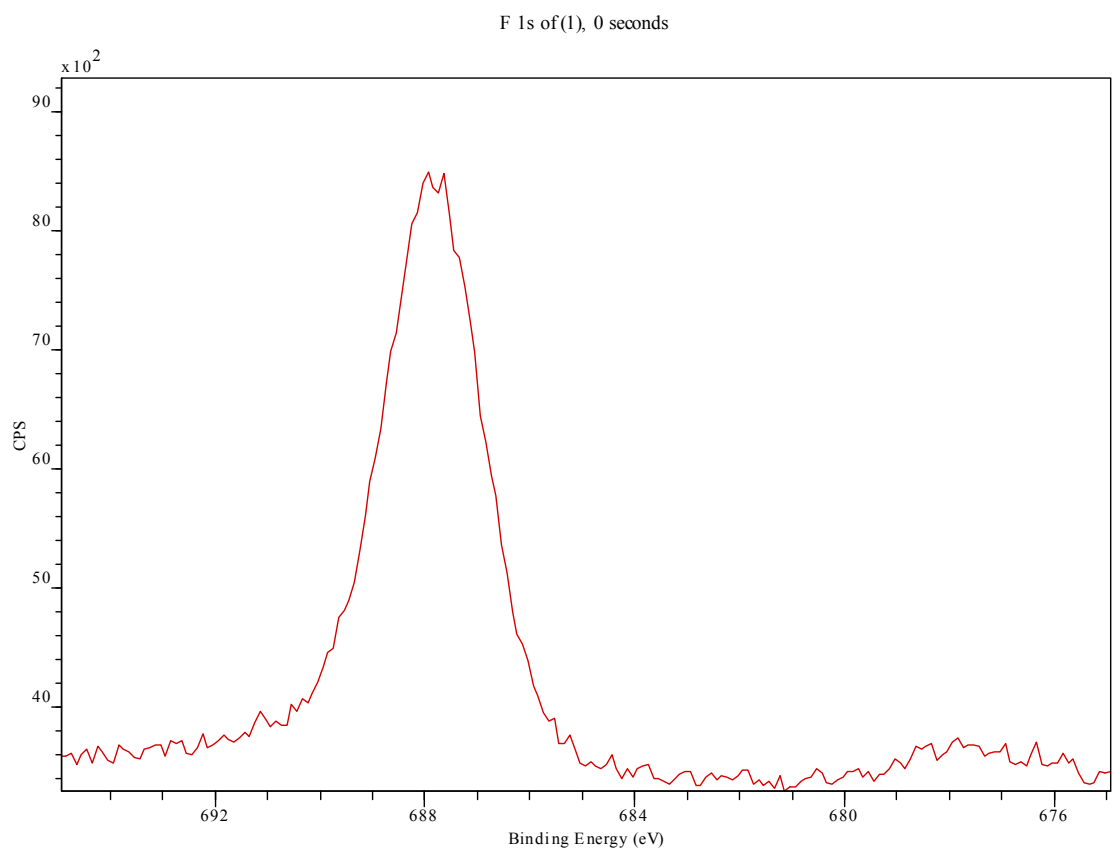


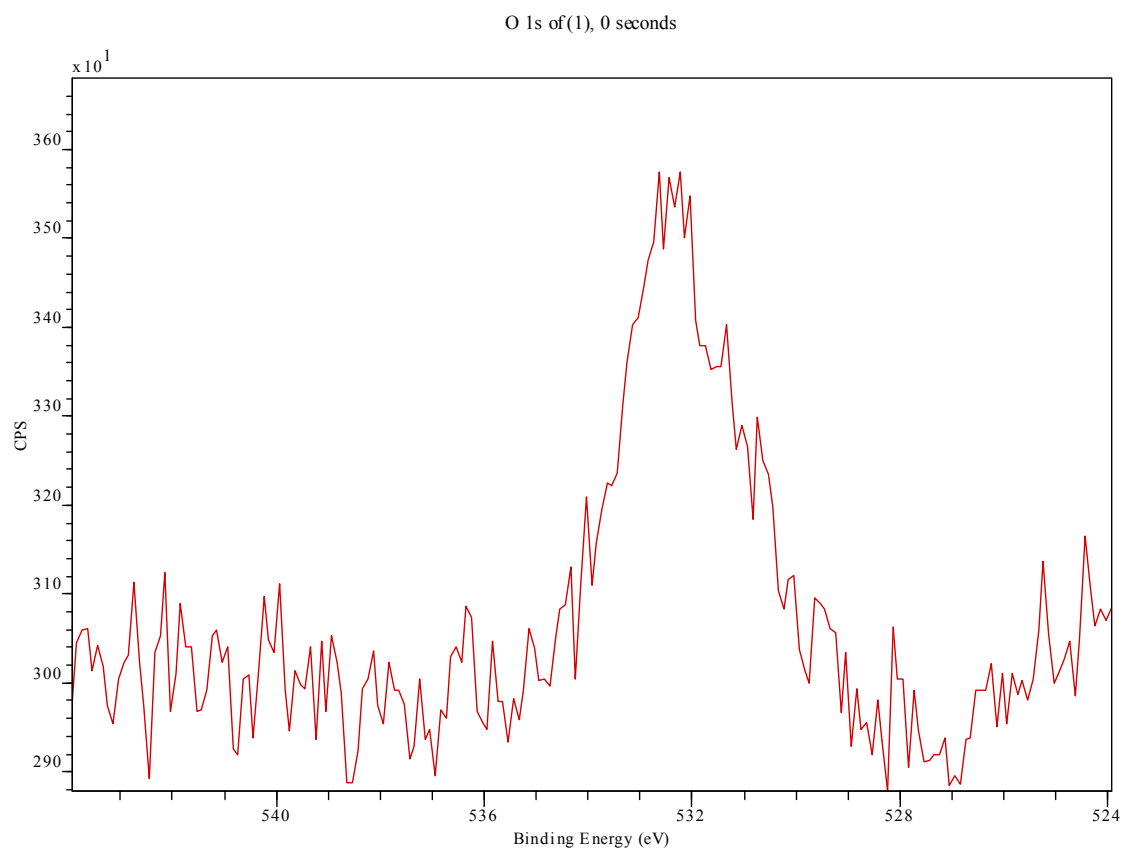
XPS spectroscopy of [Rh(η^2 -C₂H₄)₂(μ -3,5-(CF₃)₂-Pz)]₂ (**1**) using argon as the carrier gas

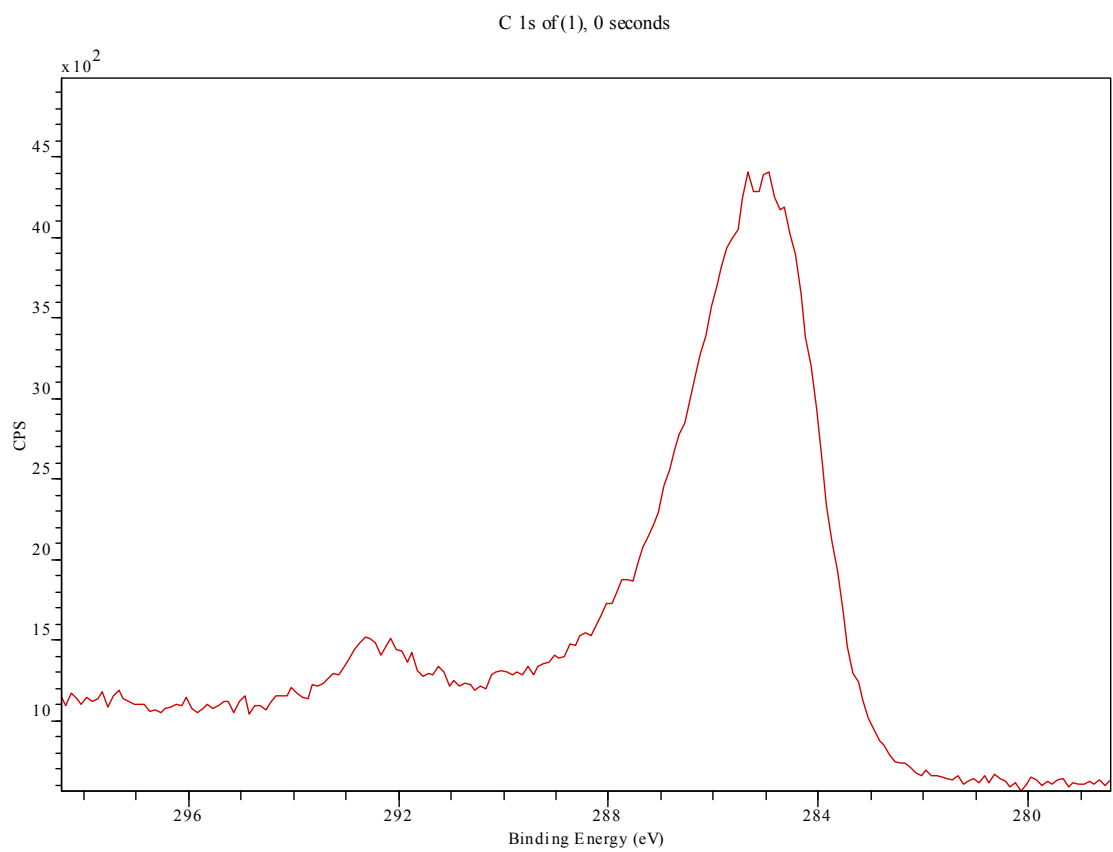


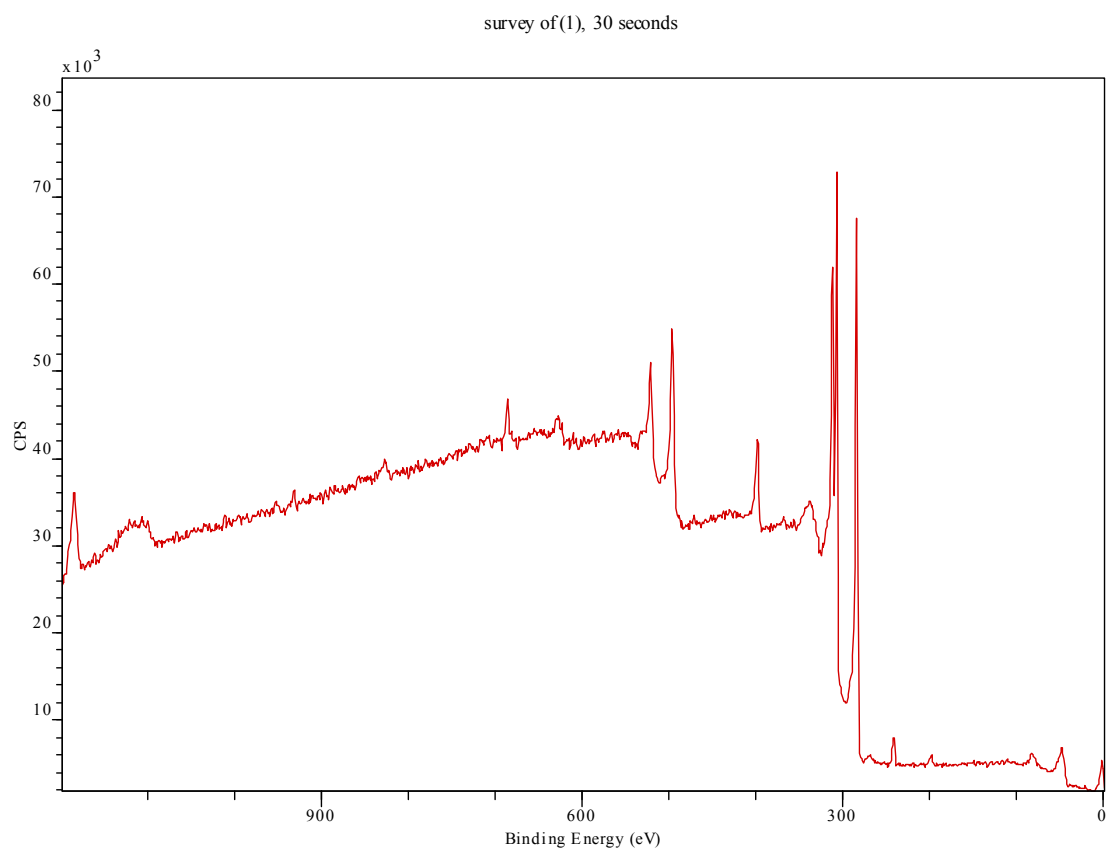


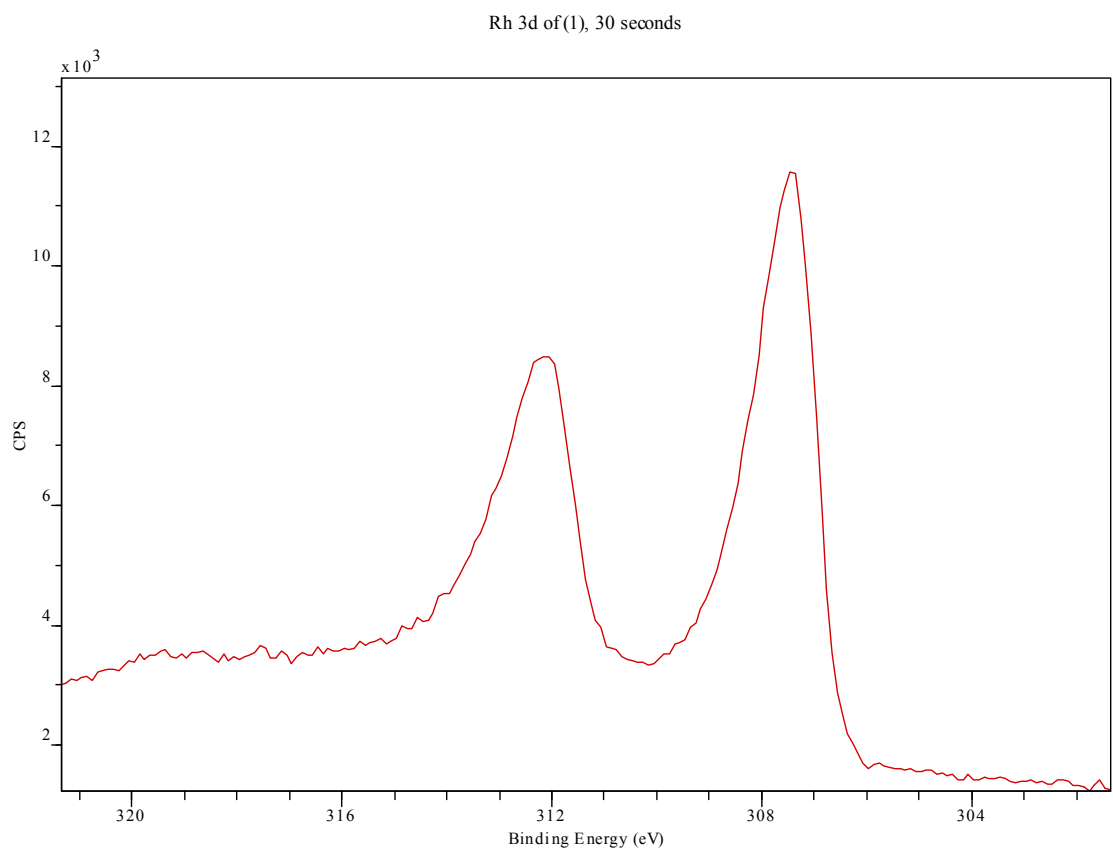


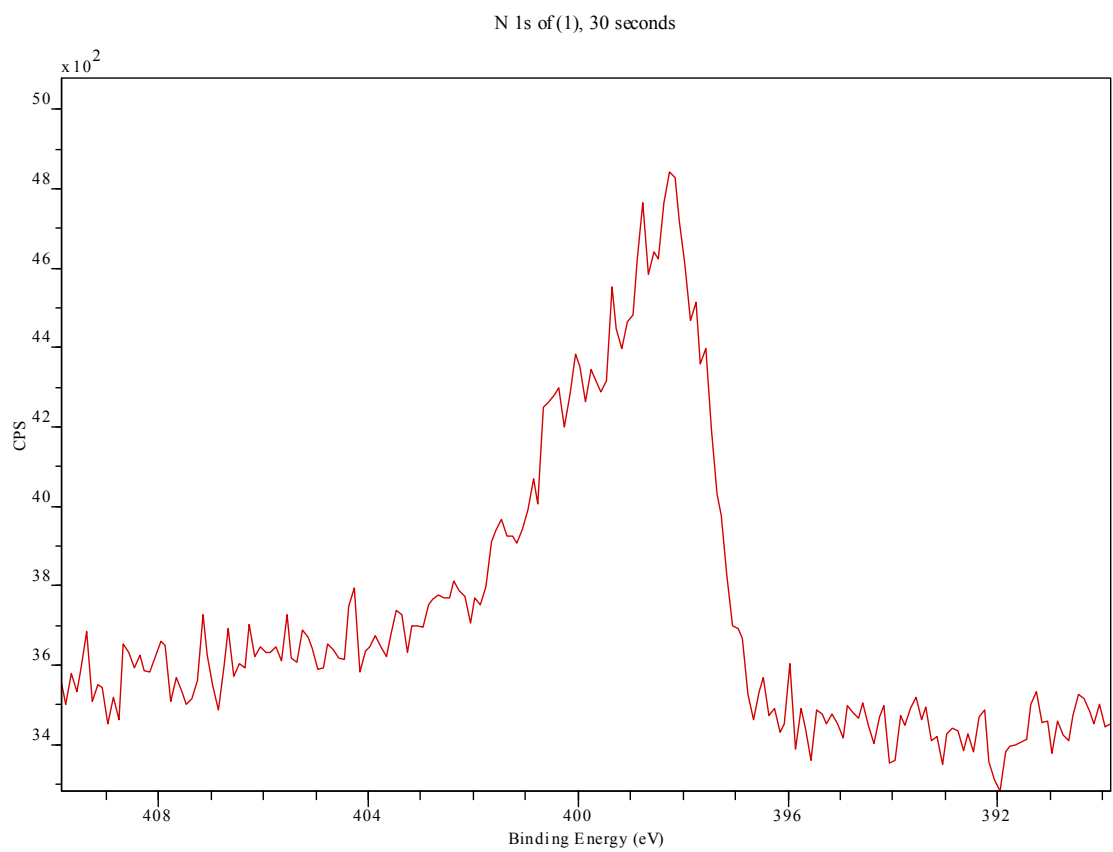


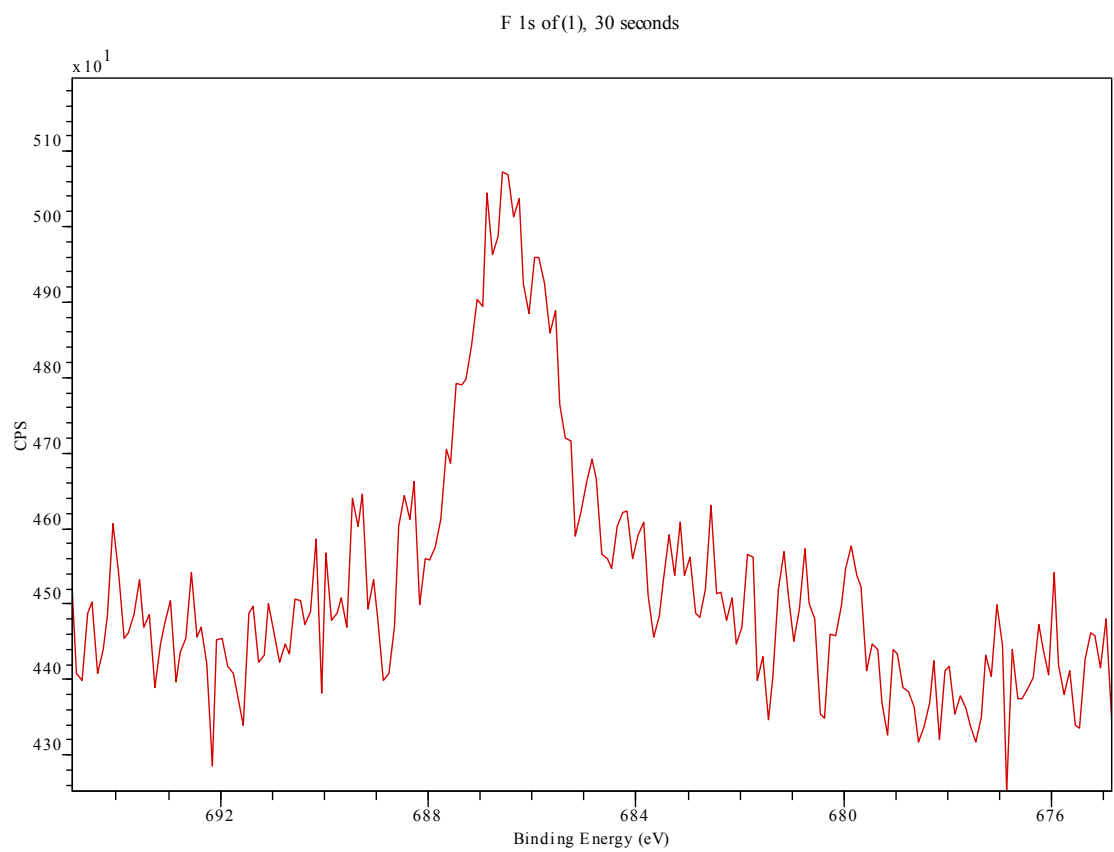


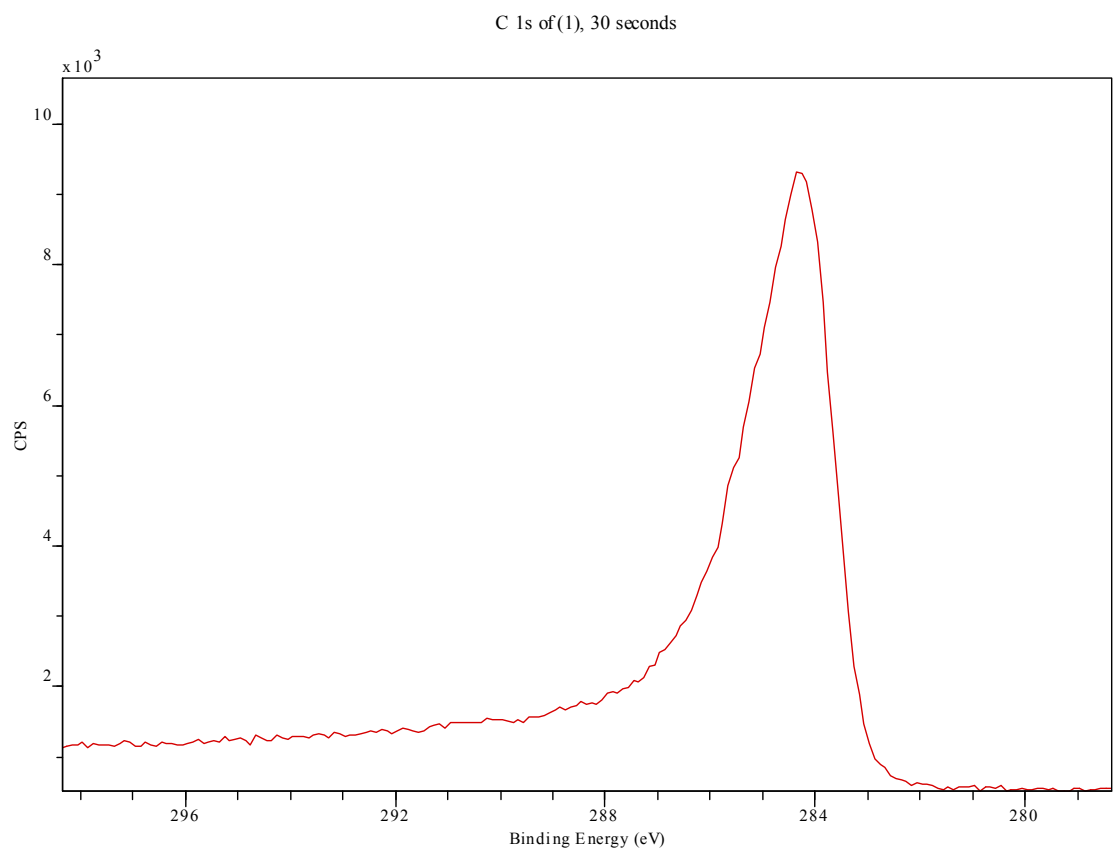


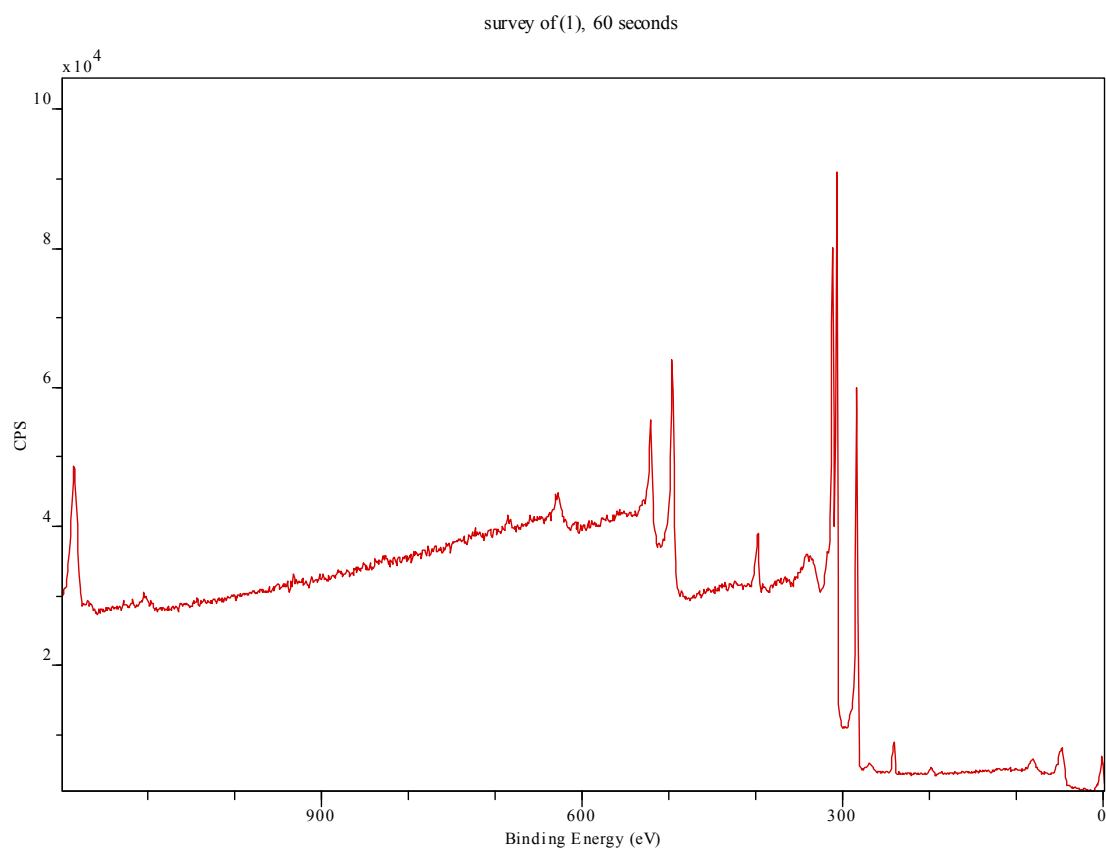


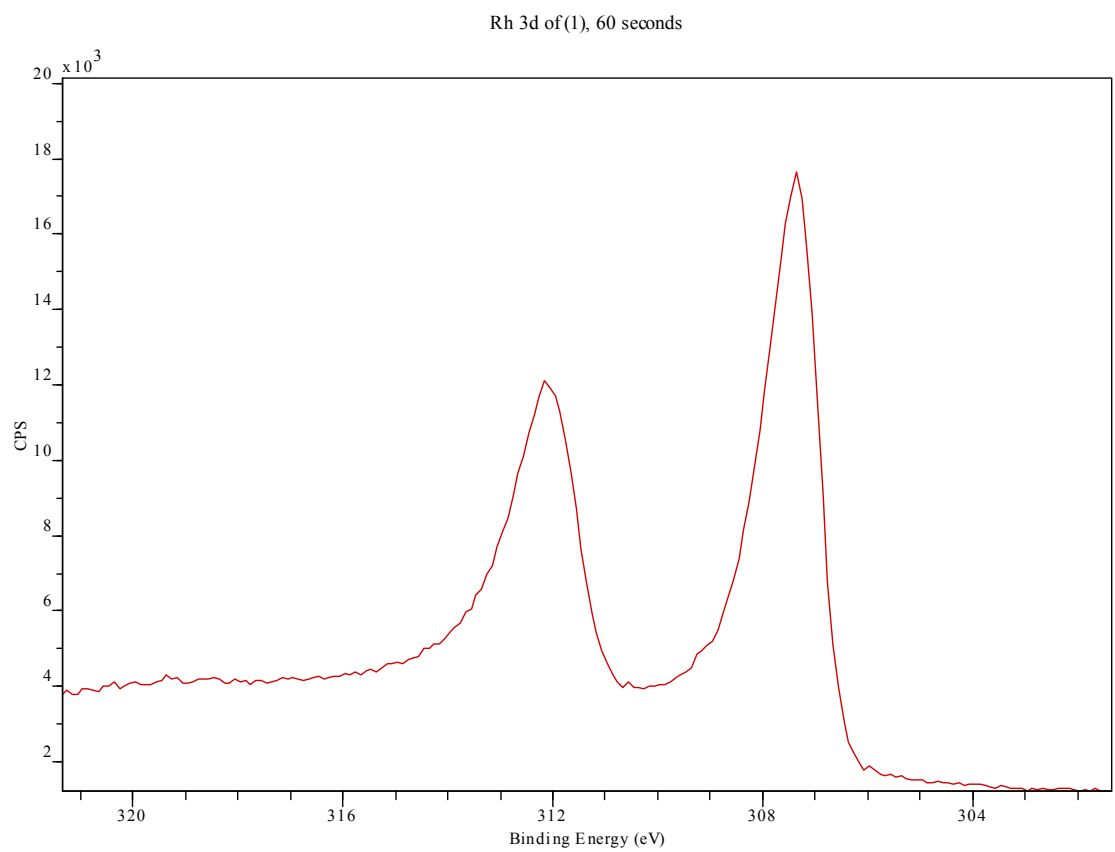


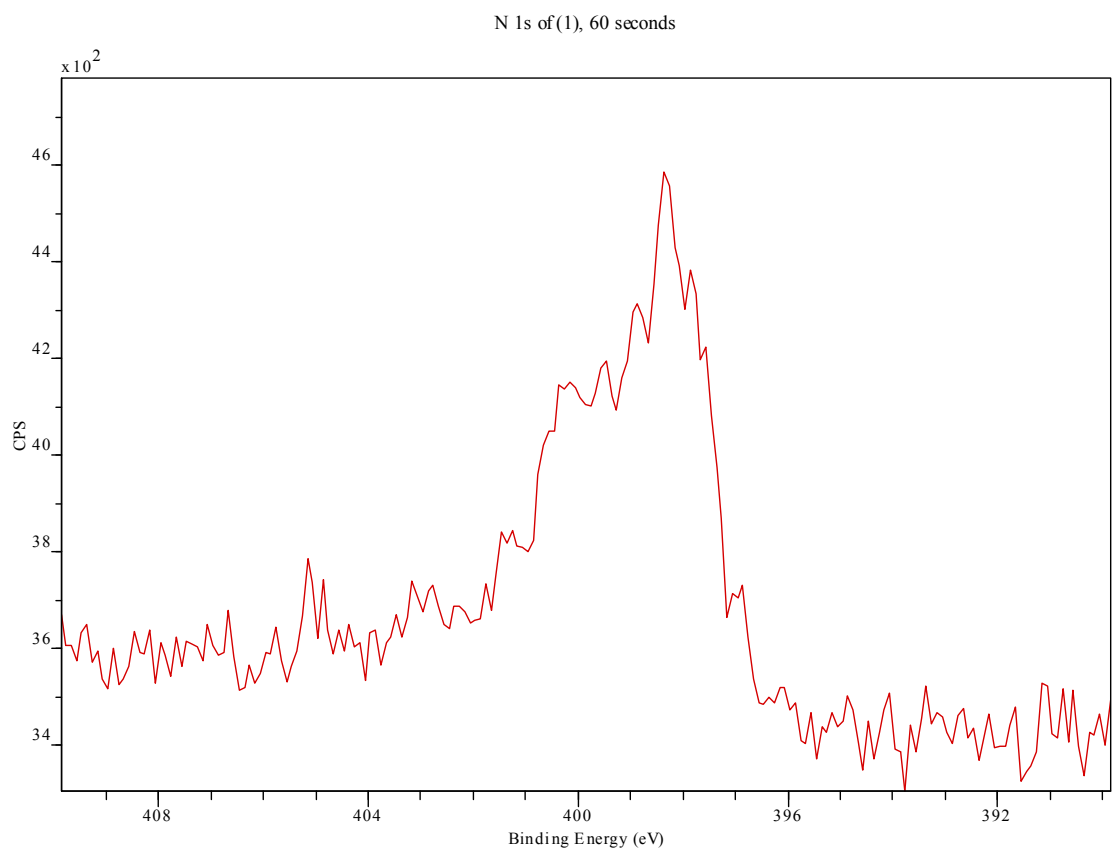


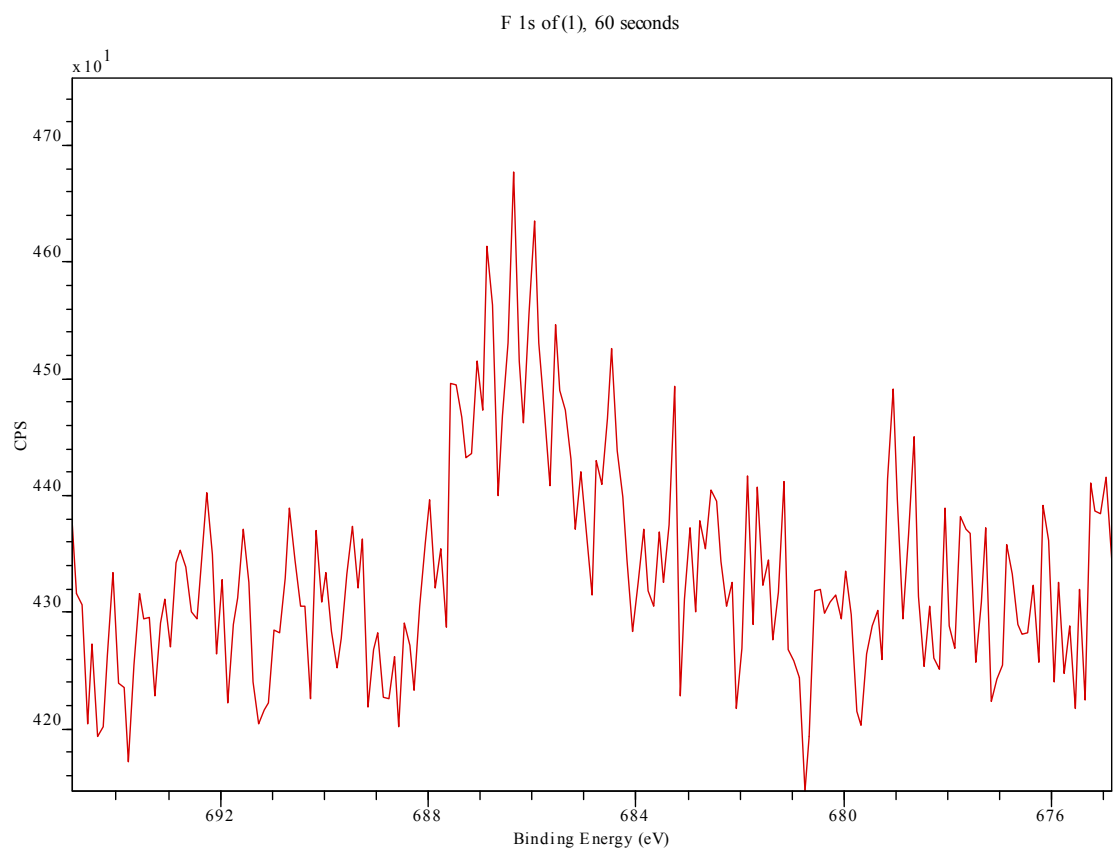


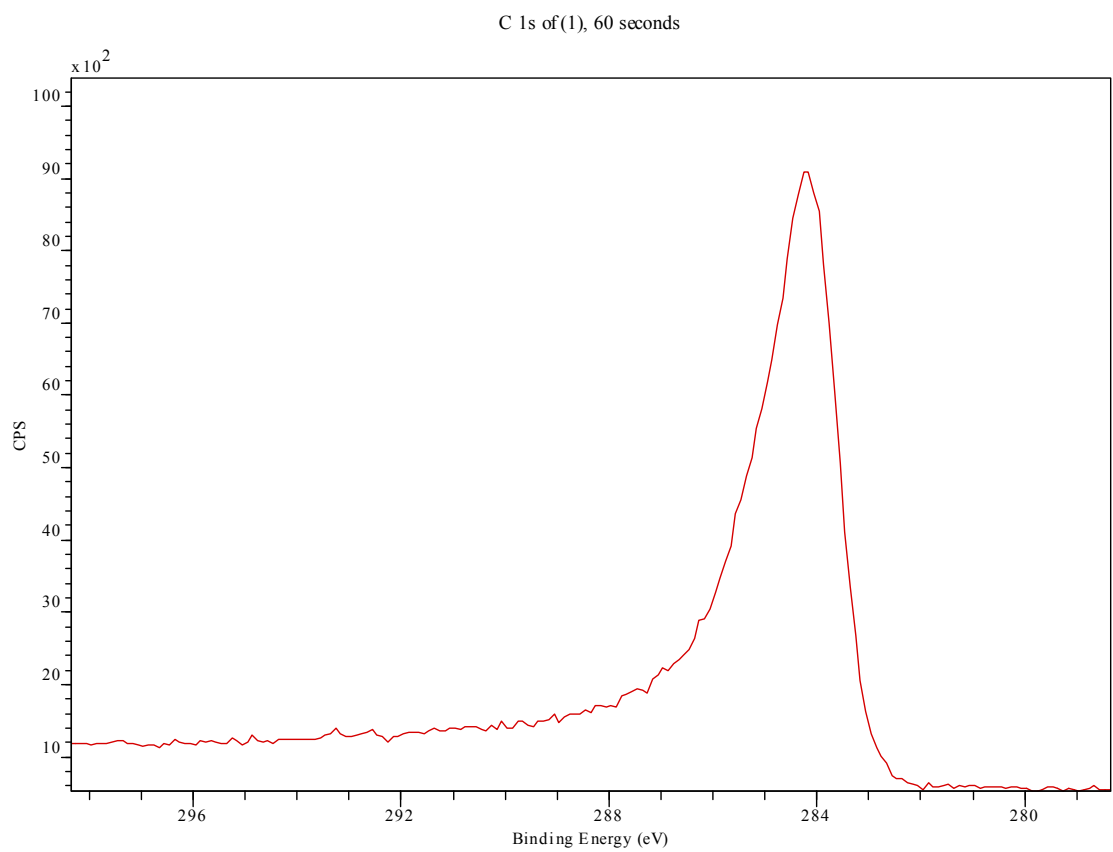


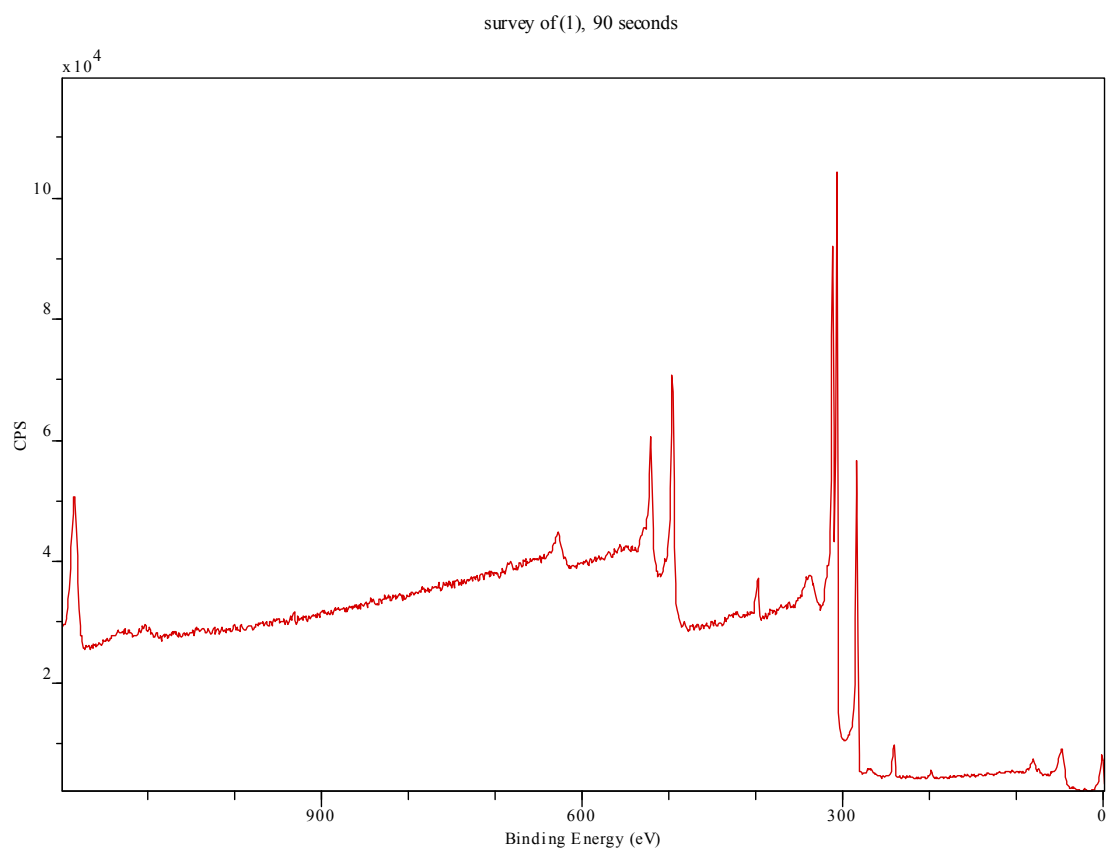


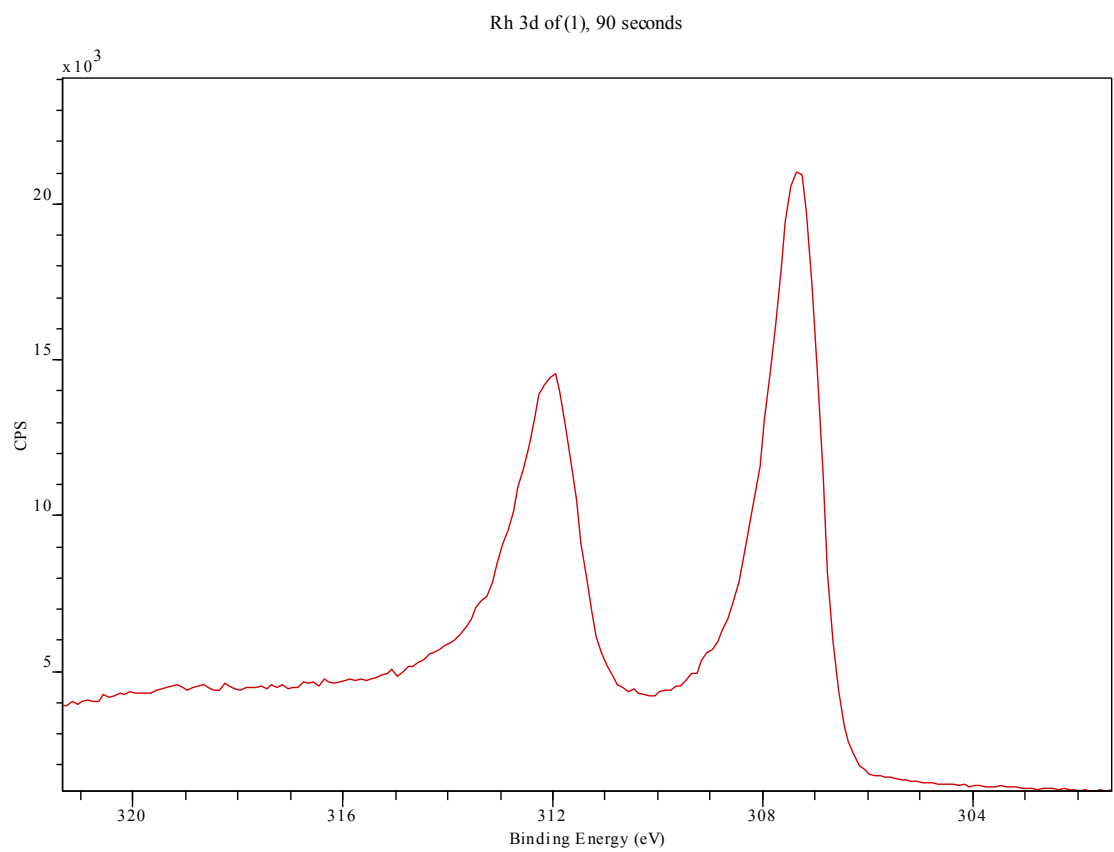


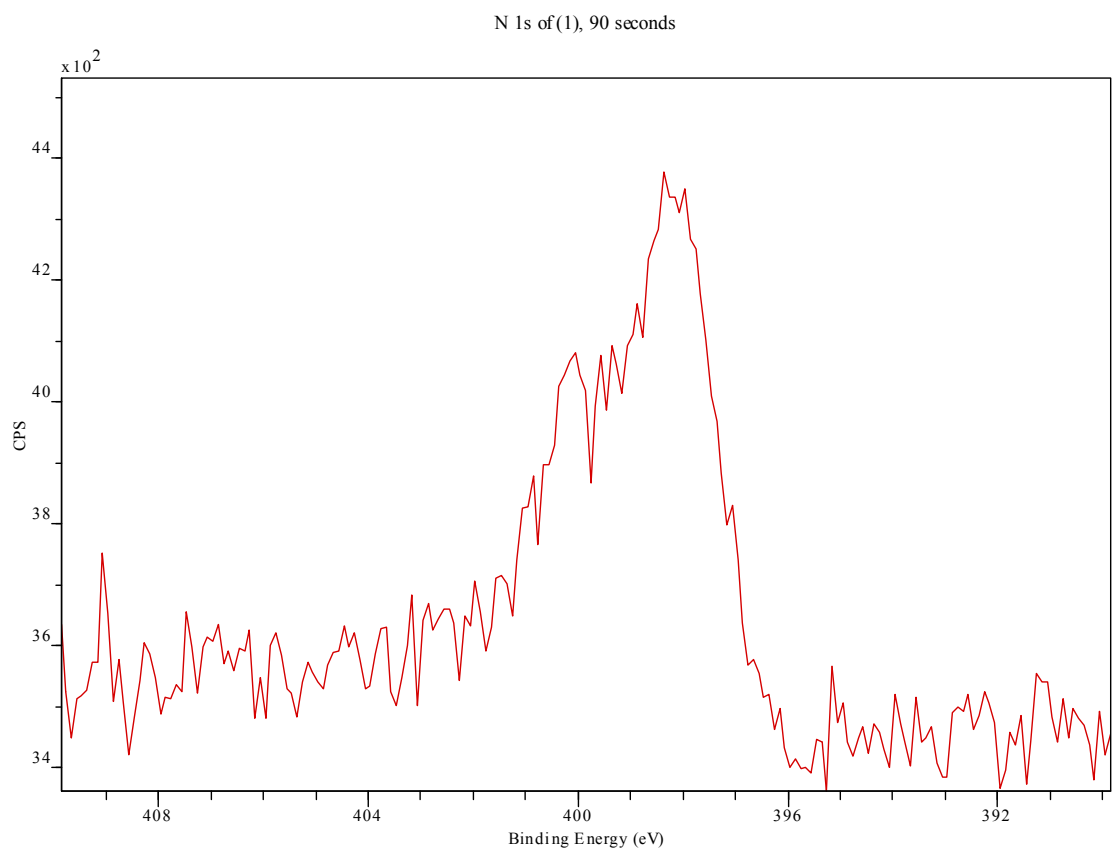


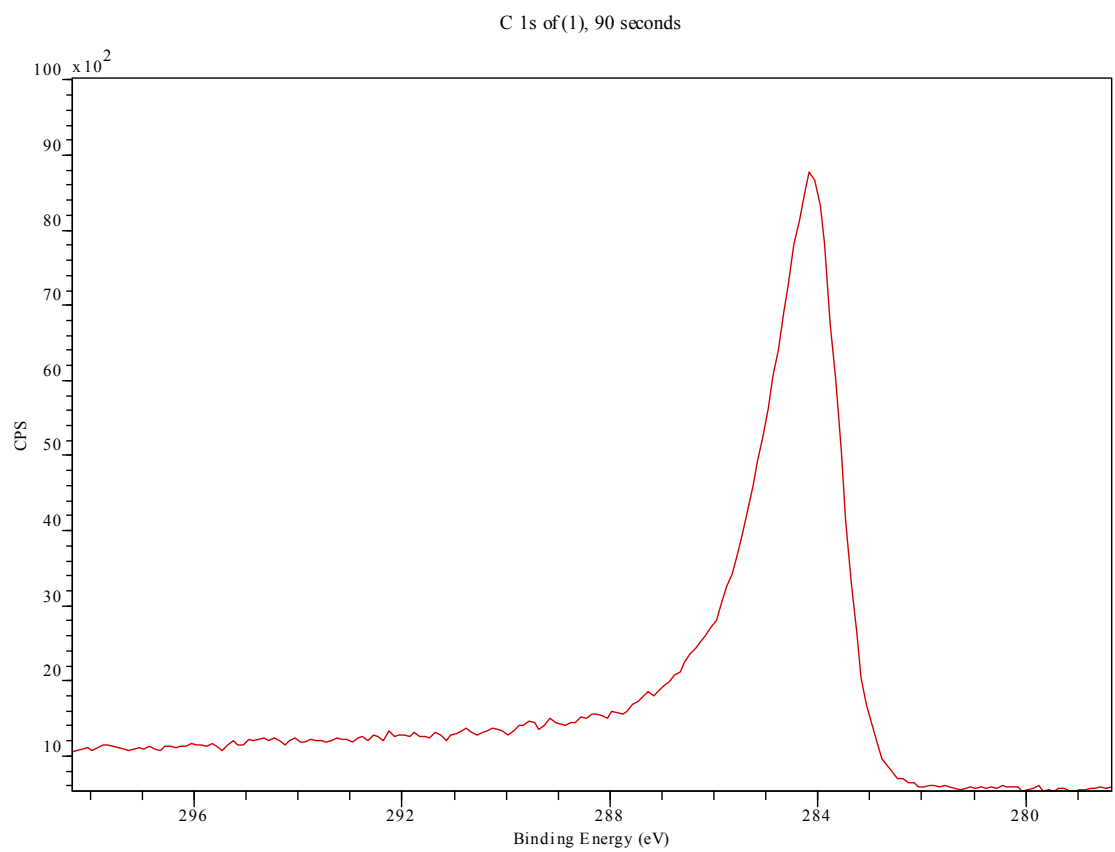


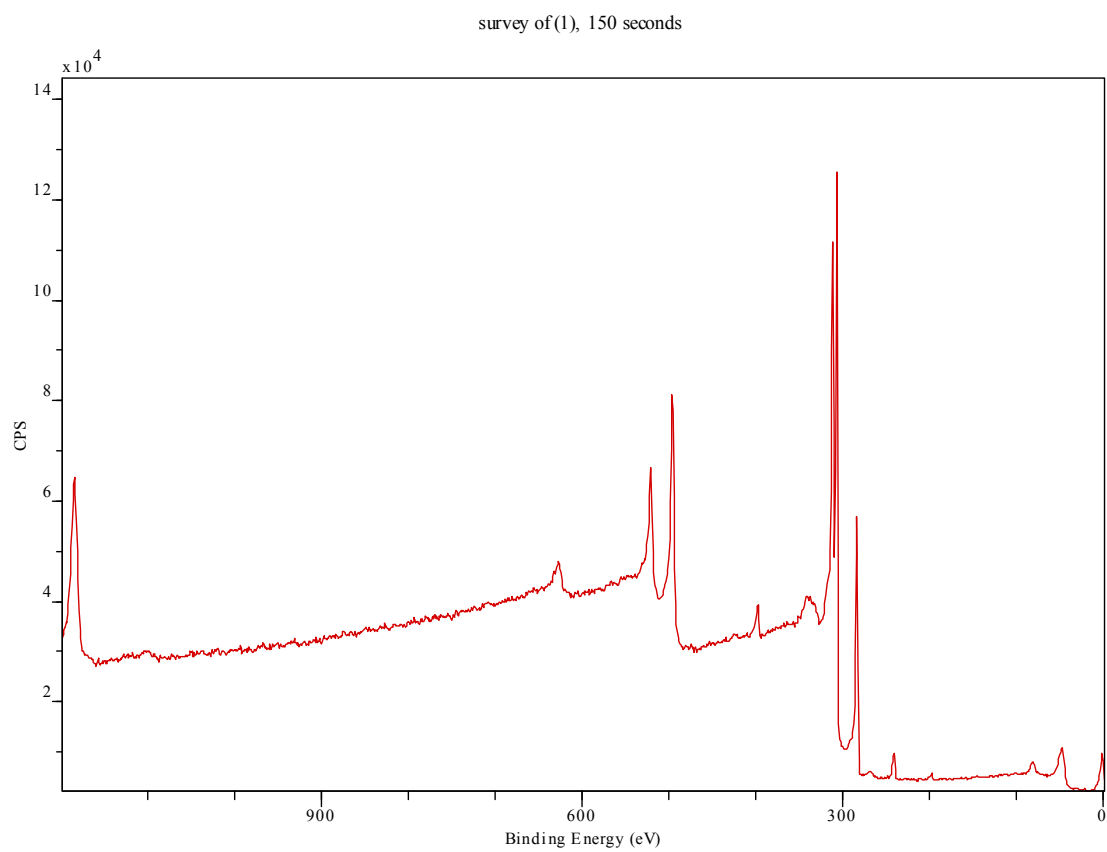


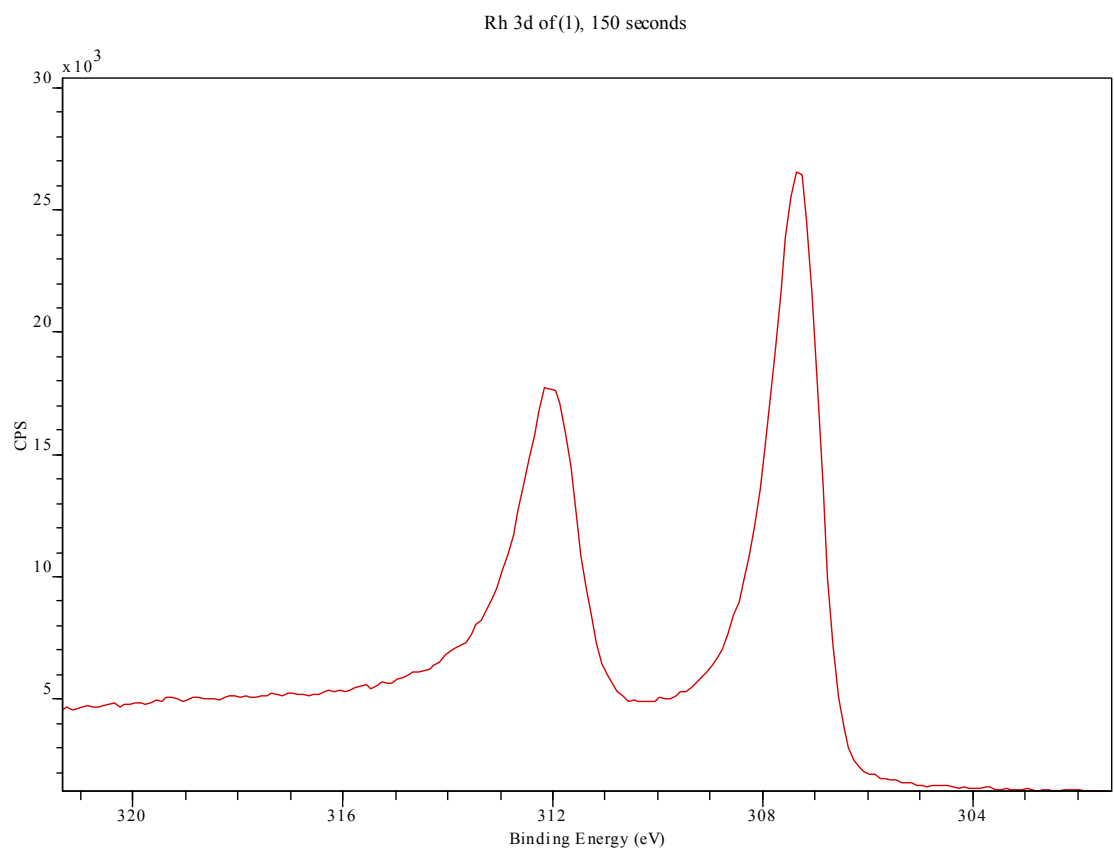


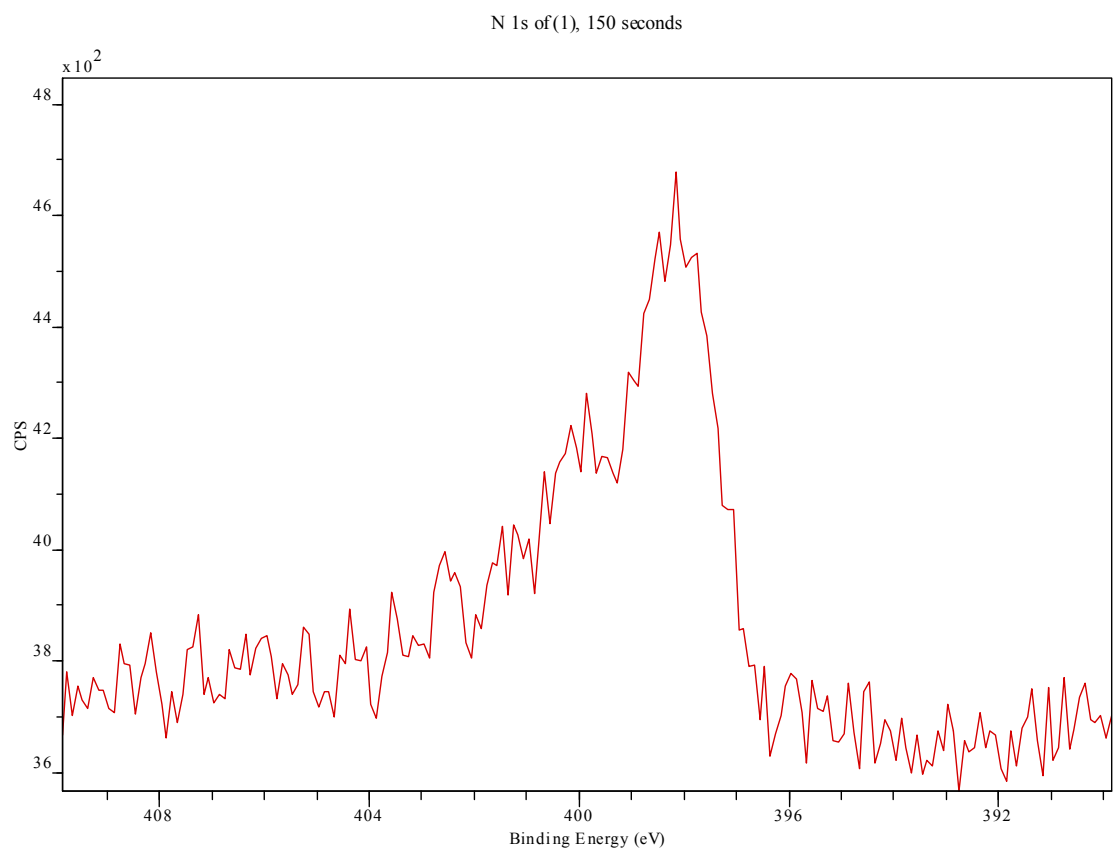


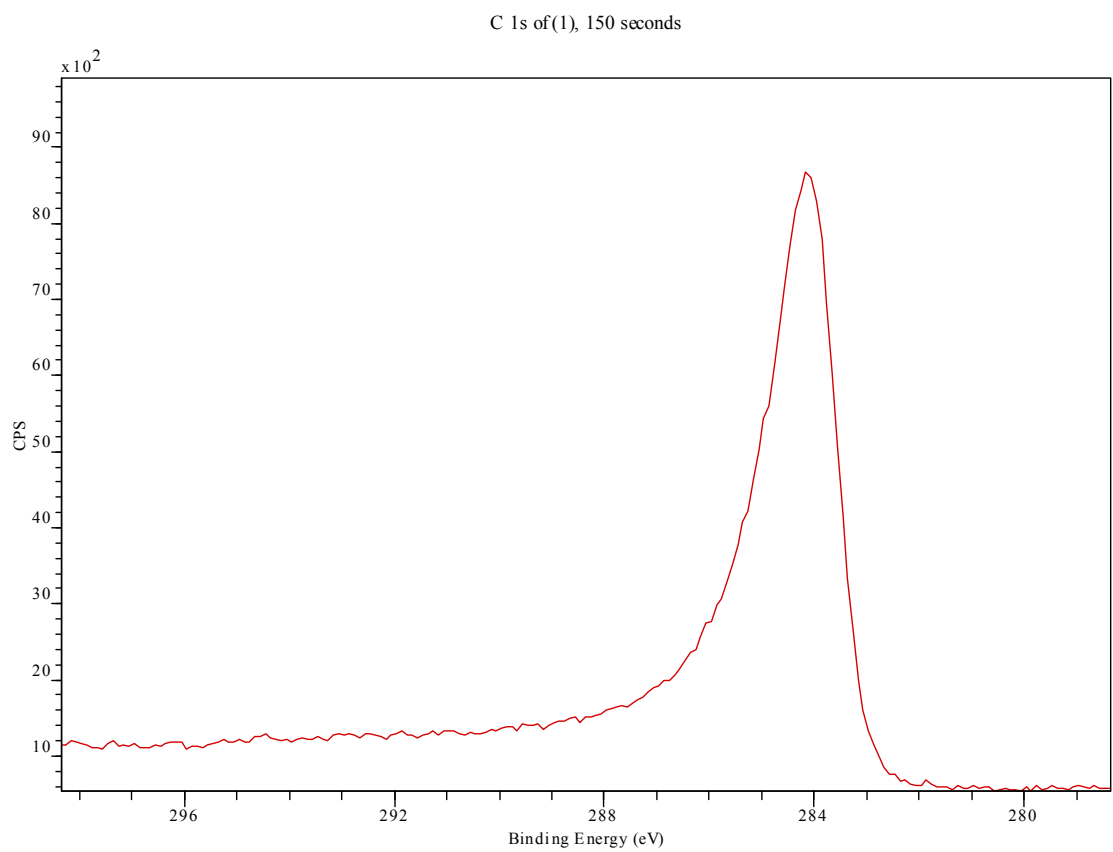


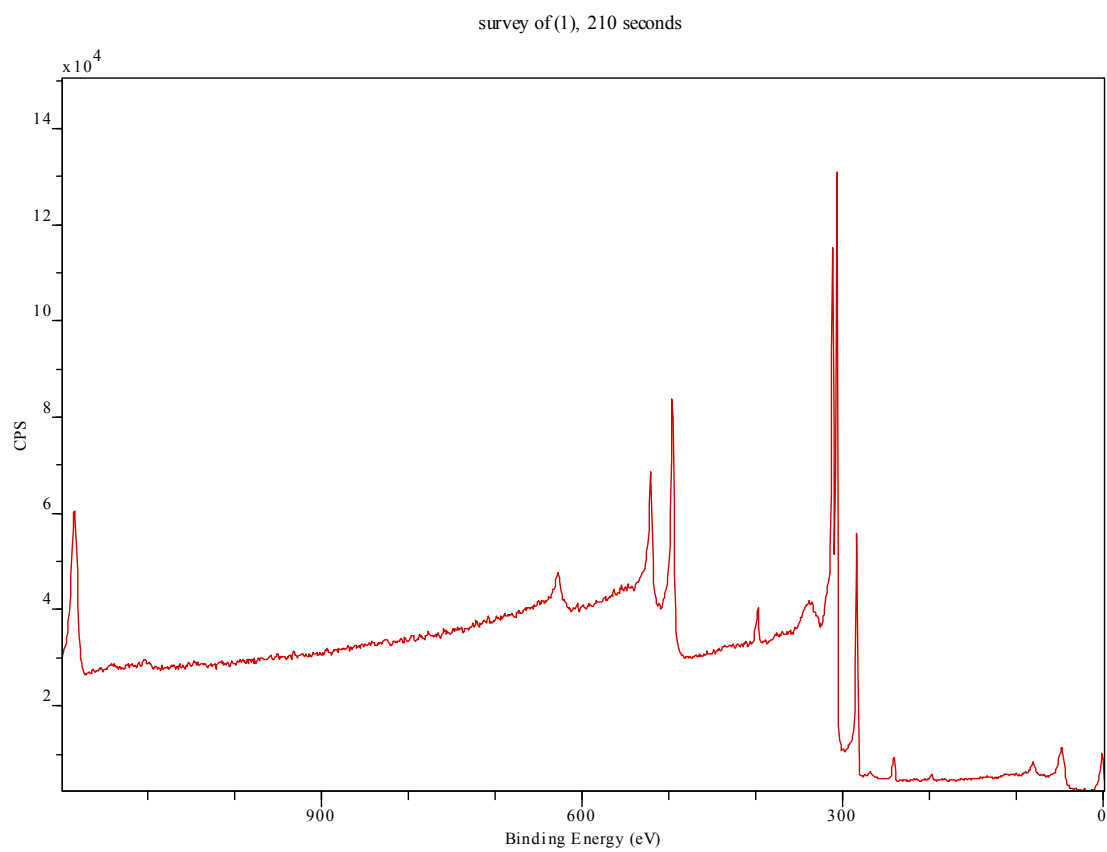


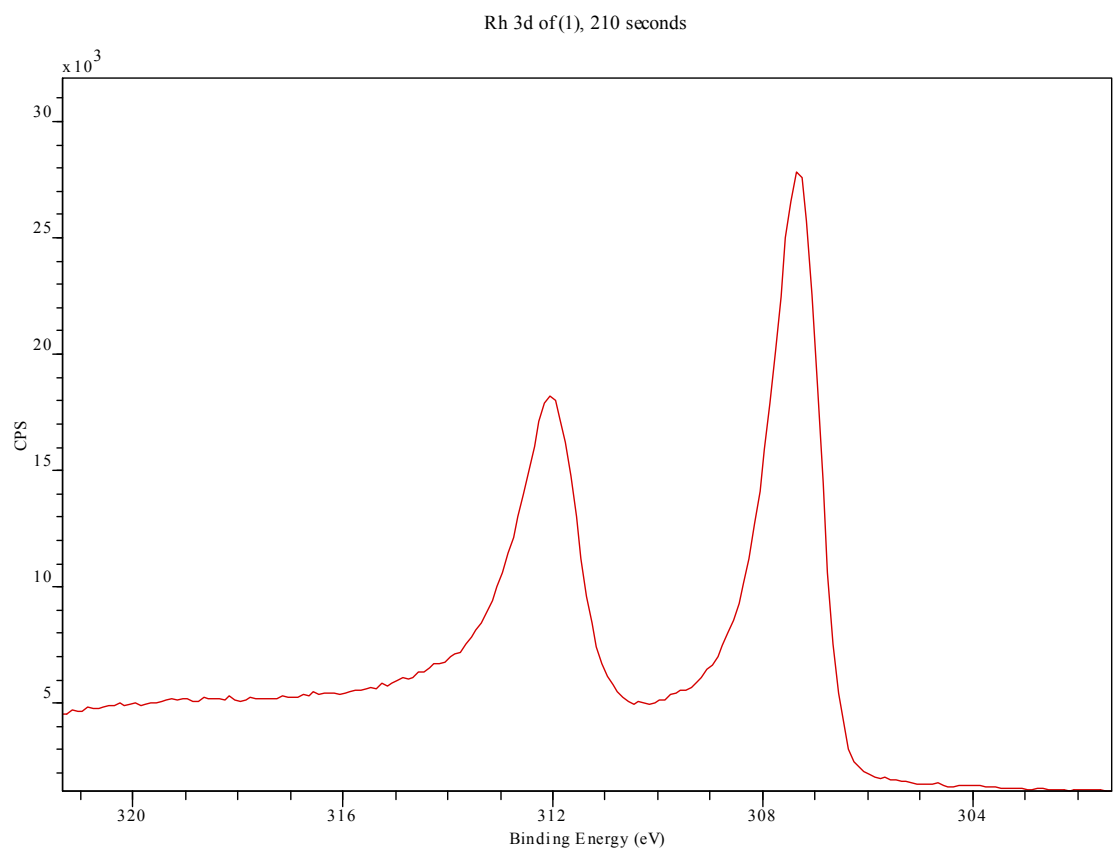


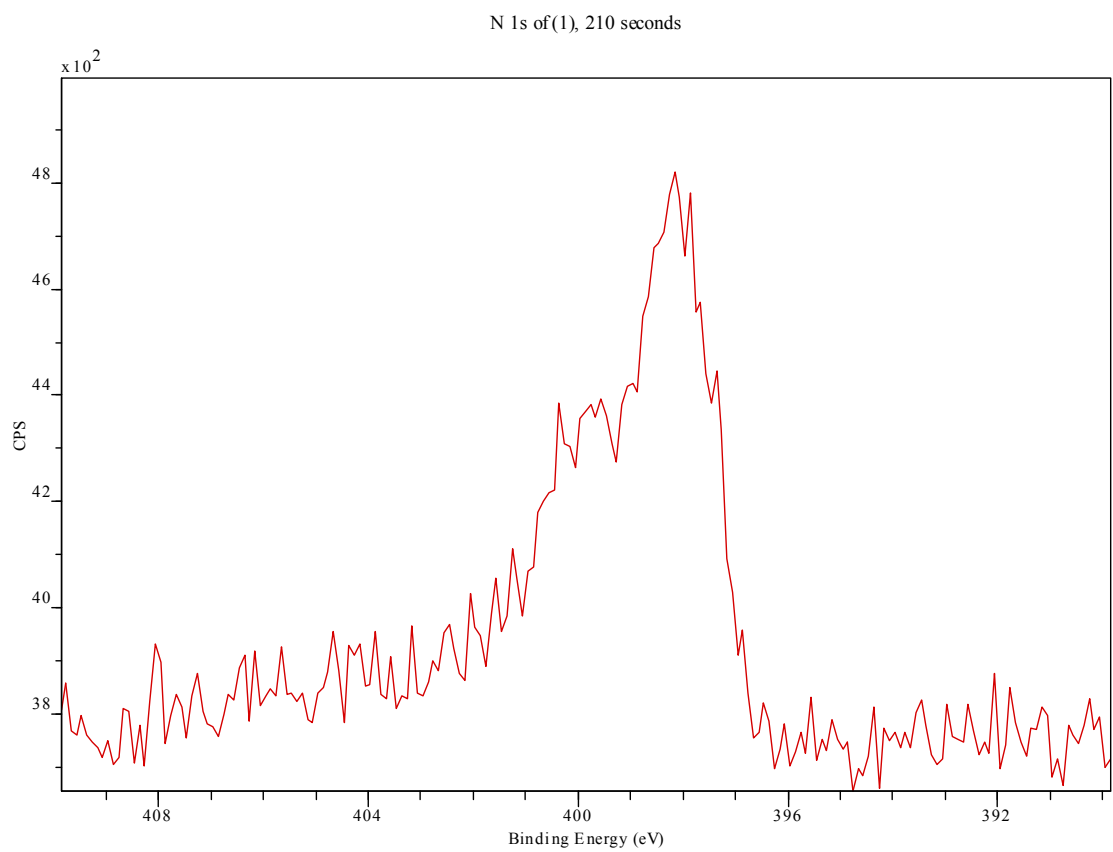


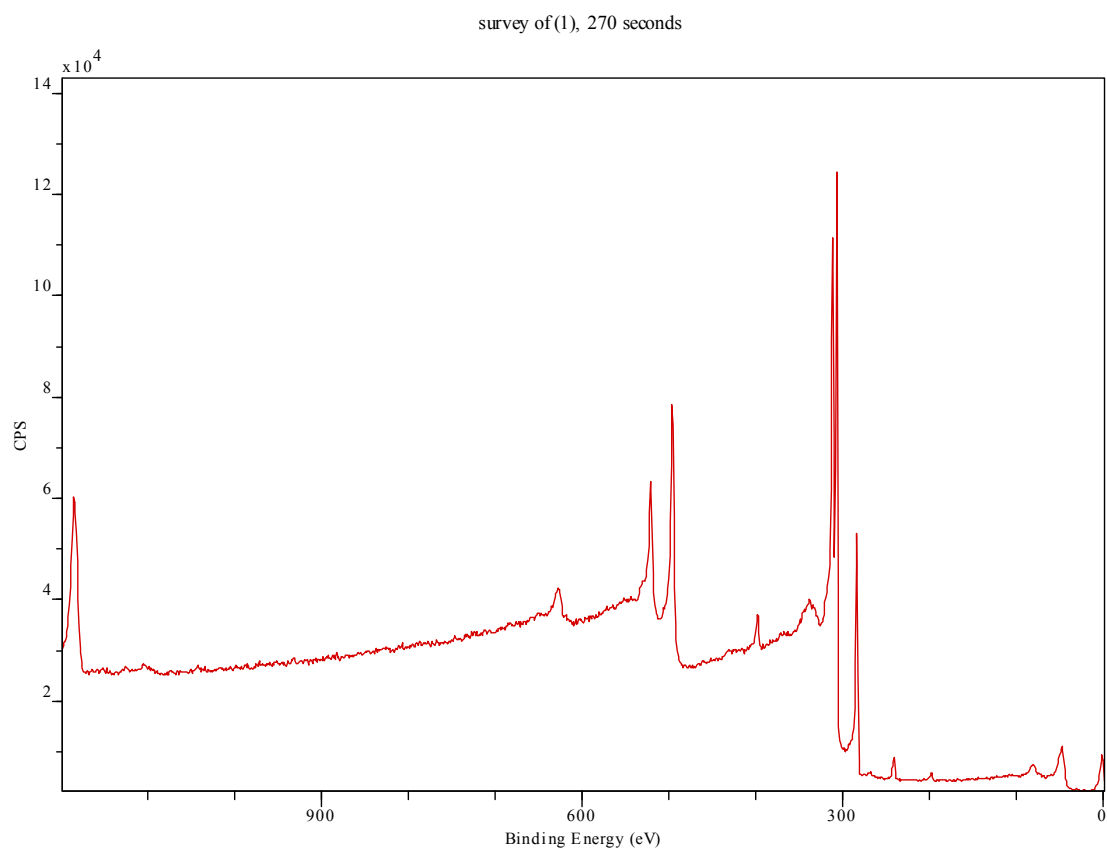


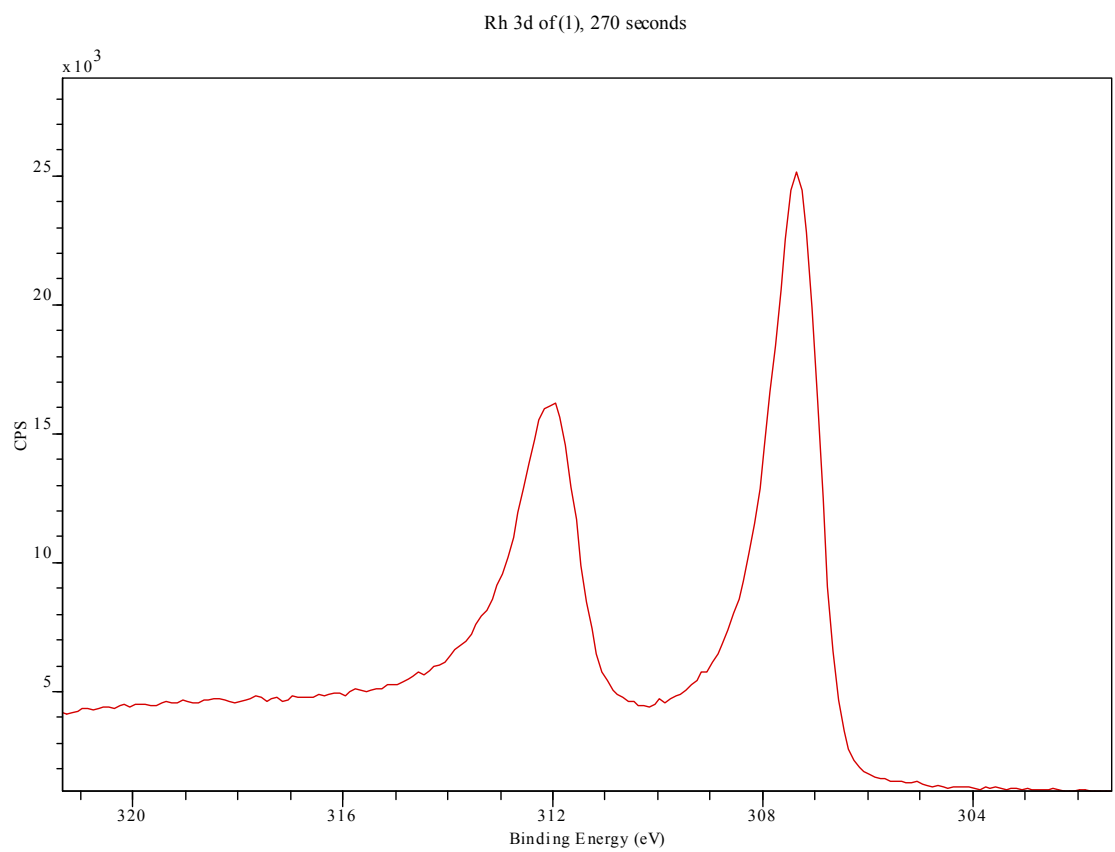


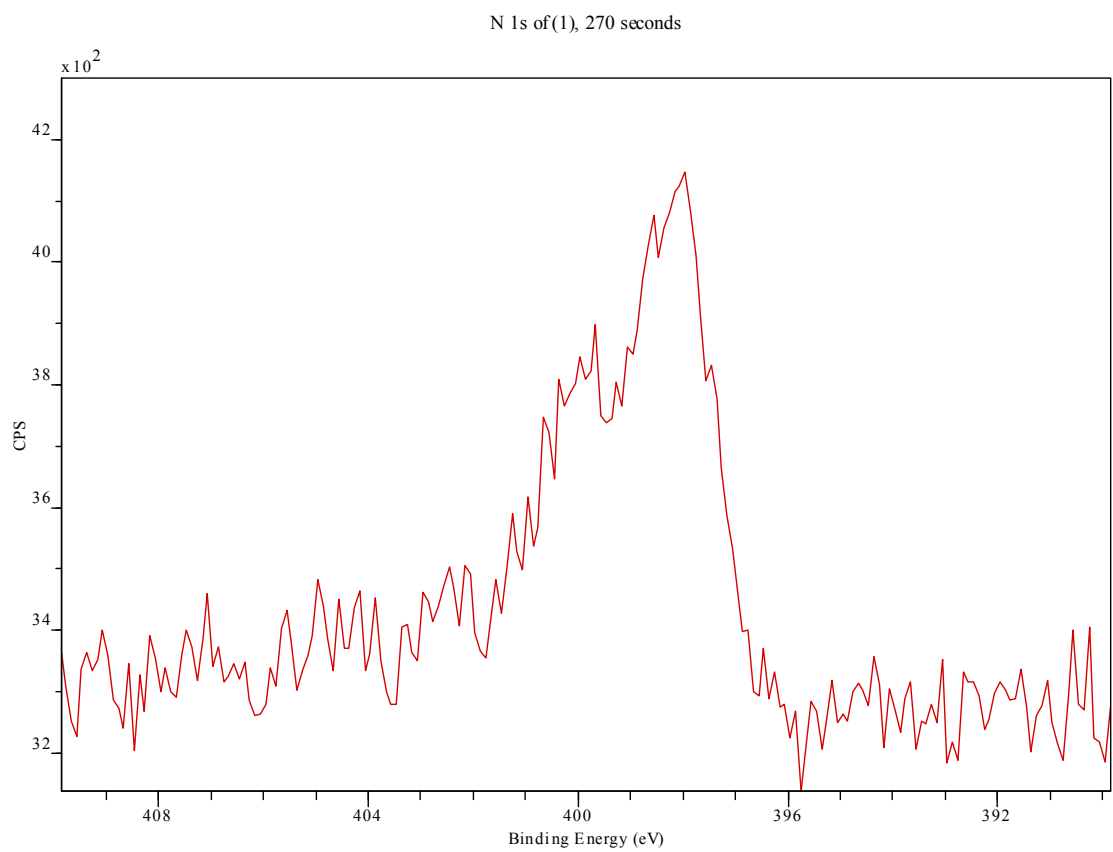


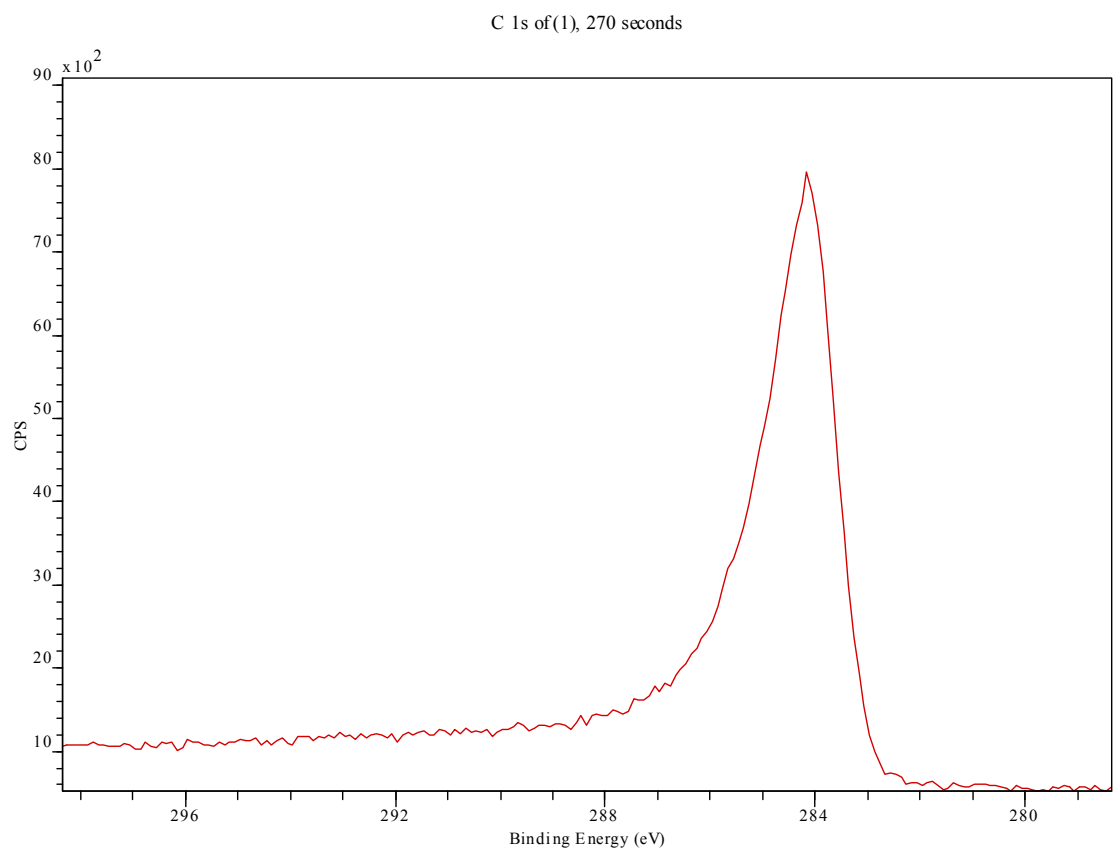


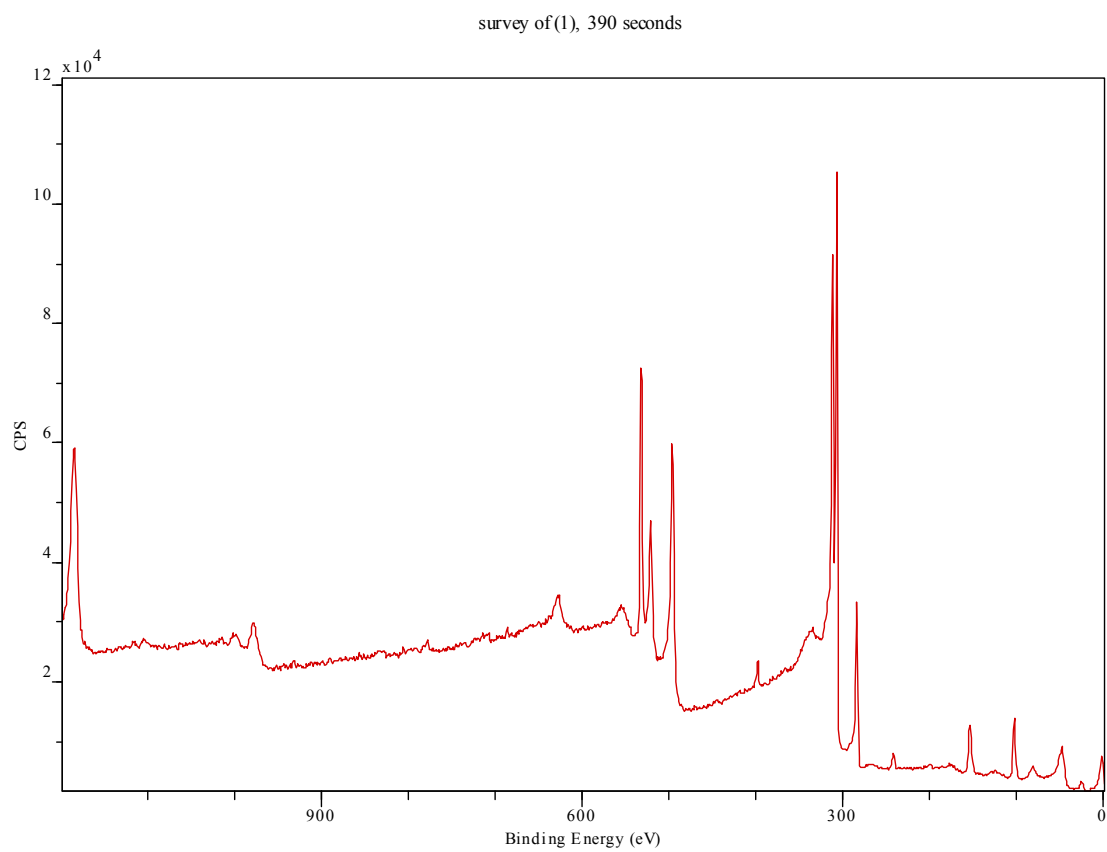


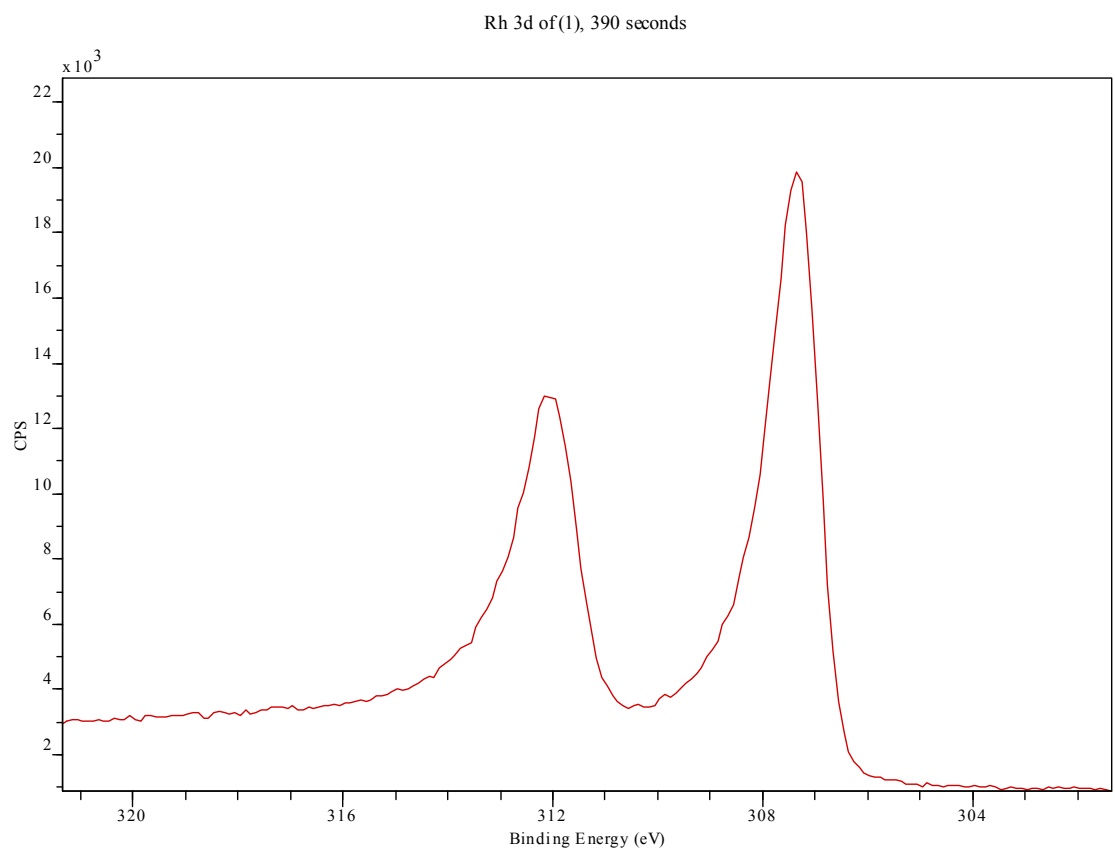


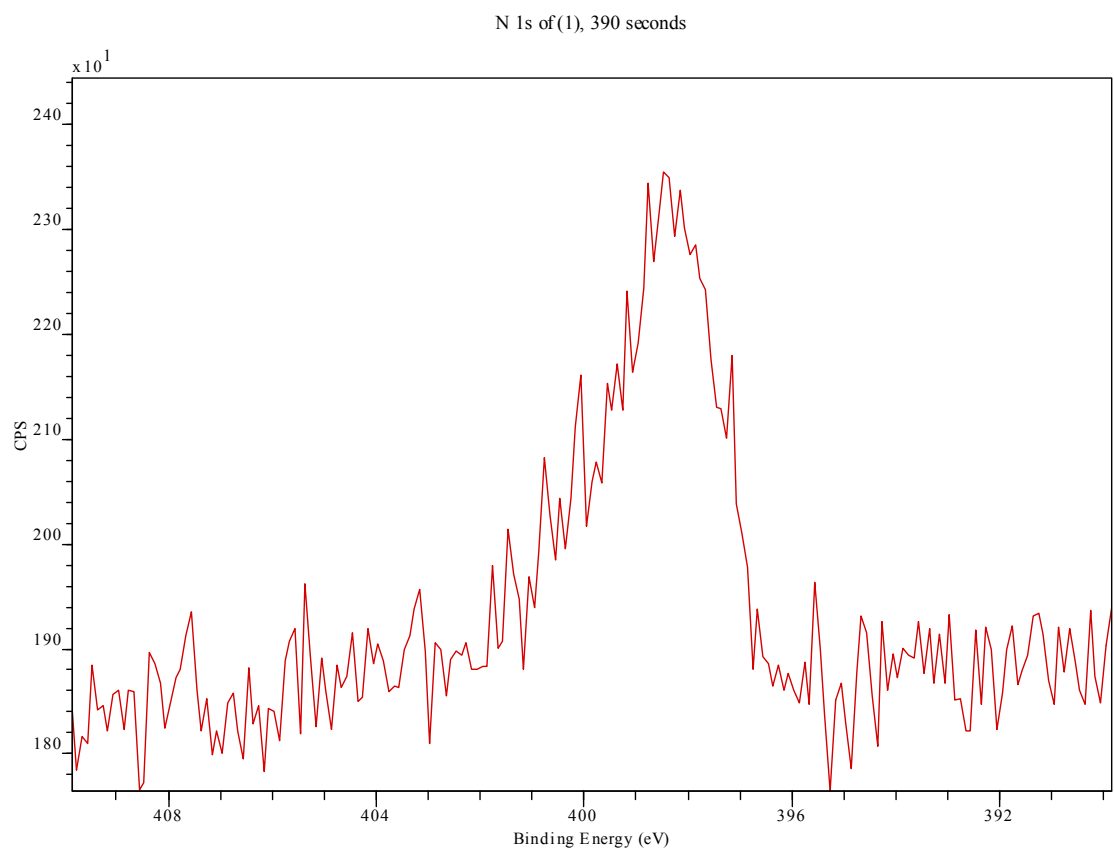


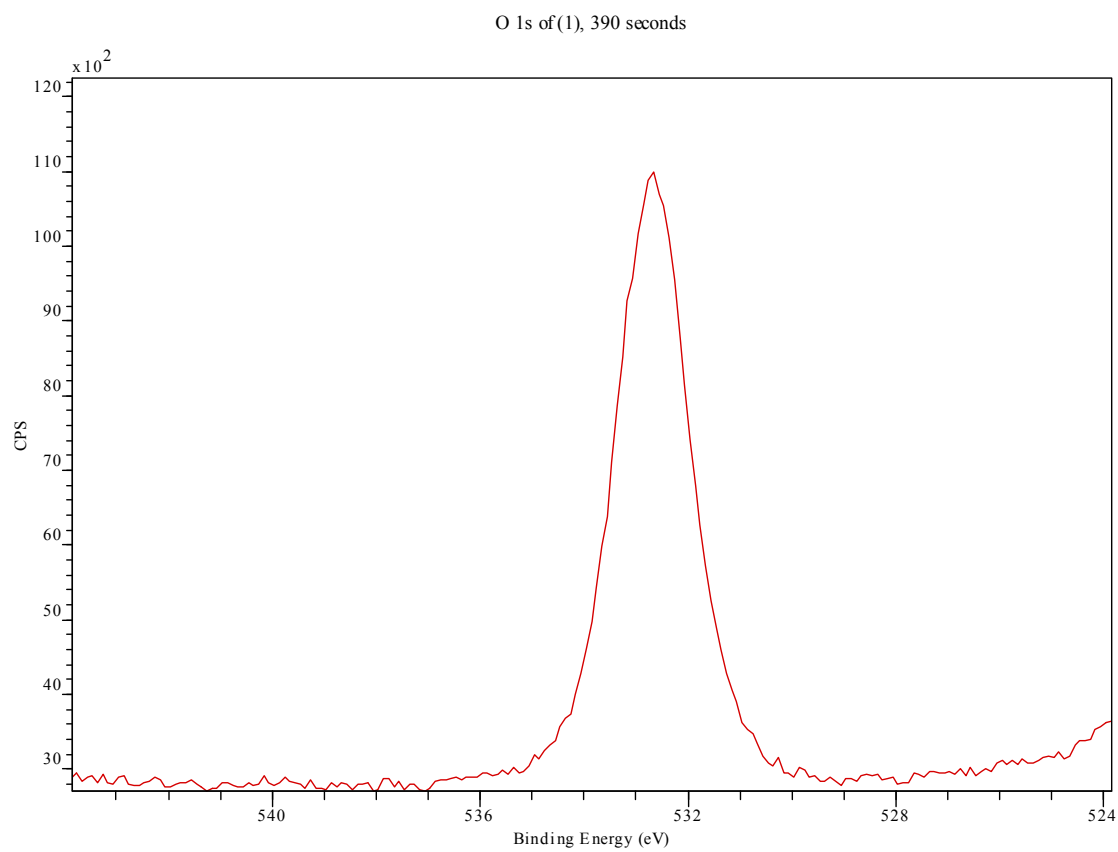


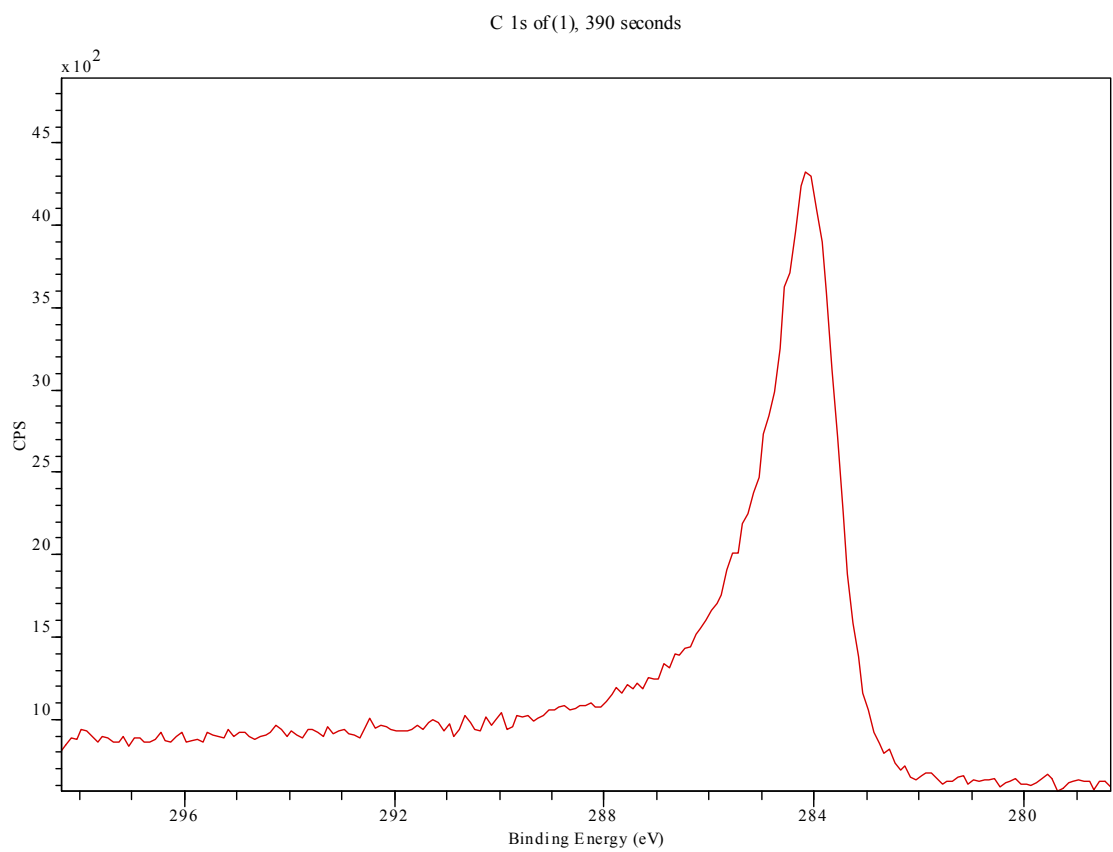


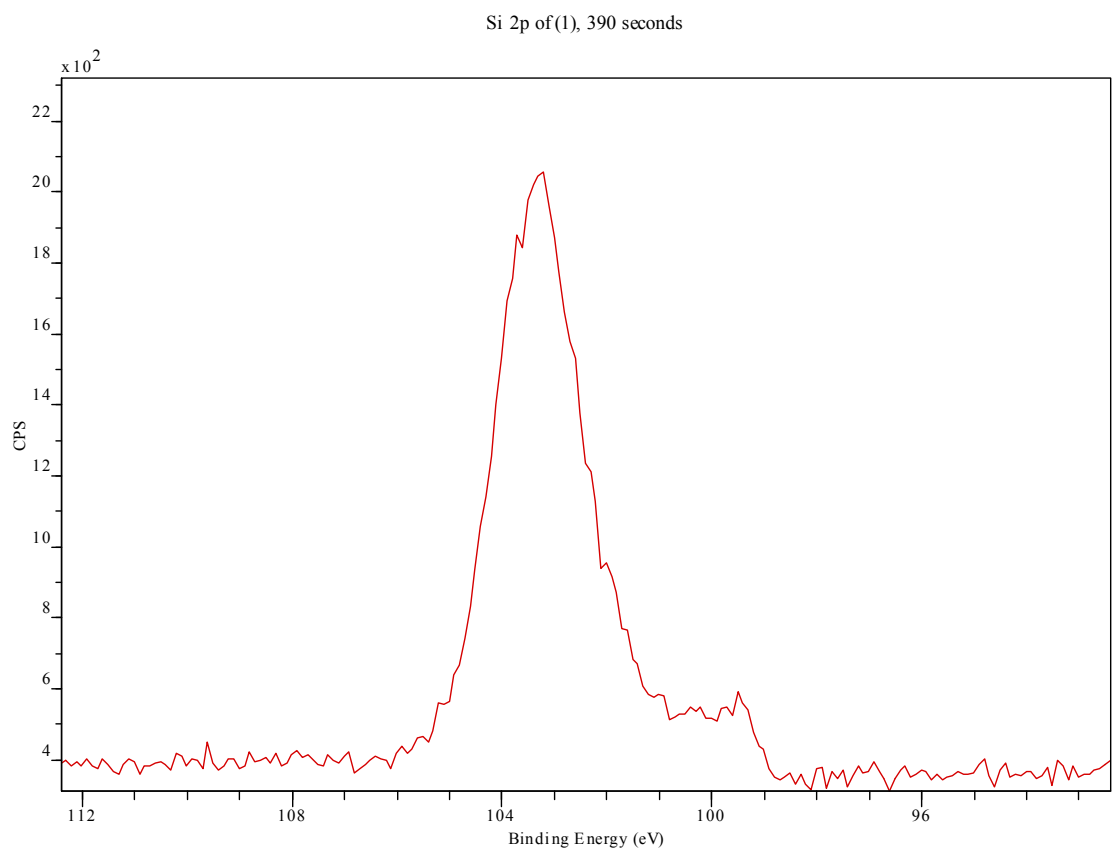


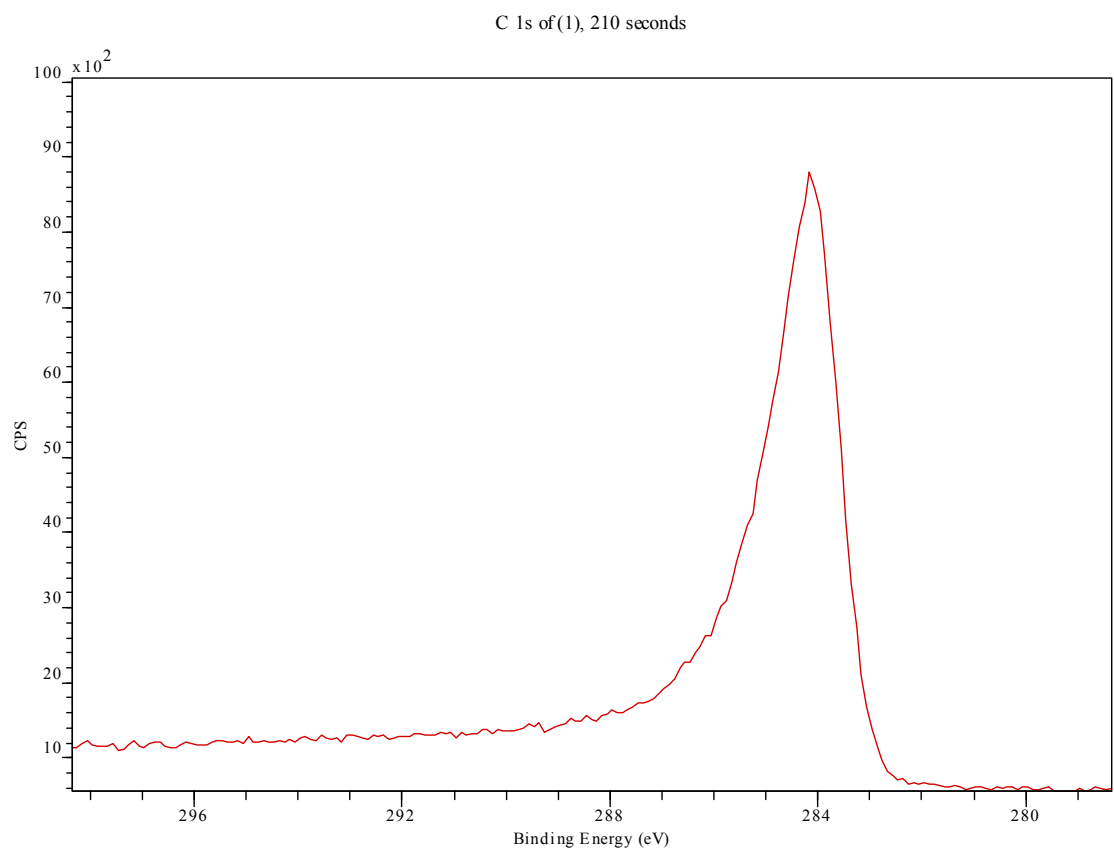












XPS spectroscopy of [Rh(3,5-(CF₃)₂-Pz)(PMe₃)₃] (**3**) using argon as the carrier gas

